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**Judul Paper: Photochemical Oxidation Process of Copper from Electroplating Wastewater: Process Performance and Kinetic Study**

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## ORIGINAL PAPER

Article

# Photochemical Oxidation Process of Copper from Electroplating Wastewater: Process Performance and Kinetic Study

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**Abstract:** An investigation of the process of ozone combined with ultraviolet radiation has been carried out in order to establish the kinetics for photochemical oxidation of copper (Cu) from electroplating wastewater. The effects of operating parameters, including initial Cu concentration, ozone dosage, UV irradiation intensity, and pH value on the photochemical oxidation of Cu have been studied comprehensively. The Cu concentration during the reaction was identified using Atomic Absorption Spectroscopy (AAS) method. The solid product was analyzed using X-ray Diffraction (XRD) and Scanning Electron Microscope–Energy Dispersive X-ray (SEM–EDX) methods. It was found that the UV–Ozone process has high performance on Cu removal compared to UV and Ozone processes due to the high production rate of HO• radicals. It was also found that solid product from UV–Ozone process was CuO monoclinic crystal phase. The initial Cu concentration, ozone dosage, and pH value were significantly affected the Cu removal efficiency. On the other hand, the UV irradiation intensity was not significant; however, it has responsibility in promoting the ozone photolysis. The kinetics model for the photochemical oxidation of Cu was established following the first-order kinetic model. Furthermore, the reaction mechanism was also developed.

**Keywords:** photochemical oxidation; Cu; kinetics; ozone; ultraviolet irradiation; advanced oxidation process

## 1. Introduction

Heavy metals have become a global issue of environmental and public health concern because of their toxicity and bioaccumulation in the human body and food chain [1]. The effects of urbanization and industrialization cause an increase in heavy metal pollution to the environment [2]. High toxicity and non-biodegradability of heavy metals caused a number of environmental problems [3]. The accumulation of heavy metals in the atmosphere is responsible for both natural and anthropogenic activities [4]. Copper (Cu), as an essential trace element, is required by biological systems for the activation of some enzymes during photosynthesis. However, at higher concentrations, it shows harmful effects on the human body. Continuous exposure may lead to kidney damage and even death. Cu is also toxic to a variety of aquatic organisms even at very low concentrations. Mining, metallurgy and industrial applications are the major sources of Cu exposure in the environment [5].

There were several techniques for the treatment of industrial wastewater containing heavy metals, including chemical precipitation, ion exchange, coagulation-flocculation, flotation, membrane filtration, electrochemical treatment, magnetic separation and purification, biosorption, and

nanotechnology [6]. Advanced oxidation processes (AOPs) are promising, efficient, and environmentally friendly methods for the removal of wastewater contaminants [7]. The AOPs can be photochemical AOP, sonochemical AOP, and electrochemical AOP [7]. The basic principles of AOPs are the in situ generations of hydroxyl radicals ( $\text{HO}\bullet$ ) during the oxidation process. The hydroxyl radicals can be produced from hydrogen peroxide ( $\text{H}_2\text{O}_2$ ), ozone, photo-catalysis, or oxidants in combination with ultraviolet (UV) radiation [8].

Ozone is an active oxidant which is commercially available and widely used in municipal water treatment and wastewater treatment. Besides having the ability as an oxidizing agent, wastewater treatment with ozone is an environmentally friendly method. The pollutants such as color, odor, and microorganisms are oxidized directly without generating harmful chlorinated by-products or substantial residues [9]. In order to increase the effectivity of the ozonation process, it is necessary to combine the ozone process with another process which can increase the reaction efficiency between ozone and pollutant. The promising process is the combination of ozone and UV irradiation that could enhance the production of hydroxyl radicals ( $\text{HO}\bullet$ ) as the main oxidant compounds in AOP [10]. The combination of UV-Ozone process has been reported as a promising process for  $\text{HO}\bullet$  radical formation [11–13]. Therefore, the oxidation process could be accelerated. Based on this characteristic, the combination of UV-Ozone process has a potential option for wastewater treatment [14].

Since the UV-Ozone process has high beneficial result in wastewater treatment; therefore, it is important to investigate this process comprehensively. However, the utilization of the UV-Ozone process for Cu removal from electroplating wastewater is still limited. Therefore, the comparison of UV, Ozone, and UV-Ozone processes is investigated in this study. Furthermore, the effect of several operating parameters, including initial Cu concentration, ozone dosage, UV irradiation intensity, and pH value, on the Cu removal process from electroplating wastewater through photochemical (UV-Ozone) oxidation process is also comprehensively studied. In addition, the kinetic study of this process is important for scale-up processing. The study of the kinetics of wastewater treatment with a combination of UV-Ozone process for organic compound degradation has been investigated by several previous researchers [15,16]. However, to the best of our knowledge, there are no previous studies concerning the kinetic study in Cu from electroplating wastewater by UV-Ozone process. In this study, the kinetic models of the Cu removal process are investigated in order to determine the order of the kinetic rate. Furthermore, the relation of operating parameters with the kinetic parameter is also investigated comprehensively.

## 2. Materials and Methods

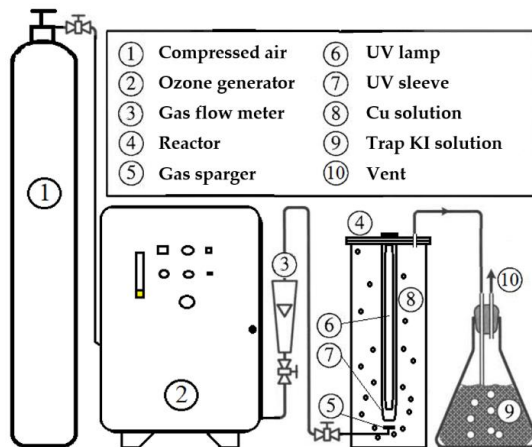
### 2.1. Materials

This experiment was carried out using synthetic wastewater with an initial copper concentration of 145.73 mg/L. The initial concentration of samples was prepared based on the composition of copper from industrial electroplating wastewater which located at Juwana, Pati, Central of Java Indonesia. Synthesized wastewater with varying copper concentrations (145.73 mg/L; 72.86 mg/L; and 36.9 mg/L) was prepared by dissolving the corresponding amount of  $\text{CuSO}_4\cdot 5\text{H}_2\text{O}$  (>98%, Merck) in deionized (DI) water. The initial pH value of the solution was adjusted using HCl (37%, Merck) and NaOH (>98%, Merck).

### 2.2. Experimental system set-up

The experimental study on photochemical oxidation of copper by ozone combined with UV irradiation was conducted in a bubble column reactor made of borosilicate glass. The reactor was equipped with a low-pressure mercury UV Light (Philips-TUV 8 Watt, main emission line at 253.7 nm). Ozone gas generated from ozone generator type dielectric barrier discharge (Dipo Technology, Diponegoro University) connected to reactors UV-Ozone (**Figure 1**). The ozone dosage was varied at 5, 10, and 15 mg/h. The UV-Ozone photoreactor was performed under a semi-batch condition reaction. The reactor was an open-top cylindrical tank with a fixed top suspension with a low-pressure mercury

UV Light. UV irradiation intensity was varied at 20, 40, and 60 mW/cm<sup>2</sup>. The UV irradiation intensity was adjusted by varying the number of UV light. A fritted glass diffuser was placed at the bottom of the reactor to allow the continuous injection of ozonized gas. Ozone was produced from the air which flows into the ozone generator. The reaction was adjusted for different time periods (i.e. 10, 20, 30, 40, 50, 60 min) and initial pH (3, 6, 8, and 10) during UV-Ozone treatment. All oxidation reaction processes were conducted at room temperature and atmospheric pressure. The initial pH was adjusted using NaOH and HCl solutions.



**Figure 1.** Schematic diagram of UV-Ozone treatment equipment

### 2.3. Analytical Methods

A pH meter analyzer (EZDO PH-5011A) was used during the procedure for assessing the pH of the response solution. An Atomic Absorption Spectroscopy (AAS – Quantachrome series 11.0) was used to analyzed Cu concentration and wastewater samples. The solid product was also analyzed using X-ray Diffraction (XRD) (Shimadzu 7000) method. The Cu K $\alpha$  radiation ( $\lambda = 1.54 \text{ \AA}$ ) was operated at 30 mA and 30 kV. The diffraction patterns were generated at  $2\theta$  angle ranges of  $20\text{--}70^\circ$  with a scanning speed of  $4^\circ \text{ min}^{-1}$ . The surface morphology and metal oxide composition of the solid product was analyzed using Scanning Electron Microscope–Energy Dispersive X-ray (SEM–EDX) (SEM-EDX JEOL JSM-6510LA) method. The removal efficiency was calculated using Equation (1), when  $\eta$  is the Cu removal efficiency (%),  $C_0$  is the initial Cu concentration (mg/L) and  $C_t$  (mg/L) is the Cu concentration at time  $t$ .

$$\eta(\%) = \frac{C_0 - C_t}{C_0} \times 100 \quad (1)$$

## 3. Results and Discussions

### 3.1. Comparison of UV, Ozone and combination UV–Ozone

In order to study the different effects of UV, Ozone, and UV–Ozone combination processes on Cu removal from electroplating wastewater, these three processes are compared. The result is shown in **Figure 2**.

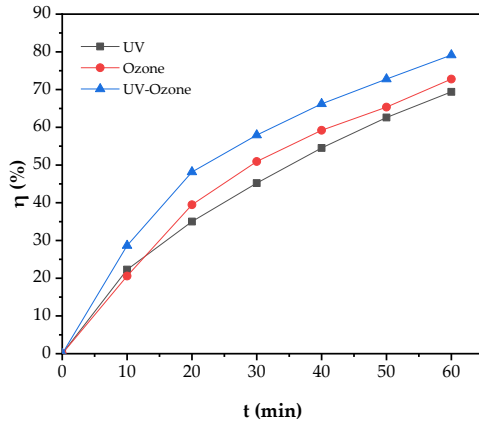


Figure 2. Comparison of UV, Ozone and UV-Ozone combination processes

Figure 2 depicted the comparison of UV, Ozone, and combined UV-Ozone treatment on Cu removal efficiency from electroplating wastewater. As can be seen, at 60 minutes of reaction, the Cu removal efficiency obtained from the UV irradiation process is 69.08%, while the Cu removal efficiency obtained from Ozone treatment is 72.64%. Interestingly, the Cu removal efficiency can be increased up to 78.8% when the UV and Ozone processes are combined. This high Cu removal efficiency can be obtained by the enhancement of hydroxyl radicals ( $HO\bullet$ ) during the combination of UV and Ozone processes. As reported by Halena et al. [10], the combination of UV irradiation and ozone could enhance the production of hydroxyl radicals; therefore the oxidation process could be accelerated. Furthermore, it is suggested that the combination of UV irradiation and Ozone treatment can increase the Cu removal efficiency in the Cu removal process from electroplating wastewater. It is true since the mechanism of Cu oxidation through AOP is initiated by the presence of  $HO\bullet$  radicals. Equations (2) and (3) represent the oxidation process of Cu through AOP. As can be seen in Equation (2), the  $Cu^{2+}$  ion is oxidized by  $HO\bullet$  radicals producing solid  $CuO$  and water molecules.



Based on Equation (2), the important thing in Cu removal through AOP is the presence of  $HO\bullet$  radicals. Therefore, it is suggested that the process of producing more  $HO\bullet$  radicals is the preferred process. As can be seen in Figure 2, the Cu removal efficiency obtained by the UV irradiation process is the lowest compared to the other processes. It is true since the UV irradiation process without the presence of ozone in the system is only produces  $HO\bullet$  radicals through the photolysis of  $H_2O$  molecule [12,17]. The photolysis of the  $H_2O$  molecule by UV irradiation is shown in Equation (4) [12]. The other possible mechanisms in  $HO\bullet$  production through the UV irradiation process are shown in Equations (5) and (6) [18].

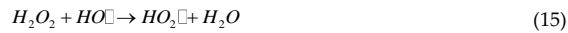


For the Ozone treatment, as depicted in Figure 2, the Cu removal efficiency is higher than the Cu removal efficiency obtained by the UV irradiation process. This is due to the fact that the Cu oxidation

through Ozone treatment can be initiated by HO• radicals and directly oxidized by the ozone molecule (Equation (3)). These two reactions occurred in Ozone treatment, therefore; the Cu removal efficiency obtained by Ozone treatment is higher than obtained by UV treatment. The chemical reaction of HO• radicals formation through Ozone treatment is shown in Equation (7) [12].



As mentioned before, the highest Cu removal efficiency is obtained by the UV-Ozone process due to the high HO• radical formation during the combination of the UV irradiation process and the Ozone process. Besides, the presence of ozone can also increase the oxidation process due to the direct oxidation process. The formation of HO• radicals in the UV-Ozone process has been widely reported. Some proposed HO• radical formation during UV-Ozone process follow the reaction mechanism as described in Equation (8-10) [12,19]:



As can be seen, in the UV-Ozone process, an additional oxidant, H<sub>2</sub>O<sub>2</sub>, is generated through O<sub>3</sub> photolysis (Equation (8)) [12]. O<sub>3</sub> reacts with H<sub>2</sub>O to form H<sub>2</sub>O<sub>2</sub> under UV irradiation. This oxidant can produce more HO• radicals. H<sub>2</sub>O<sub>2</sub> absorbs UV light to generate HO• radicals. By this fact, the Cu removal efficiency can be increased following the reaction shown in Equation (2) in the combination of UV and Ozone process. This finding is in accordance with several previous studies. In dyehouse wastewater subjected to the combination of UV-Ozone treatment, a significant color reduction was obtained up to 98.3% [13]. For another reason, Bes-Piá et al. [11] studied the UV-Ozone process for textile wastewater treatment. They reported that the combination of UV irradiation with ozone could significantly reduce the operating time to reach the same COD removal efficiency.

### 3.2. Characterisation of the solid product

As reported in the previous section (Section 3.1), the UV-Ozone process has the highest Cu removal efficiency compared to the other processes. The Cu removal through this process produces solid product which is proposed as CuO, as shown in Equation (2) and (3). In order to prove that the solid product is CuO, the solid product was analyzed. **Figure 3** shows the XRD pattern of the solid product obtained from the UV-Ozone process. Based on **Figure 3**, the characteristic peaks appear at 2θ of 32.54°, 35.56°, 38.74°, 48.68°, 53.62°, 58.16°, 61.62°, 66.12° and 68.12°, respectively. These peaks correspond to the CuO (Tenorite phase) according to the JCPDS card number 96-900-8962. These also indicate that the formation of monoclinic crystal structure [20]. On the other hand, several studies reported that two peaks at 2θ = 35.6° [002] and 2θ = 38.8° [111] observed in the diffraction patterns are ascribed to the formation of the CuO (space group C2/c) monoclinic crystal phase [21,22]. In this study, these peaks appear at 2θ = 35.56° and 2θ = 38.74°. Therefore, it is confirmed that the solid product produced from UV-Ozone process is CuO in monoclinic crystal phase.



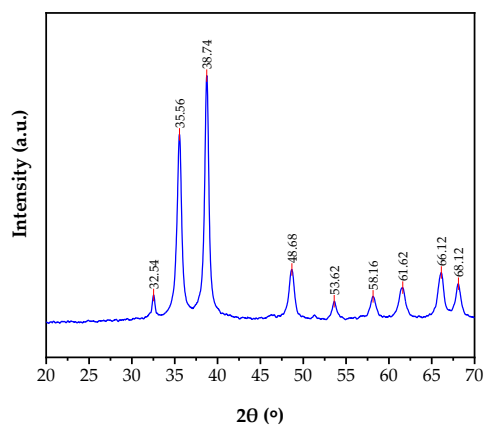
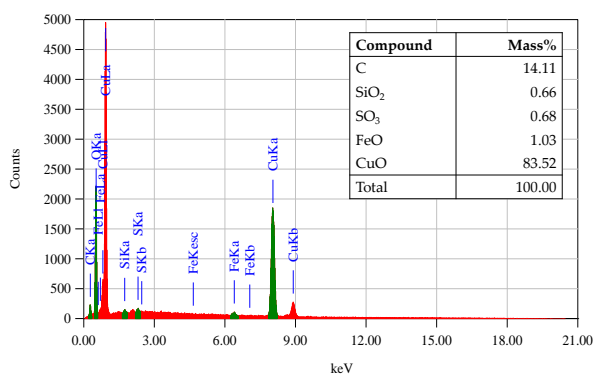
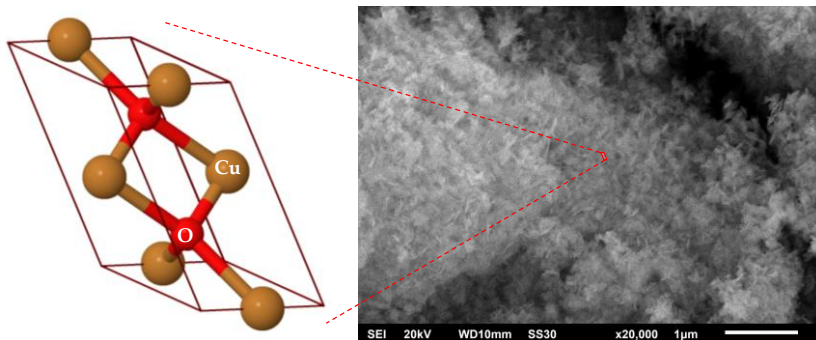


Figure 3. XRD pattern of the solid product obtained from UV-Ozone process



(a)



(b)

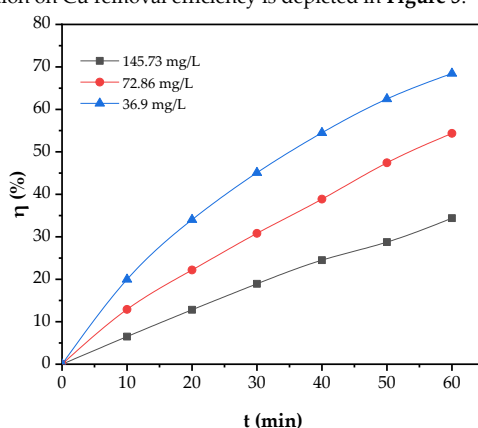
Figure 4. Composition of metal oxide in the solid product (a) and surface morphology (right) and crystal structure model (left) of the solid product (b).

The morphology and the metal oxide composition of the solid product from UV-Ozone process are identified using SEM analysis. Based on the result of SEM-EDX analysis (**Figure 4(a)**), it is confirmed that the most metal oxide presence in the solid product is CuO. The CuO content detected by SEM-EDX analysis in the solid product is 83.52%. The other components detected may be produced from the impurities in the wastewater. However, this fact confirmed that the solid product is CuO. **Figure 4(b)** is the appearance of the solid product surface (right) and the model of the CuO monoclinic crystal structure (left). As can be seen, the surface morphology of the CuO is agglomerated nanorods. Manyasree et al. [23] reported that the surface morphology the CuO nanoparticle which was synthesized from copper sulfate and sodium hydroxide through coprecipitation process is flower-shaped structure.

### 3.3. The effect of operating parameters

#### 3.3.1. Effect of initial concentration

In order to study the effect of the initial Cu concentration, the photochemical oxidation process was conducted with the variation of the initial Cu concentration. The initial Cu concentration was varied at 145.73, 72.86, and 36.9 mg/L. The monitored parameter is the Cu removal efficiency. The effect of initial Cu concentration on Cu removal efficiency is depicted in **Figure 5**.



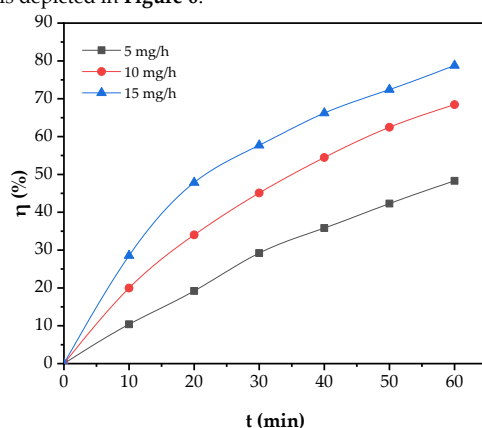
**Figure 5.** Effect of initial Cu concentration on Cu removal efficiency through photochemical process

As can be seen in **Figure 5**, the Cu removal efficiency is significantly affected by the initial Cu concentration. During the oxidation process for 60 minutes, the Cu removal efficiency obtained at the initial Cu concentration of 145.73 mg/L is 34.39%, the Cu removal efficiency obtained at the initial Cu concentration of 72.86 mg/L is 54.36%, while the Cu removal efficiency obtained at the initial Cu concentration of 36.9 mg/L is 68.46%. Based on these results, it is suggested that the initial Cu concentration has a significant effect on the Cu removal efficiency in the Cu removal process from electroplating wastewater. Furthermore, the Cu removal efficiency decreases significantly with the increase in the initial Cu concentration from 36.9 mg/L to 145.73 mg/L. The decrease in Cu removal efficiency at high initial Cu concentration is due to the presence of a high amount of hydroxyl radical scavengers. When the initial Cu concentration is high, the photochemical oxidation process is overloaded. As a result, the Cu in the solution competes with each other during the oxidation reaction process [24]. On the other hand, in the UV irradiation process, the permeation of photons is reduced at high solution concentration; therefore, the concentration of hydroxyl radical produced is low [24]. Therefore, the oxidation of Cu decreases at high initial Cu concentration. This finding is in accordance with several previous studies in AOP. Hassan et al. [25] reported that the decolorization of Direct

Yellow 50 dye in seawater through the UV-Ozone process was highly affected by the initial dye concentration which the decolorization rate decreased by increasing the dye concentration. Dai et al. [26] also reported a similar finding in the degradation of carbamazepine in water through AOP. They reported that the degradation percentage of carbamazepine decreased from 34% to 13% with the increase in the initial carbamazepine concentration from 4.2  $\mu\text{M}$  to 42.3  $\mu\text{M}$ . Jing et al. [27] also reported that the initial aniline concentration affected the aniline degradation process through ozonation. They reported that aniline degradation decreased with the increase in the initial aniline concentration due to the overloaded of ozonation process.

### 3.3.2. Effect of ozone dosage

In this study, the effect of ozone dosage on the Cu removal process through the photochemical oxidation process is studied by varying the ozone dosage. The ozone dosage was varied at 5, 10, and 15 mg/h. The Cu removal efficiency was monitored to study this matter. The effect of ozone dosage on Cu removal efficiency is depicted in **Figure 6**.



**Figure 6.** Effect of ozone dosage on Cu removal efficiency through a photochemical process

As can be seen in **Figure 6**, the Cu removal efficiency increases significantly with increasing the ozone dosage. At 60 min reaction, the Cu removal efficiency obtained at ozone dosage of 5 mg/h is 48.31%, the Cu removal efficiency obtained at ozone dosage of 10 mg/h is 68.46%, while the Cu removal efficiency obtained at ozone dosage of 15 mg/h is 78.80%. Based on these results, it is suggested that the Cu removal efficiency in Cu removal from electroplating wastewater through the photochemical oxidation process is highly affected by the ozone dosage. As the increase in ozone dosage, the Cu removal efficiency increases. It is true since in the ozonation process, the oxidation of Cu can occur through two different mechanisms, i.e. oxidation by  $\text{HO}\cdot$  radicals (Equation (2)) and direct oxidation by ozone (Equation (3)). As reported by Wang et al. [28], in the ozone-based oxidation process, there are two methods, namely indirect reaction of free radicals and direct reaction.

Pertaining to the effect of ozone dosage on  $\text{HO}\cdot$  radical formation, when ozone dosage increases, more  $\text{HO}\cdot$  radicals are formed. Under UV irradiation,  $\text{H}_2\text{O}_2$  can be formed through the reaction of ozone with  $\text{H}_2\text{O}$  (Equation (8)). Furthermore, this  $\text{H}_2\text{O}_2$  molecule absorbs the UV light to generate the  $\text{HO}\cdot$  radicals (Equation (9)) [19]. Ozone molecules also can react with  $\text{H}_2\text{O}_2$  molecules to produce  $\text{HO}\cdot$  radicals. Besides, the ozone also can also directly react with  $\text{H}_2\text{O}$  to generate  $\text{HO}\cdot$  radicals (Equation (7)). Then, Cu is oxidized by  $\text{HO}\cdot$  radicals. Therefore, the photochemical oxidation rate of Cu increases with the increase in ozone dosage. As a comparison, Wang et al. [28] reported that the decomplexation of electroplating wastewater by the ozone-based oxidation process increased with the increase in ozone dosage. Ren et al. [19] reported that the removal efficiency of polyacrylamide through the

photochemical oxidation process increased with the increase in ozone dosage. Guo et al. [29] also reported the same result in the degradation process of sulfadiazine in water by the UV-Ozone process.

### 3.3.3. Effect of UV irradiation intensity

In order to study the effect of UV irradiation intensity on Cu removal from electroplating wastewater, the photochemical process was conducted by varying the UV irradiation intensity. The UV irradiation intensity was varied at 20, 40, and 60 mW/cm<sup>2</sup>. Figure 7 shows the result of the effect of UV irradiation intensity on Cu removal efficiency.

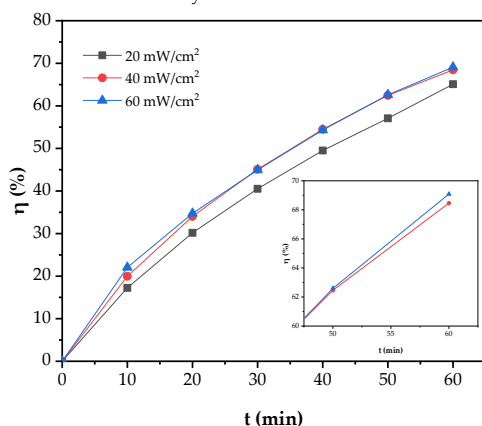


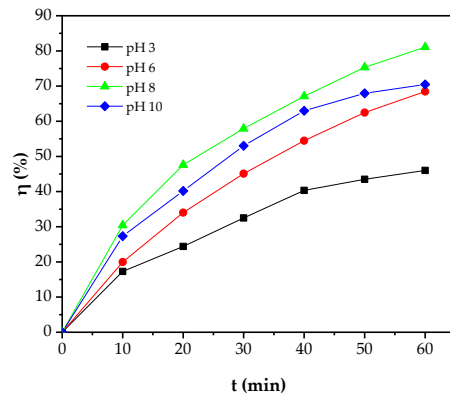
Figure 7. Effect of UV irradiation intensity on Cu removal efficiency through photochemical process

As shown in Figure 7, at 60 minutes reaction, the Cu removal efficiency obtained at a UV irradiation intensity of 20 mW/cm<sup>2</sup> is 65.09%, the Cu removal efficiency obtained at UV irradiation intensity of 40 mW/cm<sup>2</sup> is 68.46%, while the Cu removal efficiency obtained at UV irradiation intensity of 60 mW/cm<sup>2</sup> is 69.08%. It can be concluded that the Cu photochemical oxidation rate slightly increases with the increase in UV radiation intensity. The Cu removal efficiency slightly increases for UV irradiation of 20 to 40 mW/cm<sup>2</sup>. Furthermore, the Cu removal efficiency remains unchanged for UV irradiation intensity of 40 to 60 mW/cm<sup>2</sup>.

The increase in Cu removal efficiency with the increase in UV irradiation intensity is due to the high possibility to produce HO• radicals at high UV irradiation intensity. The possible process of HO• radical formation during UV irradiation is the photolytic dissociation of water by UV irradiation at a wavelength of 254 nm [30]. However, this process is still unclear since some studies reported that the photolytic dissociation of water to HO• radicals is only can be conducted at a wavelength of less than 242 nm. Deng and Zhao [12] claimed that this process occurs at a wavelength of less than 242 nm. Furthermore, Jin et al. [17] reported that the HO• radicals could be formed through irradiation on liquid water by UV light in the range of 150 – 200 nm. As the UV irradiation wavelength used in this study is around 253.7 nm, the increase in Cu removal efficiency with the increase in UV irradiation intensity from 20 to 40 mW/cm<sup>2</sup> is attributed to the formation of HO• radicals through ozone photolysis producing H<sub>2</sub>O<sub>2</sub> (Equation (8)). However, high UV irradiation intensity in the ozonation process is not good. It is true since, at high UV irradiation intensity, ozone molecule could be degraded to oxygen [31]. Therefore, the formation of HO• radicals is low at high UV irradiation intensity. Furthermore, it is suggested that the unchanged Cu removal efficiency at UV irradiation intensity of 60 mW/cm<sup>2</sup> is due to the degradation of the ozone molecule resulting in the low formation of HO• radicals.

### 3.3.4. Effect of pH

The efficiency of AOP can be influenced by various factors, such as the pH of the solution [32–34]. In order to study the effect of pH on Cu removal process from electroplating wastewater through photochemical oxidation process, the pH of solution was varied at 3, 6, 8 and 10. The result is depicted in **Figure 8**.



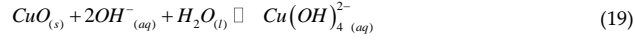
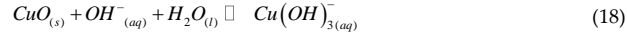
**Figure 8.** Effect of pH on Cu removal efficiency through photochemical process

As can be seen in **Figure 8**, at 60 minutes reaction, the Cu removal efficiency obtained at pH of 3 is 46.02%, the Cu removal efficiency obtained at pH of 6 is 68.46%, the Cu removal efficiency obtained at pH of 8 is 80.09%, while the Cu removal efficiency obtained at pH of 10 is 70.46%. It can be seen that the highest Cu removal efficiency is obtained at a pH of 8. Hence, it can be concluded that the photochemical oxidation of Cu from electroplating wastewater increases with the increase in pH from 3 to 8, then it decreases with a further increase in pH to 10.

The increase in Cu removal efficiency with the increase in pH value is attributed to the high rate of HO• radical formation at high pH conditions. As reported by Muniyasamy et al. [34], in the oxidation process, pH influences the process by altering the chemical nature of ozone. At low pH conditions (acidic conditions), the decomposition of the ozone molecule to produce HO• radicals is relatively slow [35]. It was reported that the decomposition rate of ozone was sluggish below the pH of 4 [36]. Furthermore, ozone tends to remain in the molecular state at acidic conditions; however, ozone can react directly as ozone radical with the contaminants at alkaline conditions [33,37]. Therefore, the Cu removal efficiency is low at low pH value. Furthermore, the higher the pH value, the higher the Cu removal efficiency. This tendency is attributed to the high formation of HO• radicals at the alkaline conditions. It was reported that the decomposition rate of ozone in water is better at higher pH values [38]. At alkaline conditions, ozone is unstable and rapidly decomposes into HO• radical [34,35]. The HO• radical formation through ozone decomposition occurs as follows:



As can be seen in Equation (16) and (17), the HO• radical which is the primary oxidant in indirect oxidation [34] is produced at high pH level represented as OH<sup>-</sup>. Therefore, the Cu removal efficiency increases with the increase in pH value since the HO• radical formation is favored at a high pH level. However, the Cu removal efficiency decrease at a pH of 10. At higher pH value, CuO can dissolve to the aqueous phase due to the formation of soluble hydroxy and hydroxide complexes [39]. Therefore, Cu removal efficiency decreases. The possible dissolution mechanism of CuO at high pH value was proposed by Khan et al. [39] as follows:



### 3.4. Kinetic study

#### 3.4.1. Determination of the kinetic rate order

Three classical kinetic models are proposed to describe the Cu removal process and to determine the order or kinetic rate. These kinetic models include first-order model, second-order model, and pseudo-first-order model. The compatibility of these models is evaluated by the  $R^2$  value as reported elsewhere [40]. In this work, the kinetic study of Cu removal from electroplating wastewater is considered for various initial Cu concentration ( $C_0$ ), ozone dosage ( $C_{O_3}$ ), UV irradiation intensity ( $I_{uv}$ ), and initial pH condition.

In this advanced oxidation process for Cu removal from electroplating wastewater, the mass conservation of Cu in the process can be generally expressed as:

$$-\frac{dC_t}{dt} = (-r) \quad (20)$$

where  $C_t$  (mg/L) is the concentration of Cu at time  $t$  (min),  $(-r)$  (mg/L.min) is the rate of Cu removal. For first order model ( $-r=k_1C_t$ ), integration of Equation (20) at the initial concentration of  $C_0$ , gives:

$$-\ln\left(\frac{C_t}{C_0}\right) = k_1t \quad (21)$$

where  $k_1$  (1/min) is the kinetic rate constant for first order. Further simplification of Equation (21) will give the time-dependent concentration of Cu (Equation (22)).

$$C_t = C_0e^{-k_1t} \quad (22)$$

For second-order model ( $-r=k_2C_t^2$ ), the integration of Equation (20) will give:

$$\frac{1}{C_t} = k_2t + \frac{1}{C_0} \quad (23)$$

where  $k_2$  (L/mg.min) is the kinetic rate constant of the second-order model. For the pseudo-first-order model ( $-r=k_p(C_0 - C_t)$ ), the time-dependent concentration of Cu through the integration of Equation (20) is obtained as:

$$C_t = C_e + (C_0 - C_e)e^{-k_p t} \quad (24)$$

where  $C_e$  (mg/L) is the concentration of Cu at equilibrium condition and  $k_p$  (1/min) is the kinetic rate constant of pseudo-first-order model.

The kinetic parameters were determined using the least-square method. As can be seen, the obtained equation for first-order and second-order kinetic models (Equations (21) and (23)) are linear equations. Therefore, the kinetic parameters ( $k_1$  and  $k_2$ ) can be obtained from the linear plot relating to these equations using the linear regression method. However, the equation derived from the pseudo-first-order kinetic model is not linear. Therefore, the kinetic parameters of the pseudo-first-order kinetic model ( $C_e$  and  $k_p$ ) are calculated using a non-linear regression method. On the other hand, to measure the goodness of the kinetic models proposed, the squared-correlation coefficient,  $R^2$ , was used as the parameter [40,41]. The obtained kinetic parameters and  $R^2$  values for first-order, second-order, and pseudo-first-order kinetic models are shown in **Table 1**.

As can be seen in **Table 1**, all proposed models fit the data as the  $R^2$  values are close to unity. However, compared to the other proposed models, the  $R^2$  value of the second-order model is far enough from unity. Besides, the values of  $R^2$  obtained are not uniform for all data. Therefore, it is suggested that the second-order model is excluded as the proposed model to describe the kinetic rate of Cu removal. Hence, the first order and pseudo-first-order models are then considered as the most suitable proposed models to describe the kinetics of Cu removal. Considering the  $R^2$  values of the first order and pseudo-first-order models, both these two models have high goodness in describing the kinetic rate of Cu removal. However, at the initial Cu concentration,  $C_0$ , of 145.73 and 72.86 mg/L, the value of the equilibrium concentrations,  $C_e$ , obtained are zero. It indicates that at a high initial concentration of Cu in the wastewater, the kinetic rate will be increased. Furthermore, some of the  $C_e$  values are relatively low. In some cases, the theoretical value of  $C_e$  might be negative when the pseudo-first-order kinetic model is forcibly used [41]. In those cases, the pseudo-first-order model cannot be used to describe the kinetic rate. Obviously, if the value of the equilibrium concentration is zero or low enough, the pseudo-first-order model gets back to the first-order model [40,41]. Therefore, it is suggested that the most suitable model to describe the kinetic rate of Cu removal from electroplating wastewater through the photochemical oxidation process, combined UV-ozone process, is the first-order model.

**Table 1.** Kinetic parameters of the first order, second-order and pseudo-first-order models

$C_0$ (mg/L)	$C_{O_3}$ (mg/h)	$I_{UV}$ (mW/cm <sup>2</sup> )	pH	Kinetic parameters						
				First order		Second order		Pseudo-first order		
				$k_1$ (1/min)	$R^2$	$k_2$ (L/mg.min)	$R^2$	$k_p$ (1/min)	$C_e$ (mg/L)	$R^2$
145.73	10	40	6	0.0069	0.9997	$5.673 \times 10^{-5}$	0.9921	0.0069	0.000	0.9994
72.86	10	40	6	0.0128	0.9993	$2.451 \times 10^{-4}$	0.9678	0.0127	0.000	0.9983
36.9	10	40	6	0.0196	0.9995	$8.898 \times 10^{-4}$	0.9707	0.0237	3.769	0.9995
36.9	5	40	6	0.0111	0.9998	$3.972 \times 10^{-4}$	0.9875	0.0116	1.223	0.9993
36.9	15	40	6	0.0267	0.9959	$1.480 \times 10^{-3}$	0.9624	0.0395	5.528	0.9979
36.9	10	20	6	0.0173	0.9996	$7.407 \times 10^{-4}$	0.9609	0.0188	1.850	0.9990
36.9	10	60	6	0.0198	0.9989	$9.031 \times 10^{-4}$	0.9654	0.0252	4.663	0.9969
36.9	10	40	3	0.0116	0.9847	$4.160 \times 10^{-4}$	0.9790	0.0330	12.126	0.9940
36.9	10	40	8	0.0282	0.9980	$1.650 \times 10^{-3}$	0.9359	0.0376	4.170	0.9962
36.9	10	40	10	0.0226	0.9904	$1.100 \times 10^{-3}$	0.9909	0.0381	7.725	0.9970

The kinetic study of Cu removal using an advanced oxidation process has been widely reported. However, the kinetic study of Cu removal using the photochemical oxidation process, UV-ozone process, is still limited. The most-reported process is the electrochemical/electrocoagulation process. Al-Shannag et al. [40] reported that the electrocoagulation of heavy metals from wastewater, including Cu, followed a pseudo-first-order model. Using the same method, Vasudevan and Lakshmi [42] reported that the electrocoagulation of Cu from water follows the second-order model. Furthermore, Khattab et al. [43] reported that Cu removal through the electrochemical process follows the first-order kinetic model.

#### 3.4.2. The effect of operating parameters on kinetic rate constant

The kinetic rate behavior of Cu removal using the photochemical oxidation process, combined UV-ozone process, follows the first-order kinetic model as reported in the previous section (Section 3.3.1). The value of the kinetic rate constant of the first-order model,  $k_1$ , is presented in **Table 1**. As can be observed, the value of  $k_1$  is varied as the variation of operating parameters, including  $C_0$ ,  $C_{O_3}$ ,  $I_{UV}$ , and pH. The value of  $k_1$  increases with a decrease in  $C_0$ . Furthermore, the value of  $k_1$  increases with the increase in  $C_{O_3}$ ,  $I_{UV}$ , and pH. However, at a pH of 10, the value of  $k_1$  decreases. Even though, these phenomena indicate that the value of the observed  $k_1$  is affected by the operating parameters. This is in accordance with some previous studies that the kinetic rate constant of the advanced oxidation process, especially the UV-ozone process, is affected by the operating parameters [19,44]. The operating

parameters-dependent of the kinetic rate constant can be mathematically written as Equations (25) and (26) where  $\varepsilon$  is the pre-exponent constant while  $a, b, c$  and  $d$  are the exponent constant characteristic of  $C_0, CO_3, I_{UV}$ , and pH, respectively. The linear form of Equation (26) is shown as Equation (27).

$$k_1 = f(C_0, C_{O_3}, I_{UV}, pH) \quad (25)$$

$$k_1 = \varepsilon C_0^a C_{O_3}^b I_{UV}^c pH^d \quad (26)$$

$$\ln k_1 = \ln \varepsilon + a \ln C_0 + b \ln C_{O_3} + c \ln I_{UV} + d \ln pH \quad (27)$$

Based on Equation (27), the value of  $\varepsilon, a, b, c,$  and  $d$  can be obtained using multiple regression analysis which also has been used elsewhere [44]. However, the value of  $k_1$  at a pH of 10 is not included in this calculation because it doesn't follow the tendency. **Table 2** shows the result of the multiple regression analysis. As can be seen, the *P-value* of the coefficients obtained for each parameter is lower than 0.05. This indicates that the coefficients obtained are significant. However, the *P-value* of  $\ln I_{UV}$  coefficient is higher than 0.05 which indicates that this coefficient is not significant. **Table 3** shows the result of the analysis of variance (ANOVA) of the multiple regression analysis. As can be observed, the value of multiple R,  $R^2$  and adjusted  $R^2$  is close to unity. These indicate that the obtained regression equation fits the data. Furthermore, the obtained *F-value* (113.4928) is higher than the *F-table* or theoretical *F-value*. The theoretical *F-value* [ $F_{0.05(4,7)}$ ] is 6.09.

**Table 2.** Multiple regression analysis result

Parameters	Coefficients	Standard Error	<i>P-value</i>
Intercept	-5.1661	0.3951	$3.5663 \times 10^{-6}$
$\ln C_0$	-0.7401	0.0441	$6.4919 \times 10^{-7}$
$\ln C_{O_3}$	0.8154	0.0778	$1.5626 \times 10^{-5}$
$\ln I_{UV}$	0.1441	0.0778	0.1064
$\ln pH$	0.8407	0.0839	$2.1105 \times 10^{-5}$

**Table 3.** Summary of the analysis of variance (ANOVA)

	<i>df</i>	<i>SS</i>	<i>MS</i>	<i>F</i>	<i>Significance F</i>
Regression	4	1.7467	0.4367	113.4928	$1.9188 \times 10^{-6}$
Residual	7	0.0269	0.0038		
Total	11	1.7736			
Multiple R	0.9924				
$R^2$	0.9848				
Adjusted $R^2$	0.9761				
Standard Error	0.0620				

Based on the result of the multiple regression analysis (**Table 2**), Equation (27) can be rewritten as Equation (28). Furthermore, Equation (26) can be rewritten as Equation (29) with the value of  $\varepsilon$  constant was calculated from the natural exponential of the intercept of Equation (28). The obtained value of  $k_1$  was then compared to the calculated value of  $k_1$  using Equation (29). The comparison of the observed  $k_1$  and calculated  $k_1$  is depicted in **Figure 9**. It is clear that the observed and calculated values of  $k_1$  are in good fit as the  $R^2$  is close to unity (0.9848). By combining the Equations (1), (22) and (29), the calculated Cu removal efficiency can be rewritten as Equation (30). Furthermore, the comparison of the Cu removal efficiency between the observed value and the calculated value is also depicted in **Figure 10**.



$$\ln k_1 = -5.1661 - 0.7401 \ln C_0 + 0.8154 \ln C_{O_2} + 0.1441 \ln I_{UV} + 0.8407 \ln pH \quad (28)$$

$$k_1 = (5.7068 \times 10^{-3}) C_0^{-0.7401} C_{O_2}^{0.8154} I_{UV}^{0.1441} pH^{0.8407} \quad (29)$$

$$\eta_{cal} (\%) = 100 - 100 \exp\left(- (5.7068 \times 10^{-3}) C_0^{-0.7401} C_{O_2}^{0.8154} I_{UV}^{0.1441} pH^{0.8407} t\right) \quad (30)$$

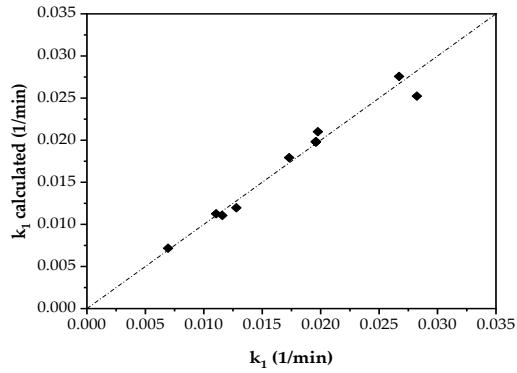
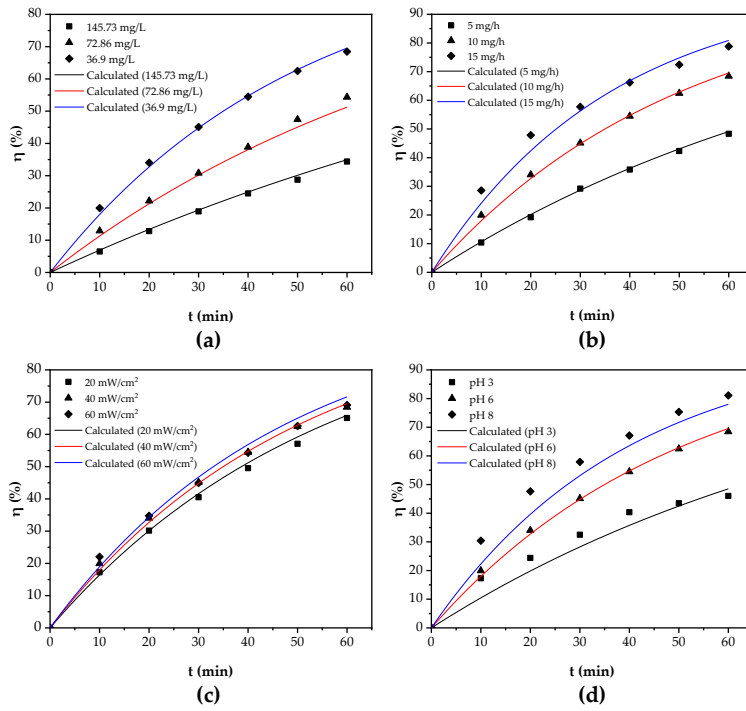


Figure 9. Comparison of observed and calculated value of  $k_1$

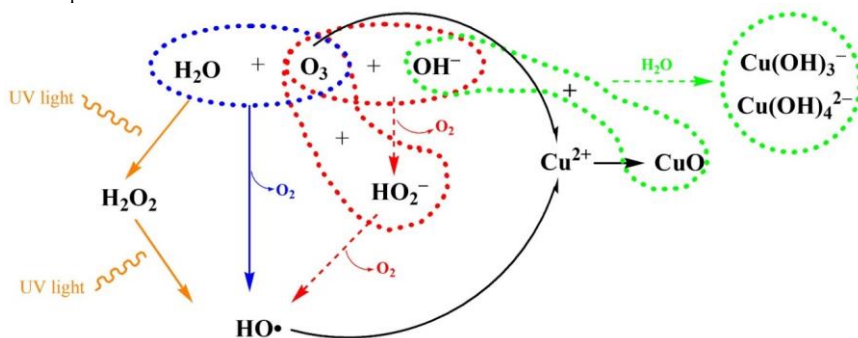


**Figure 10.** Comparison of data and calculated the Cu removal efficiency at (a) varied  $C_0$ , (b) varied  $C_{O_3}$ , (c) varied  $I_{UV}$ , and (d) varied pH.

As can be seen in **Table 2** and Equation (29), the exponent characteristic value of  $C_0$  is in a negative value. It indicates that the value of the initial Cu concentration is inversely proportional to the  $k_1$  value. This finding is in accordance with the finding of Ren et al. [19]. They reported that the initial concentration of polyacrylamide in the UV-Ozone process of polyacrylamide oxidation is inversely proportional to the kinetic rate constant value. Concerning the effect of UV and ozone treatment in this oxidation process, the value of the exponent characteristic of  $C_{O_3}$  and  $I_{UV}$  can be used to study this matter [44]. As can be seen, the exponent characteristic value of  $C_{O_3}$  is higher than  $I_{UV}$ . It is suggested that the ozone dosage is more significant in this oxidation process than UV irradiation intensity. This finding is in accordance with the previous study of the UV-Ozone process. The UV-Ozone process was conducted for  $\kappa$ -Carrageenan treatment and the result showed that the ozone dosage was more significant than UV irradiation intensity [44]. Furthermore, the value of the exponent characteristic of  $I_{UV}$  is low enough and it is close to zero. It indicates that the UV irradiation intensity is not significant enough for the Cu removal process from wastewater. In the case of the effect of pH on  $k_1$  value, it is clear that the pH has a significant effect on  $k_1$  value as the value of the exponent characteristic of pH is high. It is true because the metal oxidation process in an aqueous solution is affected by the presence of  $OH^-$  ions which can promote the formation of  $HO^\bullet$  radicals. On the other hand, the solubility of metal in aqueous solution is also affected by the pH value [39].

### 3.5. Proposed mechanism

Based on the explanation at previous sections, the mechanism of Cu removal from electroplating wastewater through UV-Ozone process is developed. **Figure 11** shows the proposed mechanism in this study. As reported in several studies, the oxidation through AOPs is initiated by the formation of  $HO^\bullet$  radical because the main oxidating agent is  $HO^\bullet$  radical [45,46]. Based on several findings obtained in this study (reported in the previous sections), the  $HO^\bullet$  radical formation takes place through three different steps. In **Figure 11**, these steps are represented in orange, blue, and red arrows. The orange arrows represent the  $HO^\bullet$  radical formation through UV-Ozone process. The blue arrow represents the direct ozonation of water producing  $HO^\bullet$  radicals releasing  $O_2$  molecules. Furthermore, the red arrows represent the ozone degradation producing  $HO^\bullet$  radicals in alkaline condition releasing  $O_2$  molecules. The red arrow is depicted in dash-line arrow type, this indicates that this process occurs in alkaline condition only due to the presence of  $OH^-$  ions. At acid condition, this process doesn't occur due to no  $OH^-$  ions presence.



**Figure 11.** Proposed mechanism of Cu removal from electroplating wastewater through UV-Ozone process

After the formation of HO• radicals occurred, the next step is oxidation process. This process is depicted in black arrows, includes direct and indirect oxidation since the oxidating agents in this UV-Ozone process are HO• radicals and ozone molecules. Both HO• radicals and O<sub>3</sub> react with Cu<sup>2+</sup> to form solid CuO. The oxidation process of Cu<sup>2+</sup> to CuO by HO• radicals is called indirect oxidation, while the oxidation process of Cu<sup>2+</sup> by O<sub>3</sub> molecules is called direct oxidation. Based on **Figure 11**, as the HO• radicals and O<sub>3</sub> molecules increase in the system, the CuO product produced increases. It means that the Cu removal from the electroplating wastewater increases. However, this CuO product can dissolve in alkaline condition. As can be seen in **Figure 11**, if the OH<sup>-</sup> ions is excessively present in the system, the CuO product will dissolve. This process is depicted as a dash-arrow in green indicating that this process occurs in alkaline condition only due to the presence of excessive OH<sup>-</sup> ions. The dissolution of CuO to the aqueous phase in alkaline condition is due to the formation of soluble hydroxy and hydroxide complexes [39].

Based on this proposed mechanism (**Figure 11**), it can be observed that the presence of ozone molecule is important in this oxidation process. The ozone molecules have role both to generate the HO• radicals and to oxidize the Cu directly. This is in accordance with the finding reported in the previous section (section 3.4) that the ozone dosage is significantly affected the kinetic rate. On the other hand, the presence of UV irradiation assists the ozone photolysis process to produce HO• radicals through the formation of intermediate oxidating agent, H<sub>2</sub>O<sub>2</sub>. Furthermore, the pH is also important in this mechanism. As can be seen in **Figure 11**, suitable alkaline condition accelerates the formation of HO• radicals. However, high alkaline condition has negative effect to the Cu removal process due to the CuO dissolution process in high alkaline condition. The excessive OH<sup>-</sup> ions catch the solid CuO to form soluble hydroxy and hydroxide complexes decreasing the Cu removal efficiency.

#### 4. Conclusions

The photochemical oxidation process of Cu from electroplating wastewater has been investigated. It is shown that the UV-Ozone process has high performance on Cu removal compared to UV and Ozone processes due to the high production rate of HO• radicals as the oxidant and due to the direct oxidation by ozone. Furthermore, this process produced CuO monoclinic crystal phase as the solid product. The initial Cu concentration, ozone dosage, and pH value have a significant effect on Cu removal efficiency. The initial Cu concentration significantly reduces Cu removal efficiency. As expected, the ozone dosage increases the Cu removal efficiency since it is responsible for HO• radical formation and direct oxidation. Furthermore, the Cu removal efficiency increases with the increase in pH value from 3 to 8. However, a further increase in pH value reduces the Cu removal efficiency due to the formation of soluble hydroxy and hydroxide complexes of Cu at the alkaline conditions. Interestingly, it is found that the UV irradiation intensity is not significant in the photochemical oxidation process on Cu from electroplating wastewater. However, it is responsible to promote the ozone photolysis producing HO• radicals through H<sub>2</sub>O<sub>2</sub> formation. It is found that the kinetic behavior of the photochemical oxidation of Cu follows the first-order kinetic model. Furthermore, the relation between the operating parameters and kinetic rate constant is also established. In addition, the mechanism of Cu removal through UV-Ozone process was also proposed concerning the findings obtained in this study.

**Author Contributions:** Conceptualization, A.P., M.D. and T.R.; methodology, A.P.; software, T.R.; validation, A.P., T.R., M.D. and W.W.; formal analysis, A.P.; investigation, A.P., M.D.; resources, T.R.; data curation, W.W.; writing—original draft preparation, A.P., T.R.; writing—review and editing, W.W.; visualization, A.P.; supervision, A.P.; project administration, A.P.; funding acquisition, W.W.

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**ASSISTANT EDITOR ASSIGNED (22 September 2020)**

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Dear Dr. Prasetyaningrum,

Your manuscript has been assigned to Diana Radulescu for further processing who will act as a point of contact for any questions related to your paper.

Journal: Processes

Manuscript ID: processes-955989

Title: Photochemical Oxidation Process of Copper from Electroplating

Wastewater: Process Performance and Kinetic Study

Authors: Aji Prasetyaningrum \*, Teguh Riyanto , Mohamad Djaeni , Widayat Widayat

Received: 21 September 2020

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**COMMENT REVIEWER-1 /**  
**MAJOR REVISIONS**  
**(28 September 2020)**

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subject: [Processes] Manuscript ID: processes-  
955989 - Major Revisions Due Date on  
8 October 2020

Dear Dr. Prasetyaningrum,

Thank you for submitting the following manuscript to Processes:

Manuscript ID: processes-955989

Type of manuscript: Article

Title: Photochemical Oxidation Process of Copper from Electroplating

Wastewater: Process Performance and Kinetic Study

Authors: Aji Prasetyaningrum \*, Teguh Riyanto, Mohamad Djaeni, Widayat Widayat

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revision of your manuscript or if you need more time. We look forward to hearing from you soon.

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## REVIEWER 1

English language and style

Extensive editing of English language and style required

Moderate English changes required

English language and style are fine/minor spell check required

I don't feel qualified to judge about the English language and style

Yes    Can be improved    Must be improved    Not applicable

Does the introduction provide sufficient background and include all relevant references?

Is the research design appropriate?

Are the methods adequately described?

Are the results clearly presented?

Are the conclusions supported by the results?

### Comments and Suggestions for Authors

The paper entitled Photochemical Oxidation Process of Copper from Electroplating Wastewater: Process Performance and Kinetic Study, deals with a very important environmental protection topic.

The authors proposed a model for photochemical oxidation process of Cu from electroplating wastewater, by using CuSO<sub>4</sub> solution and varying different reaction conditions.

However, there are some uncertain aspects that the authors should clarify them

1. For example, why the authors used only UV radiation instead of visible one, because copper sulphate have a large area of wavelengths in the visible part of the spectrum?
2. This could be an explanation for the conclusion written by the authors -UV irradiation intensity is not significant in the photochemical oxidation process on Cu from electroplating wastewater-
3. Also, the authors should improve the photochemical part, by explaining the method(s) of light intensity determination (actinometry, dosimetry, etc).
4. A spectrophotometric experiment should be included in the paper, and the decrease of copper sulphate concentration should be evaluated by UV-Vis spectra, not only by atomic absorption spectroscopy.
5. Figure 11 I think that should be redrawn, Is difficult for readers to understand the significance of some coloured lines.

I suggest the paper to be improved and re-submit after that for evaluation

**REVIEWER 2**

English language and style

- Extensive editing of English language and style required
- Moderate English changes required
- English language and style are fine/minor spell check required
- I don't feel qualified to judge about the English language and style

Yes    Can be improved    Must be improved    Not applicable

Does the introduction provide sufficient background and include all relevant references?

- 

Is the research design appropriate?

- 

Are the methods adequately described?

- 

Are the results clearly presented?

- 

Are the conclusions supported by the results?

- 

The authors presented their work in a clear and linear way. Results are presented and discussed properly, with reference to the literature. **I have a general doubt concerning the novelty of the study.** For sure they **conducted a structured investigation of the effect of different parameters**, nonetheless, many publication concerning wastewater treatment assess copper photochemical oxidation, together with other metals and/or organic materials. One example which focus on copper is the following:

Photochemical Advanced Oxidation Processes for Water and Wastewater Treatment - I. Litter, Marta; Quici, Natalia - Recent Patents on Engineering, Volume 4, Number 3, 2010, pp. 217-241(25)  
DOI: <https://doi.org/10.2174/187221210794578574>

Fig. 11 is not readable in my pdf, probably a problem in file format conversion

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We sent a revision request for the following manuscript on 28 September 2020.

Manuscript ID: processes-955989

Type of manuscript: Article

Title: Photochemical Oxidation Process of Copper from Electroplating

Wastewater: Process Performance and Kinetic Study

Authors: Aji Prasetyaningrum \*, Teguh Riyanto, Mohamad Djaeni, Widayat Widayat

Received: 21 September 2020

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955989 - Manuscript Resubmitted

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Dear Dr. Prasetyaningrum,

Thank you very much for resubmitting the modified version of the following manuscript:

Manuscript ID: processes-955989  
Type of manuscript: Article  
Title: Photochemical Oxidation Process of Copper from Electroplating  
Wastewater: Process Performance and Kinetic Study  
Authors: Aji Prasetyaningrum \*, Teguh Riyanto, Mohamad Djaeni, Widayat Widayat  
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Journal Name: Processes

Manuscript ID: processes-955989

Title: "Photochemical Oxidation Process of Copper from Electroplating Wastewater: Process Performance and Kinetic Study"

Author(s): Aji Prasetyaningrum, Teguh Riyanto, Mohamad Djaeni, and Widayat Widayat

### **REVISION NOTE BASED ON REVIEWERS COMMENTS**

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Manuscript ID: processes-955989

Title: "Photochemical Oxidation Process of Copper from Electroplating Wastewater: Process Performance and Kinetic Study"

Author(s): Aji Prasetyaningrum, Teguh Riyanto, Mohamad Djaeni, and Widayat Widayat

### **REVIEWER 1**

The paper entitled Photochemical Oxidation Process of Copper from Electroplating Wastewater: Process Performance and Kinetic Study, deals with a very important environmental protection topic.

The authors proposed a model for photochemical oxidation process of Cu from electroplating wastewater, by using CuSO<sub>4</sub> solution and varying different reaction conditions.

However, there are some uncertain aspects that the authors should clarify them

1	Comment 1	:	For example, why the authors used only UV radiation instead of visible one, because copper sulphate have a large area of wavelengths in the visible part of the spectrum? This could be an explanation for the conclusion written by the authors -UV irradiation intensity is not significant in the photochemical oxidation process on Cu from electroplating wastewater-
	Response	:	In this study, we are using UV irradiation because we study the Cu removal through the oxidation using HO• radicals and ozone (O <sub>3</sub> ) (Line 141, equation (2) and (3) in the revised manuscript). The HO• radicals can be formed through ozonation process (Line 155, equation (7) in the revised manuscript). However, it is still can be improved through UV irradiation. The UV irradiation assists the ozone photolysis to produce HO• radicals through the formation of H <sub>2</sub> O <sub>2</sub> as the intermediate oxidating agent (Line 161, equation (8) in the revised manuscript). However, based on some previous studies, this process can only be conducted at wavelength below 300 nm. Therefore, we use UV irradiation rather than visible light. This statement is included in the revised manuscript (Line 164).

2	Comment 2	: Also, the authors should improve the photochemical part, by explaining the method(s) of light intensity determination (actinometry, dosimetry, etc).
	Response	: The UV irradiation intensity was measured using an instrument. A J-225 Black Ray intensity meter was used as the instrument to measure the UV irradiation intensity. This statement is included in the revised manuscript (Line 99).
3	Comment 3	: A spectrophotometric experiment should be included in the paper, and the decrease of copper sulphate concentration should be evaluated by UV-Vis spectra, not only by atomic absorption spectroscopy.
	Response	: We agree that UV-vis spectroscopy can be used to measure the Cu concentration in the solution. However, we don't use this method due to some shortcomings. One of the shortcomings is due to the shift on maximum wavelength absorbance at different pH. This is reported in some studies, including: <ul style="list-style-type: none"> <li>• Aravinda, C.L., Mayanna, S.M. &amp; Muralidharan, V.S. Electrochemical behaviour of alkaline copper complexes. J Chem Sci 112, 543–550 (2000). <a href="https://doi.org/10.1007/BF02709287">https://doi.org/10.1007/BF02709287</a></li> <li>• Mali, S.C., Raj, S. &amp; Trivedi, R. Biosynthesis of copper oxide nanoparticles using <i>Enicostemma axillare</i> (Lam.) leaf extract. Biochemistry and Biophysics Reports 20, 100699 (2019). <a href="https://doi.org/10.1016/j.bbrep.2019.100699">https://doi.org/10.1016/j.bbrep.2019.100699</a></li> <li>• Martí, I., Ferrer, A., Escorihuela, J., Burguete, M.I. &amp; Luis, S.V. Copper(II) complexes of bis(amino amide) ligands: effect of changes in the amino acid residue. Dalton Trans 41, 6764–6776 (2012). <a href="https://doi.org/10.1039/C2DT12459A">https://doi.org/10.1039/C2DT12459A</a></li> </ul> <p>The shift in maximum wavelength absorbance could affect to the inaccuracy in the measurement. It should be noted that we performed this oxidation process at different pH. Therefore, we used another better method to measure the Cu concentration in the solution. The method used was atomic absorption spectroscopy (AAS). Some statements regarding this answer is included in the revised manuscript (Line 111).</p>
4	Comment 4	: Figure 11 I think that should be redrawn, Is difficult for readers to understand the significance of some coloured lines.
	Response	: The figure 11 was edited. The previous figure in the submitted manuscript is in “Enhanced Metafile” format. In the revised manuscript, we used the “JPG” format as attached bellow. Hopefully, it can provide better presentation (Line 450). <div style="text-align: center;"> <p>The diagram illustrates a photochemical reaction cycle. UV light (orange wavy arrows) is shown entering the system. It initiates the reaction of H<sub>2</sub>O and O<sub>3</sub> to produce H<sub>2</sub>O<sub>2</sub> and HO<sub>2</sub><sup>-</sup>. HO<sub>2</sub><sup>-</sup> then decomposes into HO• and O<sub>2</sub>. HO• reacts with Cu<sup>2+</sup> to form CuO. The final products are Cu(OH)<sub>3</sub><sup>-</sup> and Cu(OH)<sub>4</sub><sup>2-</sup>. The reaction is shown with various colored lines and arrows indicating the flow of species and the effect of UV light.</p> </div>

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**REVISION NOTE BASED ON REVIEWERS COMMENTS**

Journal Name: Processes

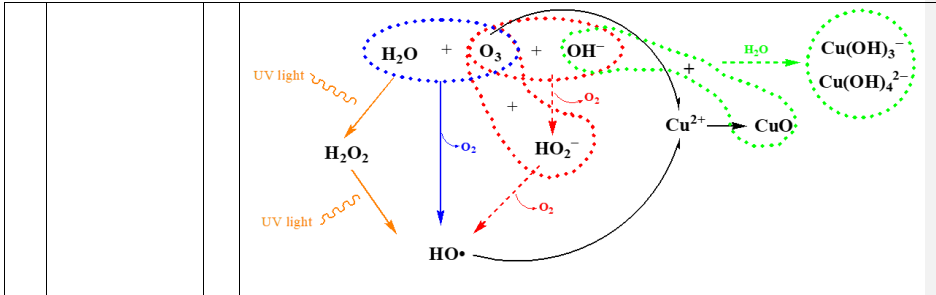
Manuscript ID: processes-955989

Title: "Photochemical Oxidation Process of Copper from Electroplating Wastewater: Process Performance and Kinetic Study"

Author(s): Aji Prasetyaningrum, Teguh Riyanto, Mohamad Djaeni, and Widayat Widayat

**REVIEWER 2**

1	Comment 1	:	The authors presented their work in a clear and linear way. Results are presented and discussed properly, with reference to the literature. I have a general doubt concerning the novelty of the study. For sure they conducted a structured investigation of the effect of different parameters, nonetheless, many publication concerning wastewater treatment assess copper photochemical oxidation, together with other metals and/or organic materials. One example which focus on copper is the following: Photochemical Advanced Oxidation Processes for Water and Wastewater Treatment - I. Litter, Marta; Quici, Natalia - Recent Patents on Engineering, Volume 4, Number 3, 2010, pp. 217-241(25) DOI: <a href="https://doi.org/10.2174/187221210794578574">https://doi.org/10.2174/187221210794578574</a>
	Response	:	The novelty of this study is strengthened. Some previous studies on Cu or other metals removal from wastewater are focused on investigating the process parameters affecting the process. Based on these understandings, we investigate the kinetic models of the Cu removal process in order to determine the order of the kinetic rate. In addition, the relation of operating parameters with the kinetic parameter is also investigated comprehensively. Extendedly, the correlation between process parameters and kinetic parameter is developed. This correlation accommodates the prediction of the kinetic parameter on different process conditions. Therefore, the kinetic rate of Cu removal through photochemical oxidation can be easily predicted. We also addressed the possible reaction mechanism. These statements are included in the revised manuscript ( <a href="#">Line 72</a> )
2	Comment 2	:	Fig. 11 is not readable in my pdf, probably a problem in file format conversion.
	Response	:	The figure 11 was edited. The previous figure in the submitted manuscript is in "Enhanced Metafile" format. In the revised manuscript, we used the "JPG" format as attached bellow. Hopefully, it can provide better presentation ( <a href="#">Line 450</a> ).



Article

# Photochemical Oxidation Process of Copper from Electroplating Wastewater: Process Performance and Kinetic Study

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**Abstract:** An investigation of the process of ozone combined with ultraviolet radiation has been carried out in order to establish the kinetics for photochemical oxidation of copper (Cu) from electroplating wastewater. The effects of operating parameters, including initial Cu concentration, ozone dosage, UV irradiation intensity, and pH value on the photochemical oxidation of Cu have been studied comprehensively. The Cu concentration during the reaction was identified using Atomic Absorption Spectroscopy (AAS) method. The solid product was analyzed using X-ray Diffraction (XRD) and Scanning Electron Microscope–Energy Dispersive X-ray (SEM–EDX) methods. It was found that the UV-Ozone process has high performance on Cu removal compared to UV and Ozone processes due to the high production rate of HO• radicals. It was also found that a solid product from the UV-Ozone process was CuO monoclinic crystal phase. The initial Cu concentration, ozone dosage, and pH value were significantly affected the Cu removal efficiency. On the other hand, the UV irradiation intensity was not significant; however, it has responsibility in promoting the ozone photolysis. The kinetics model for the photochemical oxidation of Cu was established following the first-order kinetic model. Furthermore, the reaction mechanism was also developed.

**Keywords:** photochemical oxidation; Cu; kinetics; ozone; ultraviolet irradiation; advanced oxidation process

## 1. Introduction

Heavy metals have become a global issue of environmental and public health concern because of their toxicity and bioaccumulation in the human body and food chain [1]. The effects of urbanization and industrialization cause an increase in heavy metal pollution to the environment [2]. High toxicity and non-biodegradability of heavy metals caused a number of environmental problems [3]. The accumulation of heavy metals in the atmosphere is responsible for both natural and anthropogenic activities [4]. Copper (Cu), as an essential trace element, is required by biological systems for the activation of some enzymes during photosynthesis. However, at higher concentrations, it shows harmful effects on the human body. Continuous exposure may lead to kidney damage and even death. Cu is also toxic to a variety of aquatic organisms even at very low concentrations. Mining, metallurgy, and industrial applications are the major sources of Cu exposure in the environment [5].

There were several techniques for the treatment of industrial wastewater containing heavy metals, including chemical precipitation, ion exchange, coagulation-flocculation, flotation, membrane filtration, electrochemical treatment, magnetic separation and purification, biosorption, and nanotechnology [6]. Advanced oxidation processes (AOPs) are promising, efficient, and

environmentally friendly methods for the removal of wastewater contaminants [7]. The AOPs can be photochemical AOP, sonochemical AOP, and electrochemical AOP [7]. The basic principles of AOPs are the in situ generations of hydroxyl radicals ( $\text{HO}\bullet$ ) during the oxidation process. The hydroxyl radicals can be produced from hydrogen peroxide ( $\text{H}_2\text{O}_2$ ), ozone, photo-catalysis, or oxidants in combination with ultraviolet (UV) radiation [8].

Ozone is an active oxidant which is commercially available and widely used in municipal water treatment and wastewater treatment. Besides having the ability as an oxidizing agent, wastewater treatment with ozone is an environmentally friendly method. The pollutants such as color, odor, and microorganisms are oxidized directly without generating harmful chlorinated by-products or substantial residues [9]. In order to increase the effectivity of the ozonation process, it is necessary to combine the ozone process with another process which can increase the reaction efficiency between ozone and pollutant. The promising process is the combination of ozone and UV irradiation that could enhance the production of hydroxyl radicals ( $\text{HO}\bullet$ ) as the main oxidant compounds in AOP [10]. The combination of UV-Ozone process has been reported as a promising process for  $\text{HO}\bullet$  radical formation [11–13]. Therefore, the oxidation process could be accelerated. Based on this characteristic, the combination of UV-Ozone process has a potential option for wastewater treatment [14].

Since the UV-Ozone process has high beneficial result in wastewater treatment; therefore, it is important to investigate this process comprehensively. However, the utilization of the UV-Ozone process for Cu removal from electroplating wastewater is still limited. Therefore, the comparison of UV, Ozone, and UV-Ozone processes is investigated in this study. Furthermore, the effect of several operating parameters, including initial Cu concentration, ozone dosage, UV irradiation intensity, and pH value, on the Cu removal process from electroplating wastewater through photochemical (UV-Ozone) oxidation process is also comprehensively studied. In addition, the kinetic study of this process is important for scale-up processing. The study of the kinetics of wastewater treatment with a combination of UV-Ozone process for organic compound degradation has been investigated by several previous researchers [15,16]. However, to the best of our knowledge, there are no previous studies concerning the kinetic study in Cu from electroplating wastewater by UV-Ozone process. In this study, the kinetic models of the Cu removal process are investigated in order to determine the order of the kinetic rate. Furthermore, the relation of operating parameters with the kinetic parameter is also investigated comprehensively. The possible reaction mechanism is also addressed in this study.

## 2. Materials and Method

### 2.1. Materials

This experiment was carried out using synthetic wastewater with an initial copper concentration of 145.73 mg/L. The initial concentration of samples was prepared based on the composition of copper from industrial electroplating wastewater which located at Juwana, Pati, Central of Java Indonesia. Synthesized wastewater with varying copper concentrations (145.73 mg/L; 72.86 mg/L; and 36.9 mg/L) was prepared by dissolving the corresponding amount of  $\text{CuSO}_4\cdot 5\text{H}_2\text{O}$  (>98%, Merck) in deionized (DI) water. The initial pH value of the solution was adjusted using HCl (37%, Merck) and NaOH (>98%, Merck).

### 2.2. Experimental system set-up

The experimental study on photochemical oxidation of copper by ozone combined with UV irradiation was conducted in a bubble column reactor made of borosilicate glass. The reactor was equipped with a low-pressure mercury UV Light (Philips–TUV 8 Watt, main emission line at 253.7 nm). Ozone gas generated from ozone generator type dielectric barrier discharge (Dipo Technology, Diponegoro University) connected to reactors UV-Ozone (**Figure 1**). The ozone dosage was varied at 5, 10, and 15 mg/h. The UV-Ozone photoreactor was performed under a semi-batch condition reaction. The reactor was an open-top cylindrical tank with a fixed top suspension with a low-pressure mercury UV Light. UV irradiation intensity was varied at 20, 40, and 60 mW/cm<sup>2</sup>. The UV irradiation intensity

was adjusted by varying the number of UV light. A fritted glass diffuser was placed at the bottom of the reactor to allow the continuous injection of ozonized gas. Ozone was produced from the air which flows into the ozone generator. The reaction was adjusted for different time periods (i.e. 10, 20, 30, 40, 50, 60 min) and initial pH (3, 6, 8, and 10) during UV-Ozone treatment. All oxidation reaction processes were conducted at room temperature and atmospheric pressure. The initial pH was adjusted using NaOH and HCl solutions.

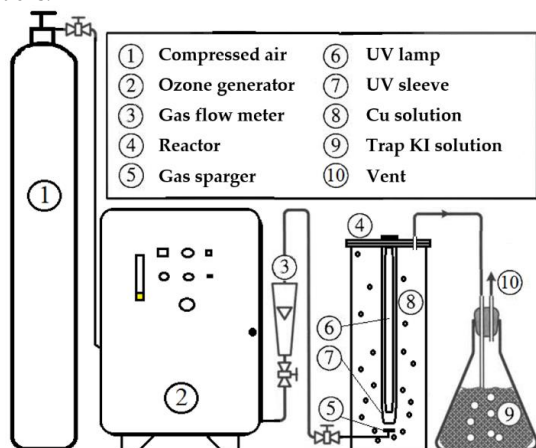


Figure 12. Schematic diagram of UV-Ozone treatment equipment

### 2.3. Analytical Methods

A pH meter analyzer (EZDO PH-5011A) was used during the procedure for assessing the pH of the response solution. An Atomic Absorption Spectroscopy (AAS – Quantachrome series 11.0) was used to analyzed Cu concentration and wastewater samples. The solid product was also analyzed using X-ray Diffraction (XRD) (Shimadzu 7000) method. The Cu K $\alpha$  radiation ( $\lambda = 1.54 \text{ \AA}$ ) was operated at 30 mA and 30 kV. The diffraction patterns were generated at  $2\theta$  angle ranges of  $20\text{--}70^\circ$  with a scanning speed of  $4^\circ \text{ min}^{-1}$ . The surface morphology and metal oxide composition of the solid product were analyzed using Scanning Electron Microscope–Energy Dispersive X-ray (SEM–EDX) (SEM–EDX JEOL JSM-6510LA) method. The removal efficiency was calculated using Equation (1), when  $\eta$  is the Cu removal efficiency (%),  $C_0$  is the initial Cu concentration (mg/L) and  $C_t$  (mg/L) is the Cu concentration at time  $t$ .

$$\eta(\%) = \frac{C_0 - C_t}{C_0} \times 100 \quad (1)$$

## 3. Results and Discussions

### 3.1. Comparison of UV, Ozone and combination UV–Ozone

In order to study the different effects of UV, Ozone, and UV–Ozone combination processes on Cu removal from electroplating wastewater, these three processes are compared. The result is shown in Figure 2.

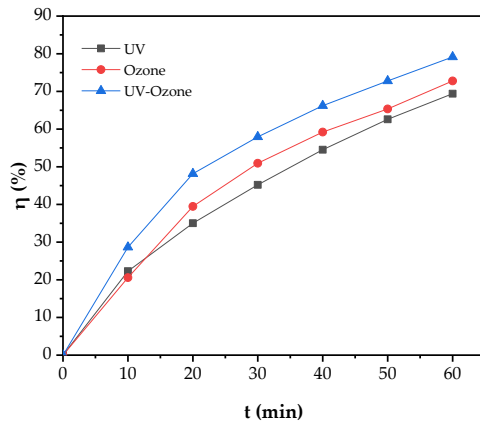
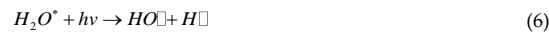


Figure 13. Comparison of UV, Ozone and UV-Ozone combination processes

Figure 2 depicted the comparison of UV, Ozone, and combined UV-Ozone treatment on Cu removal efficiency from electroplating wastewater. As can be seen, at 60 minutes of reaction, the Cu removal efficiency obtained from the UV irradiation process is 69.08%, while the Cu removal efficiency obtained from Ozone treatment is 72.64%. Interestingly, the Cu removal efficiency can be increased up to 78.8% when the UV and Ozone processes are combined. This high Cu removal efficiency can be obtained by the enhancement of hydroxyl radicals ( $\text{HO}\bullet$ ) during the combination of UV and Ozone processes. As reported by Halena et al. [10], the combination of UV irradiation and ozone could enhance the production of hydroxyl radicals; therefore the oxidation process could be accelerated. Furthermore, it is suggested that the combination of UV irradiation and Ozone treatment can increase the Cu removal efficiency in the Cu removal process from electroplating wastewater. It is true since the mechanism of Cu oxidation through AOP is initiated by the presence of  $\text{HO}\bullet$  radicals. Equations (2) and (3) represent the oxidation process of Cu through AOP. As can be seen in Equation (2), the  $\text{Cu}^{2+}$  ion is oxidized by  $\text{HO}\bullet$  radicals producing solid  $\text{CuO}$  and water molecules.



Based on Equation (2), the important thing in Cu removal through AOP is the presence of  $\text{HO}\bullet$  radicals. Therefore, it is suggested that the process of producing more  $\text{HO}\bullet$  radicals is the preferred process. As can be seen in Figure 2, the Cu removal efficiency obtained by the UV irradiation process is the lowest compared to the other processes. It is true since the UV irradiation process without the presence of ozone in the system is only produces  $\text{HO}\bullet$  radicals through the photolysis of the  $\text{H}_2\text{O}$  molecule [12,17]. The photolysis of the  $\text{H}_2\text{O}$  molecule by UV irradiation is shown in Equation (4) [12]. The other possible mechanisms in  $\text{HO}\bullet$  production through the UV irradiation process are shown in Equations (5) and (6) [18].



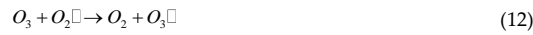
For the Ozone treatment, as depicted in Figure 2, the Cu removal efficiency is higher than the Cu removal efficiency obtained by the UV irradiation process. This is due to the fact that the Cu oxidation



through Ozone treatment can be initiated by HO• radicals and directly oxidized by the ozone molecule (Equation (3)). These two reactions occurred in Ozone treatment, therefore; the Cu removal efficiency obtained by Ozone treatment is higher than obtained by UV treatment. The chemical reaction of HO• radicals formation through Ozone treatment is shown in Equation (7) [12].



As mentioned before, the highest Cu removal efficiency is obtained by the UV-Ozone process due to the high HO• radical formation during the combination of the UV irradiation process and the Ozone process. Besides, the presence of ozone can also increase the oxidation process due to the direct oxidation process. The formation of HO• radicals in the UV-Ozone process has been widely reported. Some proposed HO• radical formation during the UV-Ozone process follow the reaction mechanism as described in Equation (8-10) [12,19]:



As can be seen, in the UV-Ozone process, an additional oxidant, H<sub>2</sub>O<sub>2</sub>, is generated through O<sub>3</sub> photolysis (Equation (8)) [12]. O<sub>3</sub> reacts with H<sub>2</sub>O to form H<sub>2</sub>O<sub>2</sub> under UV irradiation. This oxidant can produce more HO• radicals. H<sub>2</sub>O<sub>2</sub> absorbs UV light to generate HO• radicals. By this fact, the Cu removal efficiency can be increased following the reaction shown in Equation (2) in the combination of UV and Ozone process. This finding is in accordance with several previous studies. In dyehouse wastewater subjected to the combination of UV-Ozone treatment, a significant color reduction was obtained up to 98.3% [13]. For another reason, Bes-Piá et al. [11] studied the UV-Ozone process for textile wastewater treatment. They reported that the combination of UV irradiation with ozone could significantly reduce the operating time to reach the same COD removal efficiency.

### 3.2. Characterisation of the solid product

As reported in the previous section (Section 3.1), the UV-Ozone process has the highest Cu removal efficiency compared to the other processes. The Cu removal through this process produces a solid product that is proposed as CuO, as shown in Equation (2) and (3). In order to prove that the solid product is CuO, the solid product was analyzed. **Figure 3** shows the XRD pattern of the solid product obtained from the UV-Ozone process. Based on **Figure 3**, the characteristic peaks appear at 2θ of 32.54°, 35.56°, 38.74°, 48.68°, 53.62°, 58.16°, 61.62°, 66.12°, and 68.12°, respectively. These peaks correspond to the CuO (Tenorite phase) according to the JCPDS card number 96-900-8962. These also indicate that the formation of monoclinic crystal structure [20]. On the other hand, several studies reported that two peaks at 2θ = 35.6° [002] and 2θ = 38.8° [111] observed in the diffraction patterns are ascribed to the formation of the CuO (space group C2/c) monoclinic crystal phase [21,22]. In this study, these peaks appear at 2θ = 35.56° and 2θ = 38.74°. Therefore, it is confirmed that the solid product produced from the UV-Ozone process is CuO in the monoclinic crystal phase.

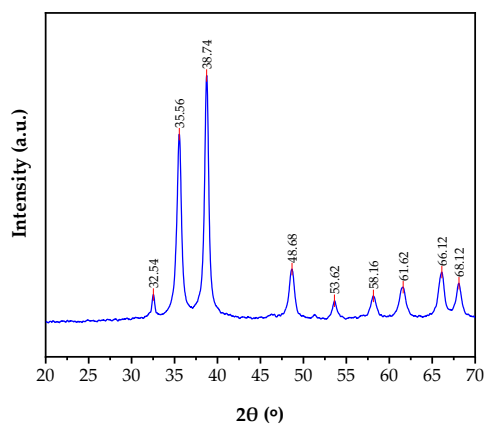
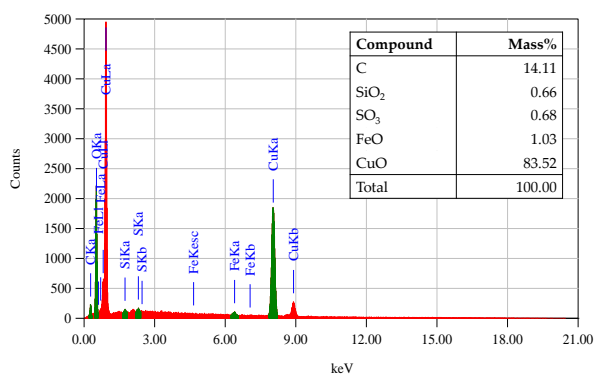
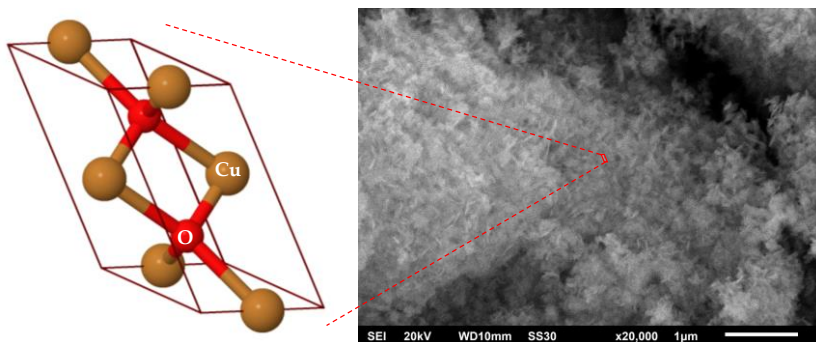


Figure 14. XRD pattern of the solid product obtained from UV-Ozone process



(a)



(b)

Figure 15. Composition of metal oxide in the solid product (a) and surface morphology (right) and crystal structure model (left) of the solid product (b).

The morphology and the metal oxide composition of the solid product from the UV-Ozone process are identified using SEM analysis. Based on the result of SEM-EDX analysis (Figure 4(a)), it is confirmed that the most metal oxide present in the solid product is CuO. The CuO content detected by SEM-EDX analysis in the solid product is 83.52%. The other components detected may be produced from the impurities in the wastewater. However, this fact confirmed that the solid product is CuO. Figure 4(b) is the appearance of the solid product surface (right) and the model of the CuO monoclinic crystal structure (left). As can be seen, the surface morphology of the CuO is agglomerated nanorods. Manyasree et al. [23] reported that the surface morphology of the CuO nanoparticle which was synthesized from copper sulfate and sodium hydroxide through the coprecipitation process is a flower-shaped structure.

### 3.3. The effect of operating parameters

#### 3.3.1. Effect of initial concentration

In order to study the effect of the initial Cu concentration, the photochemical oxidation process was conducted with the variation of the initial Cu concentration. The initial Cu concentration was varied at 145.73, 72.86, and 36.9 mg/L. The monitored parameter is the Cu removal efficiency. The effect of initial Cu concentration on Cu removal efficiency is depicted in Figure 5.

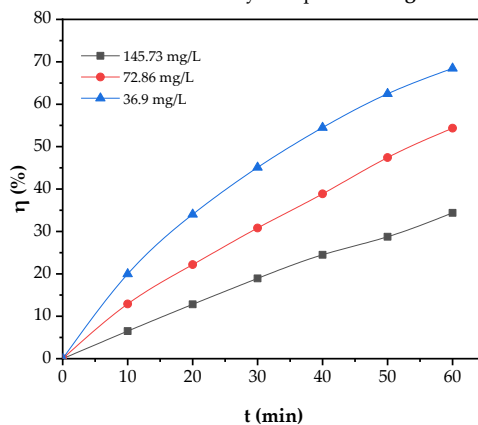


Figure 16. Effect of initial Cu concentration on Cu removal efficiency through photochemical process

As can be seen in Figure 5, the Cu removal efficiency is significantly affected by the initial Cu concentration. During the oxidation process for 60 minutes, the Cu removal efficiency obtained at the initial Cu concentration of 145.73 mg/L is 34.39%, the Cu removal efficiency obtained at the initial Cu concentration of 72.86 mg/L is 54.36%, while the Cu removal efficiency obtained at the initial Cu concentration of 36.9 mg/L is 68.46%. Based on these results, it is suggested that the initial Cu concentration has a significant effect on the Cu removal efficiency in the Cu removal process from electroplating wastewater. Furthermore, the Cu removal efficiency decreases significantly with the increase in the initial Cu concentration from 36.9 mg/L to 145.73 mg/L. The decrease in Cu removal efficiency at high initial Cu concentration is due to the presence of a high amount of hydroxyl radical scavengers. When the initial Cu concentration is high, the photochemical oxidation process is overloaded. As a result, the Cu in the solution competes with each other during the oxidation reaction process [24]. On the other hand, in the UV irradiation process, the permeation of photons is reduced at high solution concentration; therefore, the concentration of hydroxyl radical produced is low [24]. Therefore, the oxidation of Cu decreases at high initial Cu concentration. This finding is in accordance with several previous studies in AOP. Hassan et al. [25] reported that the decolorization of Direct

Yellow 50 dye in seawater through the UV-Ozone process was highly affected by the initial dye concentration which the decolorization rate decreased by increasing the dye concentration. Dai et al. [26] also reported a similar finding in the degradation of carbamazepine in water through AOP. They reported that the degradation percentage of carbamazepine decreased from 34% to 13% with an increase in the initial carbamazepine concentration from 4.2  $\mu\text{M}$  to 42.3  $\mu\text{M}$ . Jing et al. [27] also reported that the initial aniline concentration affected the aniline degradation process through ozonation. They reported that aniline degradation decreased with the increase in the initial aniline concentration due to the overloaded of the ozonation process.

### 3.3.2. Effect of ozone dosage

In this study, the effect of ozone dosage on the Cu removal process through the photochemical oxidation process is studied by varying the ozone dosage. The ozone dosage was varied at 5, 10, and 15 mg/h. The Cu removal efficiency was monitored to study this matter. The effect of ozone dosage on Cu removal efficiency is depicted in Figure 6.

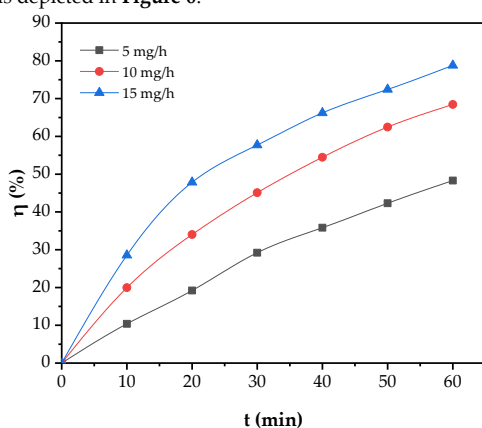


Figure 17. Effect of ozone dosage on Cu removal efficiency through a photochemical process

As can be seen in Figure 6, the Cu removal efficiency increases significantly with increasing the ozone dosage. At 60 min reaction, the Cu removal efficiency obtained at ozone dosage of 5 mg/h is 48.31%, the Cu removal efficiency obtained at ozone dosage of 10 mg/h is 68.46%, while the Cu removal efficiency obtained at ozone dosage of 15 mg/h is 78.80%. Based on these results, it is suggested that the Cu removal efficiency in Cu removal from electroplating wastewater through the photochemical oxidation process is highly affected by the ozone dosage. As the increase in ozone dosage, the Cu removal efficiency increases. It is true since in the ozonation process, the oxidation of Cu can occur through two different mechanisms, i.e. oxidation by HO• radicals (Equation (2)) and direct oxidation by ozone (Equation (3)). As reported by Wang et al. [28], in the ozone-based oxidation process, there are two methods, namely indirect reaction of free radicals and direct reaction.

Pertaining to the effect of ozone dosage on HO• radical formation, when ozone dosage increases, more HO• radicals are formed. Under UV irradiation, H<sub>2</sub>O<sub>2</sub> can be formed through the reaction of ozone with H<sub>2</sub>O (Equation (8)). Furthermore, this H<sub>2</sub>O<sub>2</sub> molecule absorbs the UV light to generate the HO• radicals (Equation (9)) [19]. Ozone molecules also can react with H<sub>2</sub>O<sub>2</sub> molecules to produce HO• radicals. Besides, the ozone also can directly react with H<sub>2</sub>O to generate HO• radicals (Equation (7)). Then, Cu is oxidized by HO• radicals. Therefore, the photochemical oxidation rate of Cu increases with the increase in ozone dosage. As a comparison, Wang et al. [28] reported that the decomplexation of electroplating wastewater by the ozone-based oxidation process increased with the increase in ozone dosage. Ren et al. [19] reported that the removal efficiency of polyacrylamide through the

photochemical oxidation process increased with the increase in ozone dosage. Guo et al. [29] also reported the same result in the degradation process of sulfadiazine in water by the UV-Ozone process.

### 3.3.3. Effect of UV irradiation intensity

In order to study the effect of UV irradiation intensity on Cu removal from electroplating wastewater, the photochemical process was conducted by varying the UV irradiation intensity. The UV irradiation intensity was varied at 20, 40, and 60 mW/cm<sup>2</sup>. Figure 7 shows the result of the effect of UV irradiation intensity on Cu removal efficiency.

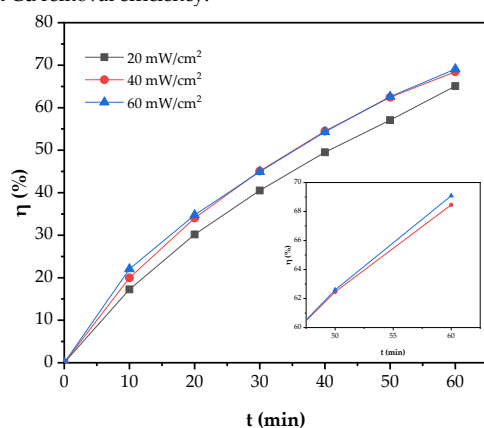


Figure 18. Effect of UV irradiation intensity on Cu removal efficiency through photochemical process

As shown in Figure 7, at 60 minutes reaction, the Cu removal efficiency obtained at a UV irradiation intensity of 20 mW/cm<sup>2</sup> is 65.09%, the Cu removal efficiency obtained at a UV irradiation intensity of 40 mW/cm<sup>2</sup> is 68.46%, while the Cu removal efficiency obtained at a UV irradiation intensity of 60 mW/cm<sup>2</sup> is 69.08%. It can be concluded that the Cu photochemical oxidation rate slightly increases with the increase in UV radiation intensity. The Cu removal efficiency slightly increases for UV irradiation of 20 to 40 mW/cm<sup>2</sup>. Furthermore, the Cu removal efficiency remains unchanged for the UV irradiation intensity of 40 to 60 mW/cm<sup>2</sup>.

The increase in Cu removal efficiency with the increase in UV irradiation intensity is due to the high possibility to produce HO• radicals at high UV irradiation intensity. The possible process of HO• radical formation during UV irradiation is the photolytic dissociation of water by UV irradiation at a wavelength of 254 nm [30]. However, this process is still unclear since some studies reported that the photolytic dissociation of water to HO• radicals is only can be conducted at a wavelength of less than 242 nm. Deng and Zhao [12] claimed that this process occurs at a wavelength of less than 242 nm. Furthermore, Jin et al. [17] reported that the HO• radicals could be formed through irradiation on liquid water by UV light in the range of 150 – 200 nm. As the UV irradiation wavelength used in this study is around 253.7 nm, the increase in Cu removal efficiency with the increase in UV irradiation intensity from 20 to 40 mW/cm<sup>2</sup> is attributed to the formation of HO• radicals through ozone photolysis producing H<sub>2</sub>O<sub>2</sub> (Equation (8)). However, high UV irradiation intensity in the ozonation process is not good. It is true since, at high UV irradiation intensity, the ozone molecule could be degraded to oxygen [31]. Therefore, the formation of HO• radicals is low at high UV irradiation intensity. Furthermore, it is suggested that the unchanged Cu removal efficiency at a UV irradiation intensity of 60 mW/cm<sup>2</sup> is due to the degradation of the ozone molecule resulting in the low formation of HO• radicals.

### 3.3.4. Effect of pH

The efficiency of AOP can be influenced by various factors, such as the pH of the solution [32–34]. In order to study the effect of pH on the Cu removal process from electroplating wastewater through the photochemical oxidation process, the pH of solution was varied at 3, 6, 8, and 10. The result is depicted in Figure 8.

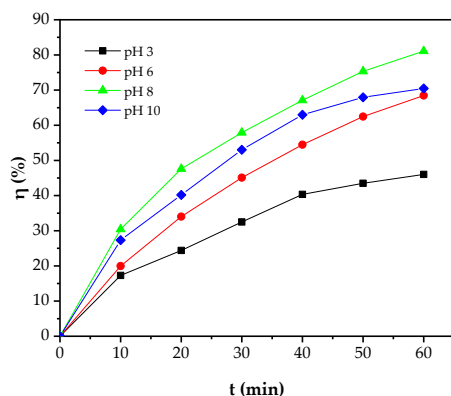
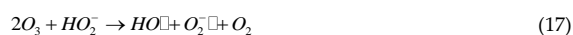


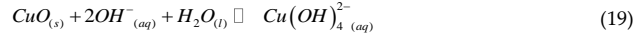
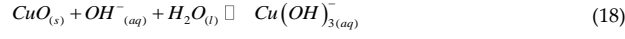
Figure 19. Effect of pH on Cu removal efficiency through photochemical process

As can be seen in Figure 8, at 60 minutes reaction, the Cu removal efficiency obtained at pH of 3 is 46.02%, the Cu removal efficiency obtained at pH of 6 is 68.46%, the Cu removal efficiency obtained at pH of 8 is 80.09%, while the Cu removal efficiency obtained at pH of 10 is 70.46%. It can be seen that the highest Cu removal efficiency is obtained at a pH of 8. Hence, it can be concluded that the photochemical oxidation of Cu from electroplating wastewater increases with the increase in pH from 3 to 8, then it decreases with a further increase in pH to 10.

The increase in Cu removal efficiency with the increase in pH value is attributed to the high rate of HO• radical formation at high pH conditions. As reported by Muniyasamy et al. [34], in the oxidation process, pH influences the process by altering the chemical nature of ozone. At low pH conditions (acidic conditions), the decomposition of the ozone molecule to produce HO• radicals is relatively slow [35]. It was reported that the decomposition rate of ozone was sluggish below the pH of 4 [36]. Furthermore, ozone tends to remain in the molecular state at acidic conditions; however, ozone can react directly as ozone radical with the contaminants at alkaline conditions [33,37]. Therefore, the Cu removal efficiency is low at a low pH value. Furthermore, the higher the pH value, the higher the Cu removal efficiency. This tendency is attributed to the high formation of HO• radicals at the alkaline conditions. It was reported that the decomposition rate of ozone in water is better at higher pH values [38]. At alkaline conditions, ozone is unstable and rapidly decomposes into HO• radical [34,35]. The HO• radical formation through ozone decomposition occurs as follows:



As can be seen in Equation (16) and (17), the HO• radical which is the primary oxidant in indirect oxidation [34] is produced at high pH level represented as OH<sup>-</sup>. Therefore, the Cu removal efficiency increases with the increase in pH value since the HO• radical formation is favored at a high pH level. However, the Cu removal efficiency decrease at a pH of 10. At higher pH value, CuO can dissolve to the aqueous phase due to the formation of soluble hydroxy and hydroxide complexes [39]. Therefore, Cu removal efficiency decreases. The possible dissolution mechanism of CuO at high pH value was proposed by Khan et al. [39] as follows:



### 3.4. Kinetic study

#### 3.4.1. Determination of the kinetic rate order

Three classical kinetic models are proposed to describe the Cu removal process and to determine the order or kinetic rate. These kinetic models include first-order model, second-order model, and pseudo-first-order model. The compatibility of these models is evaluated by the  $R^2$  value as reported elsewhere [40]. In this work, the kinetic study of Cu removal from electroplating wastewater is considered for various initial Cu concentration ( $C_0$ ), ozone dosage ( $C_{O_3}$ ), UV irradiation intensity ( $I_{uv}$ ), and initial pH condition.

In this advanced oxidation process for Cu removal from electroplating wastewater, the mass conservation of Cu in the process can be generally expressed as:

$$-\frac{dC_t}{dt} = (-r) \quad (20)$$

where  $C_t$  (mg/L) is the concentration of Cu at time  $t$  (min),  $(-r)$  (mg/L.min) is the rate of Cu removal. For first order model ( $-r=k_1C_t$ ), integration of Equation (20) at the initial concentration of  $C_0$ , gives:

$$-\ln\left(\frac{C_t}{C_0}\right) = k_1t \quad (21)$$

where  $k_1$  (1/min) is the kinetic rate constant for first order. Further simplification of Equation (21) will give the time-dependent concentration of Cu (Equation (22)).

$$C_t = C_0e^{-k_1t} \quad (22)$$

For second-order model ( $-r=k_2C_t^2$ ), the integration of Equation (20) will give:

$$\frac{1}{C_t} = k_2t + \frac{1}{C_0} \quad (23)$$

where  $k_2$  (L/mg.min) is the kinetic rate constant of the second-order model. For the pseudo-first-order model ( $-r=k_p(C_t - C_e)$ ), the time-dependent concentration of Cu through the integration of Equation (20) is obtained as:

$$C_t = C_e + (C_0 - C_e)e^{-k_p t} \quad (24)$$

where  $C_e$  (mg/L) is the concentration of Cu at equilibrium condition and  $k_p$  (1/min) is the kinetic rate constant of pseudo-first-order model.

The kinetic parameters were determined using the least-square method. As can be seen, the obtained equation for first-order and second-order kinetic models (Equations (21) and (23)) are linear equations. Therefore, the kinetic parameters ( $k_1$  and  $k_2$ ) can be obtained from the linear plot relating to these equations using the linear regression method. However, the equation derived from the pseudo-first-order kinetic model is not linear. Therefore, the kinetic parameters of the pseudo-first-order kinetic model ( $C_e$  and  $k_p$ ) are calculated using a non-linear regression method. On the other hand, to measure the goodness of the kinetic models proposed, the squared-correlation coefficient,  $R^2$ , was used as the parameter [40,41]. The obtained kinetic parameters and  $R^2$  values for first-order, second-order, and pseudo-first-order kinetic models are shown in **Table 1**.

As can be seen in **Table 1**, all proposed models fit the data as the  $R^2$  values are close to unity. However, compared to the other proposed models, the  $R^2$  value of the second-order model is far enough from unity. Besides, the values of  $R^2$  obtained are not uniform for all data. Therefore, it is suggested that the second-order model is excluded as the proposed model to describe the kinetic rate of Cu removal. Hence, the first order and pseudo-first-order models are then considered as the most suitable proposed models to describe the kinetics of Cu removal. Considering the  $R^2$  values of the first order and pseudo-first-order models, both these two models have high goodness in describing the kinetic rate of Cu removal. However, at the initial Cu concentration,  $C_0$ , of 145.73 and 72.86 mg/L, the value of the equilibrium concentrations,  $C_e$ , obtained are zero. It indicates that at a high initial concentration of Cu in the wastewater, the kinetic rate will be increased. Furthermore, some of the  $C_e$  values are relatively low. In some cases, the theoretical value of  $C_e$  might be negative when the pseudo-first-order kinetic model is forcibly used [41]. In those cases, the pseudo-first-order model cannot be used to describe the kinetic rate. Obviously, if the value of the equilibrium concentration is zero or low enough, the pseudo-first-order model gets back to the first-order model [40,41]. Therefore, it is suggested that the most suitable model to describe the kinetic rate of Cu removal from electroplating wastewater through the photochemical oxidation process, combined UV-ozone process, is the first-order model.

**Table 4.** Kinetic parameters of the first order, second-order and pseudo-first-order models

$C_0$ (mg/L)	$C_{O_3}$ (mg/h)	$I_{UV}$ (mW/cm <sup>2</sup> )	pH	Kinetic parameters						
				First order		Second order		Pseudo-first order		
				$k_1$ (1/min)	$R^2$	$k_2$ (L/mg.min)	$R^2$	$k_p$ (1/min)	$C_e$ (mg/L)	$R^2$
145.73	10	40	6	0.0069	0.9997	$5.673 \times 10^{-5}$	0.9921	0.0069	0.000	0.9994
72.86	10	40	6	0.0128	0.9993	$2.451 \times 10^{-4}$	0.9678	0.0127	0.000	0.9983
36.9	10	40	6	0.0196	0.9995	$8.898 \times 10^{-4}$	0.9707	0.0237	3.769	0.9995
36.9	5	40	6	0.0111	0.9998	$3.972 \times 10^{-4}$	0.9875	0.0116	1.223	0.9993
36.9	15	40	6	0.0267	0.9959	$1.480 \times 10^{-3}$	0.9624	0.0395	5.528	0.9979
36.9	10	20	6	0.0173	0.9996	$7.407 \times 10^{-4}$	0.9609	0.0188	1.850	0.9990
36.9	10	60	6	0.0198	0.9989	$9.031 \times 10^{-4}$	0.9654	0.0252	4.663	0.9969
36.9	10	40	3	0.0116	0.9847	$4.160 \times 10^{-4}$	0.9790	0.0330	12.126	0.9940
36.9	10	40	8	0.0282	0.9980	$1.650 \times 10^{-3}$	0.9359	0.0376	4.170	0.9962
36.9	10	40	10	0.0226	0.9904	$1.100 \times 10^{-3}$	0.9909	0.0381	7.725	0.9970

The kinetic study of Cu removal using an advanced oxidation process has been widely reported. However, the kinetic study of Cu removal using the photochemical oxidation process, UV-ozone process, is still limited. The most-reported process is the electrochemical/electrocoagulation process. Al-Shannag et al. [40] reported that the electrocoagulation of heavy metals from wastewater, including Cu, followed a pseudo-first-order model. Using the same method, Vasudevan and Lakshmi [42] reported that the electrocoagulation of Cu from water follows the second-order model. Furthermore, Khattab et al. [43] reported that Cu removal through the electrochemical process follows the first-order kinetic model.

#### 3.4.2. The effect of operating parameters on kinetic rate constant

The kinetic rate behavior of Cu removal using the photochemical oxidation process, combined UV-ozone process, follows the first-order kinetic model as reported in the previous section (Section 3.3.1). The value of the kinetic rate constant of the first-order model,  $k_1$ , is presented in **Table 1**. As can be observed, the value of  $k_1$  is varied as the variation of operating parameters, including  $C_0$ ,  $C_{O_3}$ ,  $I_{UV}$ , and pH. The value of  $k_1$  increases with a decrease in  $C_0$ . Furthermore, the value of  $k_1$  increases with the increase in  $C_{O_3}$ ,  $I_{UV}$ , and pH. However, at a pH of 10, the value of  $k_1$  decreases. Even though, these phenomena indicate that the value of the observed  $k_1$  is affected by the operating parameters. This is in accordance with some previous studies that the kinetic rate constant of the advanced oxidation process, especially the UV-ozone process, is affected by the operating parameters [19,44]. The operating



parameters-dependent of the kinetic rate constant can be mathematically written as Equations (25) and (26) where  $\varepsilon$  is the pre-exponent constant while  $a, b, c$  and  $d$  are the exponent constant characteristic of  $C_0, CO_3, I_{UV}$ , and pH, respectively. The linear form of Equation (26) is shown as Equation (27).

$$k_t = f(C_0, C_{O_3}, I_{UV}, pH) \quad (25)$$

$$k_t = \varepsilon C_0^a C_{O_3}^b I_{UV}^c pH^d \quad (26)$$

$$\ln k_t = \ln \varepsilon + a \ln C_0 + b \ln C_{O_3} + c \ln I_{UV} + d \ln pH \quad (27)$$

Based on Equation (27), the value of  $\varepsilon, a, b, c,$  and  $d$  can be obtained using multiple regression analysis which also has been used elsewhere [44]. However, the value of  $k_t$  at a pH of 10 is not included in this calculation because it doesn't follow the tendency. **Table 2** shows the result of the multiple regression analysis. As can be seen, the *P-value* of the coefficients obtained for each parameter is lower than 0.05. This indicates that the coefficients obtained are significant. However, the *P-value* of  $\ln I_{UV}$  coefficient is higher than 0.05 which indicates that this coefficient is not significant. **Table 3** shows the result of the analysis of variance (ANOVA) of the multiple regression analysis. As can be observed, the value of multiple R,  $R^2$  and adjusted  $R^2$  is close to unity. These indicate that the obtained regression equation fits the data. Furthermore, the obtained *F-value* (113.4928) is higher than the *F-table* or theoretical *F-value*. The theoretical *F-value* [ $F_{0.05(4,7)}$ ] is 6.09.

**Table 5.** Multiple regression analysis result

Parameters	Coefficients	Standard Error	<i>P-value</i>
Intercept	-5.1661	0.3951	$3.5663 \times 10^{-6}$
$\ln C_0$	-0.7401	0.0441	$6.4919 \times 10^{-7}$
$\ln CO_3$	0.8154	0.0778	$1.5626 \times 10^{-5}$
$\ln I_{UV}$	0.1441	0.0778	0.1064
$\ln pH$	0.8407	0.0839	$2.1105 \times 10^{-5}$

**Table 6.** Summary of the analysis of variance (ANOVA)

	<i>df</i>	<i>SS</i>	<i>MS</i>	<i>F</i>	<i>Significance F</i>
Regression	4	1.7467	0.4367	113.4928	$1.9188 \times 10^{-6}$
Residual	7	0.0269	0.0038		
Total	11	1.7736			
Multiple R	0.9924				
$R^2$	0.9848				
Adjusted $R^2$	0.9761				
Standard Error	0.0620				

Based on the result of the multiple regression analysis (**Table 2**), Equation (27) can be rewritten as Equation (28). Furthermore, Equation (26) can be rewritten as Equation (29) with the value of  $\varepsilon$  constant was calculated from the natural exponential of the intercept of Equation (28). The obtained value of  $k_t$  was then compared to the calculated value of  $k_t$  using Equation (29). The comparison of the observed  $k_t$  and calculated  $k_t$  is depicted in **Figure 9**. It is clear that the observed and calculated values of  $k_t$  are in good fit as the  $R^2$  is close to unity (0.9848). By combining the Equations (1), (22) and (29), the calculated Cu removal efficiency can be rewritten as Equation (30). Furthermore, the comparison of the Cu removal efficiency between the observed value and the calculated value is also depicted in **Figure 10**.

$$\ln k_1 = -5.1661 - 0.7401 \ln C_0 + 0.8154 \ln C_{O_2} + 0.1441 \ln I_{UV} + 0.8407 \ln pH \quad (28)$$

$$k_1 = (5.7068 \times 10^{-3}) C_0^{-0.7401} C_{O_2}^{0.8154} I_{UV}^{0.1441} pH^{0.8407} \quad (29)$$

$$\eta_{cal} (\%) = 100 - 100 \exp\left(- (5.7068 \times 10^{-3}) C_0^{-0.7401} C_{O_2}^{0.8154} I_{UV}^{0.1441} pH^{0.8407} t\right) \quad (30)$$

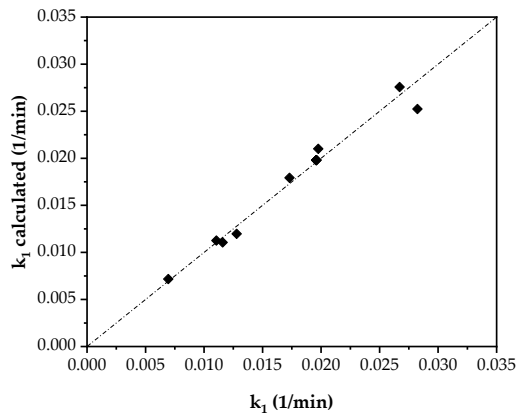
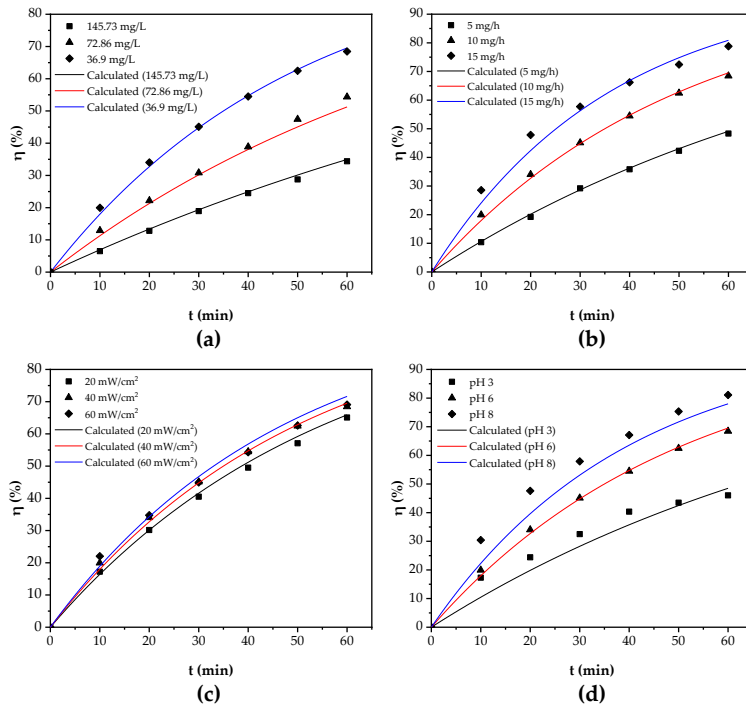


Figure 20. Comparison of observed and calculated value of  $k_1$

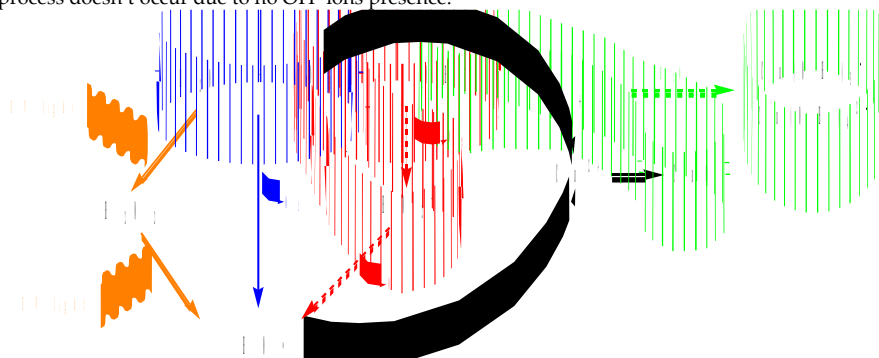


**Figure 21.** Comparison of data and calculated the Cu removal efficiency at (a) varied  $C_0$ , (b) varied  $C_{O_3}$ , (c) varied  $I_{UV}$ , and (d) varied pH.

As can be seen in **Table 2** and Equation (29), the exponent characteristic value of  $C_0$  is in a negative value. It indicates that the value of the initial Cu concentration is inversely proportional to the  $k_1$  value. This finding is in accordance with the finding of Ren et al. [19]. They reported that the initial concentration of polyacrylamide in the UV-Ozone process of polyacrylamide oxidation is inversely proportional to the kinetic rate constant value. Concerning the effect of UV and ozone treatment in this oxidation process, the value of the exponent characteristic of  $C_{O_3}$  and  $I_{UV}$  can be used to study this matter [44]. As can be seen, the exponent characteristic value of  $C_{O_3}$  is higher than  $I_{UV}$ . It is suggested that the ozone dosage is more significant in this oxidation process than UV irradiation intensity. This finding is in accordance with the previous study of the UV-Ozone process. The UV-Ozone process was conducted for  $\kappa$ -Carrageenan treatment and the result showed that the ozone dosage was more significant than UV irradiation intensity [44]. Furthermore, the value of the exponent characteristic of  $I_{UV}$  is low enough and it is close to zero. It indicates that the UV irradiation intensity is not significant enough for the Cu removal process from wastewater. In the case of the effect of pH on  $k_1$  value, it is clear that the pH has a significant effect on  $k_1$  value as the value of the exponent characteristic of pH is high. It is true because the metal oxidation process in an aqueous solution is affected by the presence of  $OH^-$  ions which can promote the formation of  $HO^\bullet$  radicals. On the other hand, the solubility of metal in aqueous solution is also affected by the pH value [39].

### 3.5. Proposed mechanism

Based on the explanation in previous sections, the mechanism of Cu removal from electroplating wastewater through the UV-Ozone process is developed. **Figure 11** shows the proposed mechanism in this study. As reported in several studies, the oxidation through AOPs is initiated by the formation of  $HO^\bullet$  radical because the main oxidating agent is  $HO^\bullet$  radical [45,46]. Based on several findings obtained in this study (reported in the previous sections), the  $HO^\bullet$  radical formation takes place through three different steps. In **Figure 11**, these steps are represented in orange, blue, and red arrows. The orange arrows represent the  $HO^\bullet$  radical formation through the UV-Ozone process. The blue arrow represents the direct ozonation of water producing  $HO^\bullet$  radicals releasing  $O_2$  molecules. Furthermore, the red arrows represent the ozone degradation producing  $HO^\bullet$  radicals in alkaline condition releasing  $O_2$  molecules. The red arrow is depicted in dash-line arrow type, this indicates that this process occurs in alkaline condition only due to the presence of  $OH^-$  ions. At acid condition, this process doesn't occur due to no  $OH^-$  ions presence.



**Figure 22.** Proposed mechanism of Cu removal from electroplating wastewater through UV-Ozone process

After the formation of HO• radicals occurred, the next step is the oxidation process. This process is depicted in black arrows, includes direct and indirect oxidation since the oxidating agents in this UV-Ozone process are HO• radicals and ozone molecules. Both HO• radicals and O<sub>3</sub> react with Cu<sup>2+</sup> to form solid CuO. The oxidation process of Cu<sup>2+</sup> to CuO by HO• radicals is called indirect oxidation, while the oxidation process of Cu<sup>2+</sup> by O<sub>3</sub> molecules is called direct oxidation. Based on **Figure 11**, as the HO• radicals and O<sub>3</sub> molecules increase in the system, the CuO product produced increases. It means that the Cu removal from the electroplating wastewater increases. However, this CuO product can dissolve in an alkaline condition. As can be seen in **Figure 11**, if the OH<sup>-</sup> ions are excessively present in the system, the CuO product will dissolve. This process is depicted as a dash-arrow in green indicating that this process occurs in alkaline conditions only due to the presence of excessive OH<sup>-</sup> ions. The dissolution of CuO to the aqueous phase in the alkaline condition is due to the formation of soluble hydroxy and hydroxide complexes [39].

Based on this proposed mechanism (**Figure 11**), it can be observed that the presence of the ozone molecule is important in this oxidation process. The ozone molecules have roles both to generate the HO• radicals and to oxidize the Cu directly. This is in accordance with the finding reported in the previous section (section 3.4) that the ozone dosage significantly affected the kinetic rate. On the other hand, the presence of UV irradiation assists the ozone photolysis process to produce HO• radicals through the formation of an intermediate oxidating agent, H<sub>2</sub>O<sub>2</sub>. Furthermore, the pH is also important in this mechanism. As can be seen in **Figure 11**, suitable alkaline condition accelerates the formation of HO• radicals. However, the high alkaline condition has a negative effect on the Cu removal process due to the CuO dissolution process in high alkaline conditions. The excessive OH<sup>-</sup> ions catch the solid CuO to form soluble hydroxy and hydroxide complexes decreasing the Cu removal efficiency.

#### 4. Conclusions

The photochemical oxidation process of Cu from electroplating wastewater has been investigated. It is shown that the UV-Ozone process has high performance on Cu removal compared to UV and Ozone processes due to the high production rate of HO• radicals as the oxidant and due to the direct oxidation by ozone. Furthermore, this process produced a CuO monoclinic crystal phase as the a solid product. The initial Cu concentration, ozone dosage, and pH value have a significant effect on Cu removal efficiency. The initial Cu concentration significantly reduces Cu removal efficiency. As expected, the ozone dosage increases the Cu removal efficiency since it is responsible for HO• radical formation and direct oxidation. Furthermore, the Cu removal efficiency increases with the increase in pH value from 3 to 8. However, a further increase in pH value reduces the Cu removal efficiency due to the formation of soluble hydroxy and hydroxide complexes of Cu at the alkaline conditions. Interestingly, it is found that the UV irradiation intensity is not significant in the photochemical oxidation process on Cu from electroplating wastewater. However, it is responsible to promote the ozone photolysis producing HO• radicals through H<sub>2</sub>O<sub>2</sub> formation. It is found that the kinetic behavior of the photochemical oxidation of Cu follows the first-order kinetic model. Furthermore, the relation between the operating parameters and kinetic rate constant is also established. In addition, the mechanism of Cu removal through the UV-Ozone process was also proposed concerning the findings obtained in this study.

**Author Contributions:** Conceptualization, A.P., M.D. and T.R.; methodology, A.P.; software, T.R.; validation, A.P., T.R., M.D. and W.W.; formal analysis, A.P.; investigation, A.P., M.D.; resources, T.R.; data curation, W.W.; writing—original draft preparation, A.P., T.R.; writing—review and editing, W.W.; visualization, A.P.; supervision, A.P.; project administration, A.P.

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Received: 21 September 2020

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Article

# Photochemical Oxidation Process of Copper from Electroplating Wastewater: Process Performance and Kinetic Study

Aji Prasetyaningrum\*, Teguh Riyanto, Mohamad Djaeni and Widayat Widayat

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**Abstract:** An investigation of the process of ozone combined with ultraviolet radiation has been carried out in order to establish the kinetics for photochemical oxidation of copper (Cu) from electroplating wastewater. The effects of operating parameters, including initial Cu concentration, ozone dosage, UV irradiation intensity, and pH value on the photochemical oxidation of Cu have been studied comprehensively. The Cu concentration during the reaction was identified using atomic absorption spectroscopy (AAS) method. The solid product was analyzed using X-ray diffraction (XRD) and scanning electron microscope–energy–dispersive X-ray (SEM–EDX) methods. It was found that the UV–Ozone process has high performance on Cu removal compared to UV and Ozone processes due to the high production rate of HO• radicals. It was also found that the solid product from the UV–Ozone process was CuO monoclinic crystal phase. The initial Cu concentration, ozone dosage, and pH value were significantly affected the Cu removal efficiency. On the other hand, the UV irradiation intensity was not significant; however, it has responsibility in promoting the ozone photolysis. The kinetics model for the photochemical oxidation of Cu was established following the first-order kinetic model. Furthermore, the reaction mechanism was also developed.

**Keywords:** photochemical oxidation; Cu; kinetics; ozone; ultraviolet irradiation; advanced oxidation process

## 1. Introduction

Heavy metals have become a global issue of environmental and public health concern because of their toxicity and bioaccumulation in the human body and food chain [1]. The effects of urbanization and industrialization cause an increase in heavy metal pollution to the environment [2]. High toxicity and nonbiodegradability of heavy metals caused a number of environmental problems [3]. The accumulation of heavy metals in the atmosphere is responsible for both natural and anthropogenic activities [4]. Copper (Cu), as an essential trace element, is required by biological systems for the activation of some enzymes during photosynthesis. However, at higher concentrations, it shows harmful effects on the human body. Continuous exposure may lead to kidney damage and even death. Cu is also toxic to a variety of aquatic organisms even at very low concentrations. Mining, metallurgy, and industrial applications are the major sources of Cu exposure in the environment [5].

There were several techniques for the treatment of industrial wastewater containing heavy metals, including chemical precipitation, ion exchange, coagulation–flocculation, flotation, membrane filtration, electrochemical treatment, magnetic separation and purification, biosorption, and nanotechnology [6]. Advanced oxidation processes (AOPs) are promising, efficient, and

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environmentally friendly methods for the removal of wastewater contaminants [7]. The AOPs can be photochemical AOP, sonochemical AOP, and electrochemical AOP [7]. The basic principles of AOPs are the in situ generations of hydroxyl radicals ( $\text{HO}\bullet$ ) during the oxidation process. The hydroxyl radicals can be produced from hydrogen peroxide ( $\text{H}_2\text{O}_2$ ), ozone, photocatalysis, or oxidants in combination with ultraviolet (UV) radiation [8].

Ozone is an active oxidant, which is commercially available and widely used in municipal water treatment and wastewater treatment. Moreover, wastewater treatment with ozone is an environment-friendly method. The pollutants such as color, odor, and microorganisms are oxidized directly without generating harmful chlorinated by-products or substantial residues [9]. In order to increase the effectivity of the ozonation process, it is necessary to combine the ozone process with another process that can increase the reaction efficiency between ozone and pollutant. The promising process is the combination of ozone and UV irradiation that could enhance the production of hydroxyl radicals ( $\text{HO}\bullet$ ) as the main oxidant compounds in AOP [10]. The combination of UV-Ozone process has been reported as a promising process for  $\text{HO}\bullet$  radical formation [11–13]. Therefore, the oxidation process could be accelerated. Based on this characteristic, the combination of UV-Ozone process has a potential option for wastewater treatment [14].

Since the UV-Ozone process has high beneficial result in wastewater treatment, it is important to investigate this process comprehensively. However, the utilization of the UV-Ozone process for Cu removal from electroplating wastewater is still limited. Therefore, the comparison of UV, Ozone, and UV-Ozone processes is investigated in this study. Furthermore, the effect of several operating parameters, including initial Cu concentration, ozone dosage, UV irradiation intensity, and pH value, on the Cu removal process from electroplating wastewater through photochemical (UV-Ozone) oxidation process is also comprehensively studied. In addition, the kinetic study of this process is important for scale-up processing. The study of the kinetics of wastewater treatment with a combination of UV-Ozone process for organic compound degradation has been investigated by several previous researchers [15,16]. However, to the best of our knowledge, there are no previous studies concerning the kinetic study in Cu removal from electroplating wastewater by UV-Ozone process. Some previous studies on Cu or other metals removal from wastewater are focused on investigating the process parameters affecting the process [17,18]. Based on these understandings, in this study, the kinetic models of the Cu removal process are investigated in order to determine the order of the kinetic rate. In addition, the relation of operating parameters with the kinetic parameter is also investigated comprehensively. Extendedly, the correlation between process parameters and kinetic parameter is developed. This correlation accommodates the prediction of the kinetic parameter on different process conditions. Therefore, the kinetic rate of Cu removal through photochemical oxidation can be easily predicted. The possible reaction mechanism of Cu removal using UV-Ozone process is also addressed in this study.

## 2. Materials and Method

### 2.1. Materials

This experiment was carried out using synthetic wastewater with an initial copper concentration of 145.73 mg/L. The initial concentration of samples was prepared based on the composition of copper from industrial electroplating wastewater from a plant located at Juwana, Pati, Central of Java Indonesia. Synthesized wastewater with varying copper concentrations (145.73, 72.86, and 36.9 mg/L) was prepared by dissolving the corresponding amount of  $\text{CuSO}_4\cdot 5\text{H}_2\text{O}$  (>98%, Merck) in deionized (DI) water. The initial pH value of the solution was adjusted using HCl (37%, Merck) and NaOH (>98%, Merck).

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## 2.2. Experimental System Setup

The experimental study on photochemical oxidation of copper by ozone combined with UV irradiation was conducted in a bubble column reactor made of borosilicate glass. The reactor was equipped with a low-pressure mercury UV light (Philips-TUV 8 Watt, main emission line at 253.7 nm). Ozone gas generated from ozone generator type dielectric barrier discharge (Dipo Technology, Diponegoro University) connected to reactors UV-Ozone (Figure 1). The ozone dosage was varied at 5, 10, and 15 mg/h. The UV-Ozone photoreactor was performed under a semibatch condition reaction. The reactor was an open-top cylindrical tank with a fixed top suspension with a low-pressure mercury UV light. UV irradiation intensity was varied at 20, 40, and 60 mW/cm<sup>2</sup>. The UV irradiation intensity was adjusted by varying the number of UV light. The UV irradiation intensity was measured using a J-225 Black Ray intensity meter. A fritted glass diffuser was placed at the bottom of the reactor to allow the continuous injection of ozonized gas. Ozone was produced from the air, which flows into the ozone generator. The reaction was adjusted for different time periods (i.e., 10, 20, 30, 40, 50, and 60 min) and initial pH (3, 6, 8, and 10) during UV-Ozone treatment. All oxidation reaction processes were conducted at room temperature and atmospheric pressure. The initial pH was adjusted using NaOH and HCl solutions.

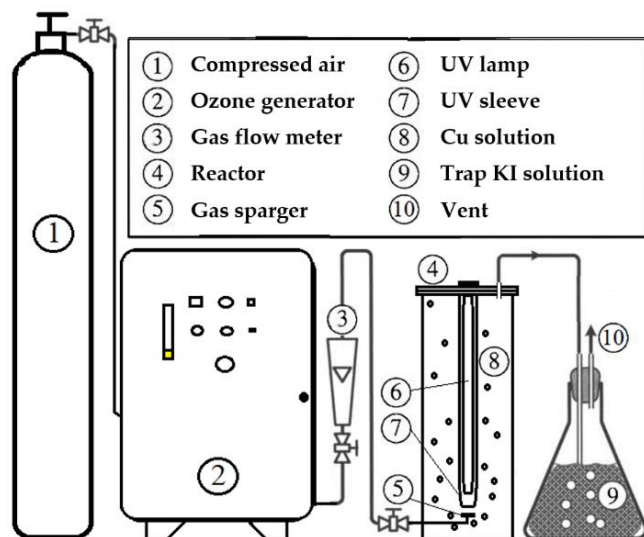


Figure 1. Schematic diagram of UV-Ozone treatment equipment.

## 2.3. Analytical Methods

A pH meter analyzer (EZDO PH-5011A) was used during the procedure for assessing the pH of the response solution. An atomic absorption spectroscopy (AAS—Quantachrome series 11.0) was used to analyze Cu concentration and wastewater samples. Even though the UV-VIS method can be used to analyze Cu concentration in the solutions, the shift on maximum wavelength absorbance at different pH could affect the inaccuracy in the measurement [19–21] since we varied the pH as one of the process parameters investigated. The solid product was also analyzed using X-ray diffraction (XRD) (Shimadzu 7000) method. The Cu K $\alpha$  radiation ( $\lambda = 1.54 \text{ \AA}$ ) was operated at 30 mA and 30 kV. The diffraction patterns were generated at  $2\theta$  angle ranges of  $20\text{--}70^\circ$  with a scanning speed of  $4^\circ \text{ min}^{-1}$ . The surface morphology and metal oxide composition of the solid product were analyzed using scanning electron microscope–energy dispersive X-ray (SEM–EDX) (SEM–EDX JEOL JSM-6510LA) method. The

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removal efficiency was calculated using Equation (1), when  $\eta$  is the Cu removal efficiency (%),  $C_0$  is the initial Cu concentration (mg/L), and  $C_t$  (mg/L) is the Cu concentration at time  $t$ .

$$\eta(\%) = \frac{C_0 - C_t}{C_0} \times 100. \quad (1)$$

### 3. Results and Discussions

#### 3.1. Comparison of UV, Ozone, and Combination UV-Ozone

In order to study the different effects of UV, Ozone, and UV-Ozone combination processes on Cu removal from electroplating wastewater, these three processes are compared. The result is shown in Figure 2.

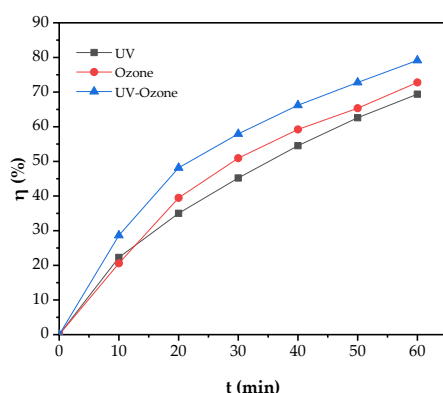


Figure 2. Comparison of UV, Ozone, and UV-Ozone combination processes.

Figure 2 depicted the comparison of UV, Ozone, and combined UV-Ozone treatment on Cu removal efficiency from electroplating wastewater. As can be seen, at 60 min of reaction, the Cu removal efficiency obtained from the UV irradiation process is 69.08%, whereas the Cu removal efficiency obtained from Ozone treatment is 72.64%. Interestingly, the Cu removal efficiency can be increased up to 78.8% when the UV and Ozone processes are combined. This high Cu removal efficiency can be obtained by the enhancement of hydroxyl radicals ( $\text{HO}\bullet$ ) during the combination of UV and Ozone processes. As reported by Hanela et al. [10], the combination of UV irradiation and ozone could enhance the production of hydroxyl radicals; therefore, the oxidation process could be accelerated. Furthermore, it is suggested that the combination of UV irradiation and Ozone treatment can increase the Cu removal efficiency in the Cu removal process from electroplating wastewater. It is true since the mechanism of Cu oxidation through AOP is initiated by the presence of  $\text{HO}\bullet$  radicals. Equations (2) and (3) represent the oxidation process of Cu through AOP. As can be seen in Equation (2), the  $\text{Cu}^{2+}$  ion is oxidized by  $\text{HO}\bullet$  radicals producing solid  $\text{CuO}$  and water molecules.



Based on Equation (2), the important thing in Cu removal through AOP is the presence of  $\text{HO}\bullet$  radicals. Therefore, it is suggested that the process of producing more  $\text{HO}\bullet$  radicals is the preferred process. As can be seen in Figure 2, the Cu removal efficiency obtained by the UV irradiation process is the lowest compared to the other processes. It is true since the UV irradiation process without the presence of ozone in the system only produces  $\text{HO}\bullet$  radicals through the photolysis of the  $\text{H}_2\text{O}$  molecule [12,22]. The photolysis of the  $\text{H}_2\text{O}$  molecule by UV irradiation is shown in Equation (4) [12].

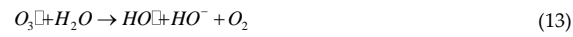
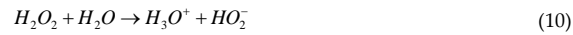
The other possible mechanisms in HO• production through the UV irradiation process are shown in Equations (5) and (6) [23].



For the Ozone treatment, as depicted in Figure 2, the Cu removal efficiency is higher than the Cu removal efficiency obtained by the UV irradiation process. This is due to the fact that the Cu oxidation through Ozone treatment can be initiated by HO• radicals and directly oxidized by the ozone molecule (Equation (3)). These two reactions occurred in Ozone treatment, therefore; the Cu removal efficiency obtained by Ozone treatment is higher than obtained by UV treatment. The chemical reaction of HO• radicals formation through Ozone treatment is shown in Equation (7) [12].



As mentioned before, the highest Cu removal efficiency is obtained by the UV-Ozone process due to the high HO• radical formation during the combination of the UV irradiation process and the Ozone process. Besides, the presence of ozone can also increase the oxidation process due to the direct oxidation process. The formation of HO• radicals in the UV-Ozone process has been widely reported. Some proposed HO• radical formation during the UV-Ozone process follow the reaction mechanism as described in Equations (8)–(10) [12,24]:



As can be seen, in the UV-Ozone process, an additional oxidant, H<sub>2</sub>O<sub>2</sub>, is generated through O<sub>3</sub> photolysis (Equation (8)) [12]. O<sub>3</sub> reacts with H<sub>2</sub>O to form H<sub>2</sub>O<sub>2</sub> under UV irradiation. This oxidant can produce more HO• radicals. H<sub>2</sub>O<sub>2</sub> absorbs UV light to generate HO• radicals. It should be noted that this process can occur only at the presence in light sources with wavelength below 300 nm [17]. Therefore, UV light is preferred rather than visible light in this study. By this fact, the Cu removal efficiency can be increased following the reaction shown in Equation (2) in the combination of UV and Ozone process. This finding is in accordance with several previous studies. In dyehouse wastewater subjected to the combination of UV-Ozone treatment, a significant color reduction, up to 98.3%, was obtained [13]. For another reason, Bes-Piá et al. [11] studied the UV-Ozone process for textile wastewater treatment. They reported that the combination of UV irradiation with ozone could significantly reduce the operating time to reach the same COD removal efficiency.

### 3.2. Characterization of the Solid Product

As reported in Section 3.1, the UV-Ozone process has the highest Cu removal efficiency compared to the other processes. The Cu removal through this process produces a solid product that is proposed as CuO, as shown in Equations (2) and (3). In order to prove that the solid product is CuO, the solid product was analyzed. Figure 3 shows the XRD pattern of the solid product obtained from the UV-Ozone process. Based on Figure 3, the characteristic peaks appear at  $2\theta$  of  $32.54^\circ$ ,  $35.56^\circ$ ,  $38.74^\circ$ ,  $48.68^\circ$ ,  $53.62^\circ$ ,  $58.16^\circ$ ,  $61.62^\circ$ ,  $66.12^\circ$ , and  $68.12^\circ$ . These peaks correspond to the CuO (tenorite phase) according to the JCPDS card number 96-900-8962. These also indicate that the formation of monoclinic crystal structure [25]. On the other hand, several studies reported that two peaks at  $2\theta = 35.6^\circ$  (002) and  $2\theta = 38.8^\circ$  (111) observed in the diffraction patterns are ascribed to the formation of the CuO (space group C2/c) monoclinic crystal phase [26,27]. In this study, these peaks appear at  $2\theta = 35.56^\circ$  and  $2\theta = 38.74^\circ$ . Therefore, it is confirmed that the solid product produced from the UV-Ozone process is CuO in the monoclinic crystal phase.

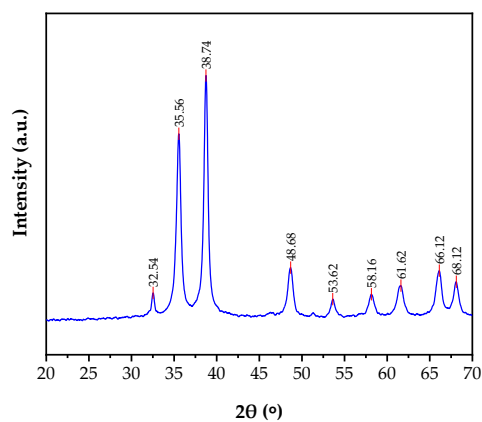
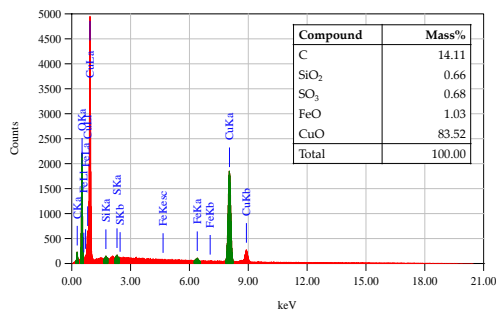


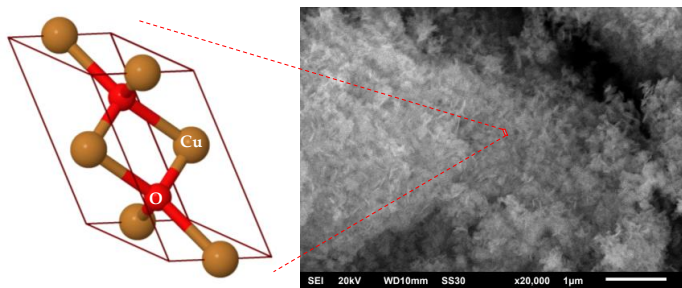
Figure 3. XRD pattern of the solid product obtained from UV-Ozone process.

The morphology and the metal oxide composition of the solid product from the UV-Ozone process are identified using SEM analysis. Based on the result of SEM-EDX analysis (Figure 4a), it is confirmed that the most metal oxide present in the solid product is CuO. The CuO content detected by SEM-EDX analysis in the solid product is 83.52%. The other components detected may be produced from the impurities in the wastewater. However, it is confirmed that the solid product is CuO. Figure 4b shows the appearance of the solid product surface (right) and the model of the CuO monoclinic crystal structure (left). As can be seen, the surface morphology of the CuO is agglomerated nanorods. Manyasree et al. [28] reported that the surface morphology of the CuO nanoparticle, which was synthesized from copper sulfate and sodium hydroxide through the coprecipitation process, is a flower-shaped structure.

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(a)



(b)

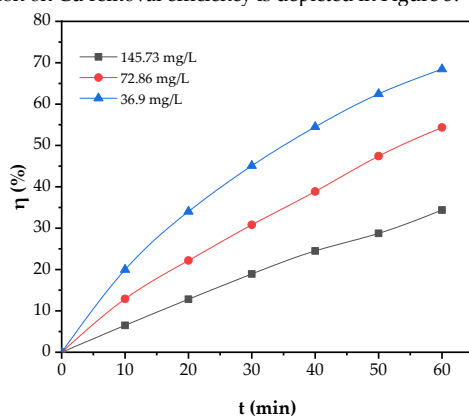
Figure 4. Composition of metal oxide in the solid product (a) and surface morphology (right) and crystal structure model (left) of the solid product (b).

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### 3.3. The Effect of Operating Parameters

#### 3.3.1. Effect of Initial Concentration

In order to study the effect of the initial Cu concentration, the photochemical oxidation process was conducted with the variation of the initial Cu concentration. The initial Cu concentration was varied at 145.73, 72.86, and 36.9 mg/L. The monitored parameter is the Cu removal efficiency. The effect of initial Cu concentration on Cu removal efficiency is depicted in Figure 5.

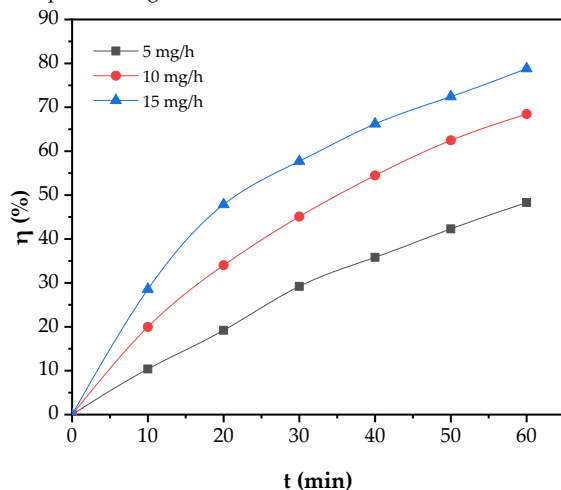


**Figure 5.** Effect of initial Cu concentration on Cu removal efficiency through photochemical process.

As can be seen in Figure 5, the Cu removal efficiency is significantly affected by the initial Cu concentration. During the oxidation process for 60 min, the Cu removal efficiency obtained at the initial Cu concentration of 145.73 mg/L is 34.39%, the Cu removal efficiency obtained at the initial Cu concentration of 72.86 mg/L is 54.36%, while the Cu removal efficiency obtained at the initial Cu concentration of 36.9 mg/L is 68.46%. Based on these results, it is suggested that the initial Cu concentration has a significant effect on the Cu removal efficiency in the Cu removal process from electroplating wastewater. Furthermore, the Cu removal efficiency decreases significantly with the increase in the initial Cu concentration from 36.9 to 145.73 mg/L. The decrease in Cu removal efficiency at high initial Cu concentration is due to the presence of a high amount of hydroxyl radical scavengers. When the initial Cu concentration is high, the photochemical oxidation process is overloaded. As a result, the Cu in the solution competes with each other during the oxidation reaction process [29]. On the other hand, in the UV irradiation process, the permeation of photons is reduced at high solution concentration; therefore, the concentration of hydroxyl radical produced is low [29]. Therefore, the oxidation of Cu decreases at high initial Cu concentration. This finding is in accordance with several previous studies in AOP. Hassan et al. [30] reported that the decolorization of Direct Yellow 50 dye in seawater through the UV-Ozone process was highly affected by the initial dye concentration, i.e., the decolorization rate decreased by increasing the dye concentration. Dai et al. [31] also reported a similar finding in the degradation of carbamazepine in water through AOP. They reported that the degradation percentage of carbamazepine decreased from 34% to 13% with an increase in the initial carbamazepine concentration from 4.2 to 42.3  $\mu\text{M}$ . Jing et al. [32] also reported that the initial aniline concentration affected the aniline degradation process through ozonation. They reported that aniline degradation decreased with the increase in the initial aniline concentration due to the overload of the ozonation process.

### 3.3.2. Effect of Ozone Dosage

In this study, the effect of ozone dosage on the Cu removal process through the photochemical oxidation process is studied by varying the ozone dosage. The ozone dosage was varied at 5, 10, and 15 mg/h. Cu removal efficiency was monitored to study this matter. The effect of ozone dosage on Cu removal efficiency is depicted in Figure 6.



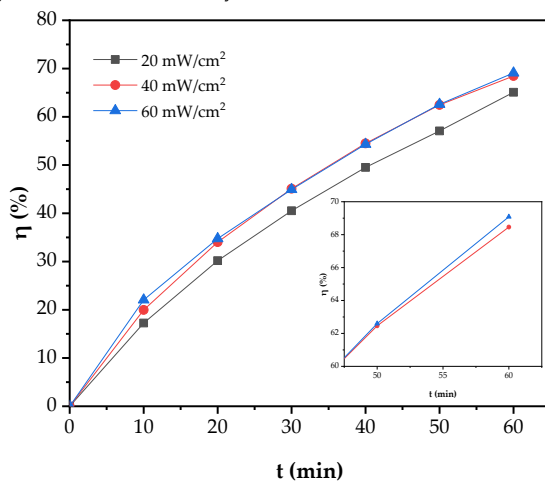
**Figure 6.** Effect of ozone dosage on Cu removal efficiency through a photochemical process.

As can be seen in Figure 6, the Cu removal efficiency increases significantly with increasing the ozone dosage. At 60 min reaction, the Cu removal efficiency obtained at ozone dosage of 5 mg/h is 48.31%, the Cu removal efficiency obtained at ozone dosage of 10 mg/h is 68.46%, while the Cu removal efficiency obtained at ozone dosage of 15 mg/h is 78.80%. Based on these results, it is suggested that the Cu removal efficiency in Cu removal from electroplating wastewater through the photochemical oxidation process is highly affected by the ozone dosage. As the ozone dosage increases, the Cu removal efficiency increases. It is true since in the ozonation process, the oxidation of Cu can occur through two different mechanisms, i.e., oxidation by HO• radicals (Equation (2)) and direct oxidation by ozone (Equation (3)). As reported by Wang et al. [33], in the ozone-based oxidation process, there are two methods, namely, indirect reaction of free radicals and direct reaction.

Pertaining to the effect of ozone dosage on HO• radical formation, when ozone dosage increases, more HO• radicals are formed. Under UV irradiation, H<sub>2</sub>O<sub>2</sub> can be formed through the reaction of ozone with H<sub>2</sub>O (Equation (8)). Furthermore, this H<sub>2</sub>O<sub>2</sub> molecule absorbs the UV light to generate the HO• radicals (Equation (9)) [24]. Ozone molecules also can react with H<sub>2</sub>O<sub>2</sub> molecules to produce HO• radicals. Besides, the ozone also can also directly react with H<sub>2</sub>O to generate HO• radicals (Equation (7)). Then, Cu is oxidized by HO• radicals. Therefore, the photochemical oxidation rate of Cu increases with the increase in ozone dosage. As a comparison, Wang et al. [33] reported that the decomplexation of electroplating wastewater by the ozone-based oxidation process increased with the increase in ozone dosage. Ren et al. [24] reported that the removal efficiency of polyacrylamide through the photochemical oxidation process increased with the increase in ozone dosage. Guo et al. [34] also reported the same result in the degradation process of sulfadiazine in water by the UV-Ozone process.

### 3.3.3. Effect of UV Irradiation Intensity

In order to study the effect of UV irradiation intensity on Cu removal from electroplating wastewater, the photochemical process was conducted by varying the UV irradiation intensity. The UV irradiation intensity was varied at 20, 40, and 60 mW/cm<sup>2</sup>. Figure 7 shows the result of the effect of UV irradiation intensity on Cu removal efficiency.



**Figure 7.** Effect of UV irradiation intensity on Cu removal efficiency through photochemical process.

As shown in Figure 7, at 60 min reaction, the Cu removal efficiency obtained at a UV irradiation intensity of 20 mW/cm<sup>2</sup> is 65.09%, the Cu removal efficiency obtained at UV irradiation intensity of 40 mW/cm<sup>2</sup> is 68.46%, while the Cu removal efficiency obtained at UV irradiation intensity of 60 mW/cm<sup>2</sup> is 69.08%. It can be concluded that the Cu photochemical oxidation rate slightly increases with the

increase in UV radiation intensity. The Cu removal efficiency slightly increases for UV irradiation of 20–40 mW/cm<sup>2</sup>. Furthermore, the Cu removal efficiency remains unchanged for UV irradiation intensity of 40–60 mW/cm<sup>2</sup>.

The increase in Cu removal efficiency with the increase in UV irradiation intensity is due to the high possibility to produce HO• radicals at high UV irradiation intensity. The possible process of HO• radical formation during UV irradiation is the photolytic dissociation of water by UV irradiation at a wavelength of 254 nm [35]. However, this process is still unclear since some studies reported that the photolytic dissociation of water to HO• radicals only can be conducted at a wavelength of less than 242 nm. Deng and Zhao [12] claimed that this process occurs at a wavelength of less than 242 nm. Furthermore, Jin et al. [22] reported that the HO• radicals could be formed through irradiation on liquid water by UV light in the range of 150–200 nm. As the UV irradiation wavelength used in this study is around 253.7 nm, the increase in Cu removal efficiency with the increase in UV irradiation intensity from 20 to 40 mW/cm<sup>2</sup> is attributed to the formation of HO• radicals through ozone photolysis producing H<sub>2</sub>O<sub>2</sub> (Equation (8)). However, high UV irradiation intensity in the ozonation process is not good. It is true since, at high UV irradiation intensity, the ozone molecule could be degraded to oxygen [36]. Therefore, the formation of HO• radicals is low at high UV irradiation intensity. Furthermore, it is suggested that the unchanged Cu removal efficiency at a UV irradiation intensity of 60 mW/cm<sup>2</sup> is due to the degradation of the ozone molecule resulting in the low formation of HO• radicals.

#### 3.3.4. Effect of pH

The efficiency of AOP can be influenced by various factors, such as the pH of the solution [37–39]. In order to study the effect of pH on the Cu removal process from electroplating wastewater through the photochemical oxidation process, the pH of solution was varied at 3, 6, 8, and 10. The result is depicted in Figure 8.

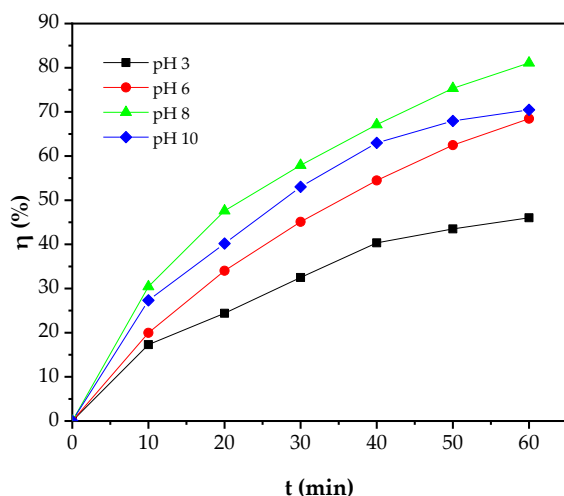


Figure 8. Effect of pH on Cu removal efficiency through photochemical process.

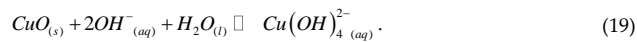
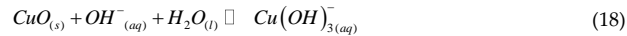
As can be seen in Figure 8, at 60 min reaction, the Cu removal efficiency obtained at pH of 3 is 46.02%, the Cu removal efficiency obtained at pH of 6 is 68.46%, the Cu removal efficiency obtained at pH of 8 is 80.09%, while the Cu removal efficiency obtained at pH of 10 is 70.46%. It can be seen that the highest Cu removal efficiency is obtained at a pH of 8. Hence, it can be concluded that the photochemical oxidation of Cu from electroplating wastewater increases with the increase in pH from 3 to 8, then it decreases with a further increase in pH to 10.



The increase in Cu removal efficiency with the increase in pH value is attributed to the high rate of HO• radical formation at high pH conditions. As reported by Muniyasamy et al. [39], in the oxidation process, pH influences the process by altering the chemical nature of ozone. At low pH conditions (acidic conditions), the decomposition of the ozone molecule to produce HO• radicals is relatively slow [40]. It was reported that the decomposition rate of ozone was sluggish below the pH of 4 [41]. Furthermore, ozone tends to remain in the molecular state at acidic conditions; however, ozone can react directly as ozone radical with the contaminants at alkaline conditions [38,42]. Therefore, the Cu removal efficiency is low at a low pH value. Furthermore, the higher the pH value, the higher the Cu removal efficiency. This tendency is attributed to the high formation of HO• radicals at the alkaline conditions. It was reported that the decomposition rate of ozone in water is better at higher pH values [43]. At alkaline conditions, ozone is unstable and rapidly decomposes into HO• radical [39,40]. The HO• radical formation through ozone decomposition occurs as follows:



As can be seen in Equations (16) and (17), the HO• radical, which is the primary oxidant in indirect oxidation [39], is produced at high pH level represented as OH<sup>-</sup>. Therefore, the Cu removal efficiency increases with the increase in pH value since the HO• radical formation is favored at a high pH level. However, the Cu removal efficiency decrease at a pH of 10. At higher pH value, CuO can dissolve to the aqueous phase due to the formation of soluble hydroxy and hydroxide complexes [44]. Therefore, Cu removal efficiency decreases. The possible dissolution mechanism of CuO at high pH value was proposed by Khan et al. [44] as follows:



### 3.4. Kinetic Study

#### 3.4.1. Determination of the Kinetic Rate Order

Three classical kinetic models are proposed to describe the Cu removal process and to determine the order or kinetic rate. These kinetic models include first-order model, second-order model, and pseudo-first-order model. The compatibility of these models is evaluated by the R<sup>2</sup> value as reported elsewhere [45]. In this work, the kinetic study of Cu removal from electroplating wastewater is considered for various initial Cu concentration ( $C_0$ ), ozone dosage ( $C_{O_3}$ ), UV irradiation intensity ( $I_{uv}$ ), and initial pH condition.

In this advanced oxidation process for Cu removal from electroplating wastewater, the mass conservation of Cu in the process can be generally expressed as:

$$-\frac{dC_t}{dt} = (-r), \quad (20)$$

where  $C_t$  (mg/L) is the concentration of Cu at time  $t$  (min) and  $(-r)$  (mg/L.min) is the rate of Cu removal. For first order model ( $-r = k_1 C_t$ ), integration of Equation (20) at the initial concentration of  $C_0$ , gives:

$$-\ln\left(\frac{C_t}{C_0}\right) = k_1 t, \quad (21)$$

where  $k_1$  (1/min) is the kinetic rate constant for first order. Further simplification of Equation (21) will give the time-dependent concentration of Cu (Equation (22)).

$$C_t = C_0 e^{-k_1 t}. \quad (22)$$

For second-order model ( $-r = k_2 C_t^2$ ), the integration of Equation (20) will give:

$$\frac{1}{C_t} = k_2 t + \frac{1}{C_0}, \quad (23)$$

where  $k_2$  (L/mg.min) is the kinetic rate constant of the second-order model. For the pseudo-first-order model ( $-r = k_p(C_t - C_e)$ ), the time-dependent concentration of Cu through the integration of Equation (20) is obtained as:

$$C_t = C_e + (C_0 - C_e)e^{-k_p t}, \quad (24)$$

where  $C_e$  (mg/L) is the concentration of Cu at equilibrium condition and  $k_p$  (1/min) is the kinetic rate constant of pseudo-first-order model.

The kinetic parameters were determined using the least-square method. As can be seen, the obtained equation for first-order and second-order kinetic models (Equations (21) and (23)) are linear equations. Therefore, the kinetic parameters ( $k_1$  and  $k_2$ ) can be obtained from the linear plot relating to these equations using the linear regression method. However, the equation derived from the pseudo-first-order kinetic model is not linear. Therefore, the kinetic parameters of the pseudo-first-order kinetic model ( $C_e$  and  $k_p$ ) are calculated using a nonlinear regression method. On the other hand, to measure the goodness of the kinetic models proposed, the squared-correlation coefficient,  $R^2$ , was used as the parameter [40,41]. The obtained kinetic parameters and  $R^2$  values for first-order, second-order, and pseudo-first-order kinetic models are shown in Table 1.

As can be seen in Table 1, all proposed models fit the data as the  $R^2$  values are close to unity. However, compared to the other proposed models, the  $R^2$  value of the second-order model is far enough from unity. Besides, the values of  $R^2$  obtained are not uniform for all data. Therefore, it is suggested that the second-order model is excluded as the proposed model to describe the kinetic rate of Cu removal. Hence, the first order and pseudo-first-order models are then considered as the most suitable proposed models to describe the kinetics of Cu removal. Considering the  $R^2$  values of the first order and pseudo-first-order models, both these two models have high goodness in describing the kinetic rate of Cu removal. However, at the initial Cu concentration,  $C_0$ , of 145.73 and 72.86 mg/L, the value of the equilibrium concentrations,  $C_e$ , obtained are zero. It indicates that at a high initial concentration of Cu in the wastewater, the kinetic rate will be increased. Furthermore, some of the  $C_e$  values are relatively low. In some cases, the theoretical value of  $C_e$  might be negative when the pseudo-first-order kinetic model is forcibly used [46]. In those cases, the pseudo-first-order model cannot be used to describe the kinetic rate. Obviously, if the value of the equilibrium concentration is zero or low enough, the pseudo-first-order model gets back to the first-order model [45,46]. Therefore, it is suggested that the most suitable model to describe the kinetic rate of Cu removal from electroplating wastewater through the photochemical oxidation process, combined UV-Ozone process, is the first-order model.

**Table 7.** Kinetic parameters of the first order, second-order, and pseudo-first-order models.

$C_0$ (mg/L)	$C_{O3}$ (mg/h)	$I_{UV}$ (mW/cm <sup>2</sup> )	pH	Kinetic Parameters						
				First-Order		Second-Order		Pseudo-First-Order		
				$k_1$ (1/min)	$R^2$	$k_2$ (L/mg.min)	$R^2$	$k_p$ (1/min)	$C_e$ (mg/L)	$R^2$
145.73	10	40	6	0.0069	0.9997	$5.673 \times 10^{-5}$	0.9921	0.0069	0.000	0.9994
72.86	10	40	6	0.0128	0.9993	$2.451 \times 10^{-4}$	0.9678	0.0127	0.000	0.9983
36.9	10	40	6	0.0196	0.9995	$8.898 \times 10^{-4}$	0.9707	0.0237	3.769	0.9995
36.9	5	40	6	0.0111	0.9998	$3.972 \times 10^{-4}$	0.9875	0.0116	1.223	0.9993
36.9	15	40	6	0.0267	0.9959	$1.480 \times 10^{-3}$	0.9624	0.0395	5.528	0.9979
36.9	10	20	6	0.0173	0.9996	$7.407 \times 10^{-4}$	0.9609	0.0188	1.850	0.9990
36.9	10	60	6	0.0198	0.9989	$9.031 \times 10^{-4}$	0.9654	0.0252	4.663	0.9969
36.9	10	40	3	0.0116	0.9847	$4.160 \times 10^{-4}$	0.9790	0.0330	12.126	0.9940
36.9	10	40	8	0.0282	0.9980	$1.650 \times 10^{-3}$	0.9359	0.0376	4.170	0.9962
36.9	10	40	10	0.0226	0.9904	$1.100 \times 10^{-3}$	0.9909	0.0381	7.725	0.9970

The kinetic study of Cu removal using an advanced oxidation process has been widely reported. However, the kinetic study of Cu removal using the photochemical oxidation process, UV-Ozone

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process, is still limited. The most-reported process is the electrochemical/electrocoagulation process. Al-Shannag et al. [45] reported that the electrocoagulation of heavy metals from wastewater, including Cu, followed a pseudo-first-order model. Using the same method, Vasudevan and Lakshmi [47] reported that the electrocoagulation of Cu from water follows the second-order model. Furthermore, Khattab et al. [48] reported that Cu removal through the electrochemical process follows the first-order kinetic model.

### 3.4.2. The Effect of Operating Parameters on Kinetic Rate Constant

The kinetic rate behavior of Cu removal using the photochemical oxidation process, combined UV-Ozone process, follows the first-order kinetic model as reported in Section 3.3.1. The value of the kinetic rate constant of the first-order model,  $k_1$ , is presented in Table 1. As can be observed, the value of  $k_1$  is varied as the variation of operating parameters, including  $C_0$ ,  $C_{O_3}$ ,  $I_{UV}$ , and pH. The value of  $k_1$  increases with a decrease in  $C_0$ . Furthermore, the value of  $k_1$  increases with the increase in  $C_{O_3}$ ,  $I_{UV}$ , and pH. However, at a pH of 10, the value of  $k_1$  decreases. These phenomena indicate that the value of the observed  $k_1$  is affected by the operating parameters. This is in accordance with some previous studies that the kinetic rate constant of the advanced oxidation process, especially the UV-Ozone process, is affected by the operating parameters [24,49]. The operating parameters-dependent of the kinetic rate constant can be mathematically written as Equations (25) and (26) where  $\varepsilon$  is the pre-exponent constant, whereas  $a$ ,  $b$ ,  $c$ , and  $d$  are the exponent constant characteristic of  $C_0$ ,  $C_{O_3}$ ,  $I_{UV}$ , and pH, respectively. The linear form of Equation (26) is shown as Equation (27).

$$k_1 = f(C_0, C_{O_3}, I_{UV}, pH) \quad (25)$$

$$k_1 = \varepsilon C_0^a C_{O_3}^b I_{UV}^c pH^d \quad (26)$$

$$\ln k_1 = \ln \varepsilon + a \ln C_0 + b \ln C_{O_3} + c \ln I_{UV} + d \ln pH \quad (27)$$

Based on Equation (27), the value of  $\varepsilon$ ,  $a$ ,  $b$ ,  $c$ , and  $d$  can be obtained using multiple regression analysis which also has been used elsewhere [49]. However, the value of  $k_1$  at a pH of 10 is not included in this calculation because it does not follow the tendency. Table 2 shows the result of the multiple regression analysis. As can be seen, the  $p$ -value of the coefficients obtained for each parameter is lower than 0.05. This indicates that the coefficients obtained are significant. However, the  $p$ -value of  $\ln I_{UV}$  coefficient is higher than 0.05, which indicates that this coefficient is not significant. Table 3 shows the result of the analysis of variance (ANOVA) of the multiple regression analysis. As can be observed, the value of multiple R,  $R^2$ , and adjusted  $R^2$  is close to unity. These indicate that the obtained regression equation fits the data. Furthermore, the obtained  $F$ -value (113.4928) is higher than the  $F$ -table or theoretical  $F$ -value ( $F_{0.05(4,7)}$ ) is 6.09.

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Table 2. Multiple regression analysis result.

Parameters	Coefficients	Standard Error	$p$ -value
Intercept	-5.1661	0.3951	$3.5663 \times 10^{-6}$
$\ln C_0$	-0.7401	0.0441	$6.4919 \times 10^{-7}$
$\ln C_{O_3}$	0.8154	0.0778	$1.5626 \times 10^{-5}$
$\ln I_{UV}$	0.1441	0.0778	0.1064
$\ln pH$	0.8407	0.0839	$2.1105 \times 10^{-5}$

**Table 3.** Summary of the analysis of variance (ANOVA).

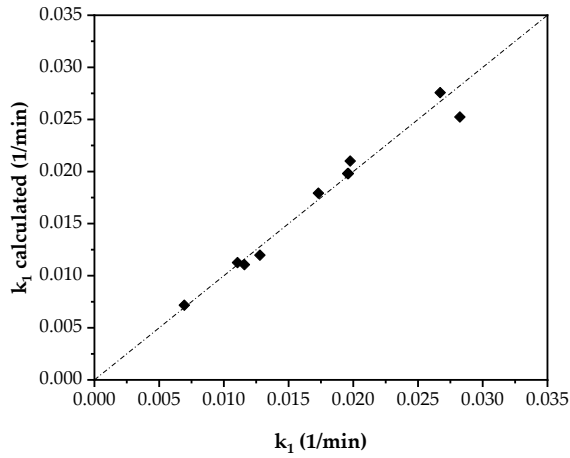
	<i>df</i>	<i>SS</i>	<i>MS</i>	<i>F</i>	<i>Significance F</i>
Regression	4	1.7467	0.4367	113.4928	$1.9188 \times 10^{-6}$
Residual	7	0.0269	0.0038		
Total	11	1.7736			
Multiple R	0.9924				
R <sup>2</sup>	0.9848				
Adjusted R <sup>2</sup>	0.9761				
Standard error	0.0620				

Based on the result of the multiple regression analysis (Table 2), Equation (27) can be rewritten as Equation (28). Furthermore, Equation (26) can be rewritten as Equation (29) with the value of  $\varepsilon$  constant calculated from the natural exponential of the intercept of Equation (28). The obtained value of  $k_t$  was then compared to the calculated value of  $k_t$  using Equation (29). The comparison of the observed  $k_t$  and calculated  $k_t$  is depicted in Figure 9. It is clear that the observed and calculated values of  $k_t$  are in good fit as the R<sup>2</sup> is close to unity (0.9848). By combining the Equations (1), (22), and (29), the calculated Cu removal efficiency can be rewritten as Equation (30). Furthermore, the comparison of the Cu removal efficiency between the observed value and the calculated value is also depicted in Figure 10.

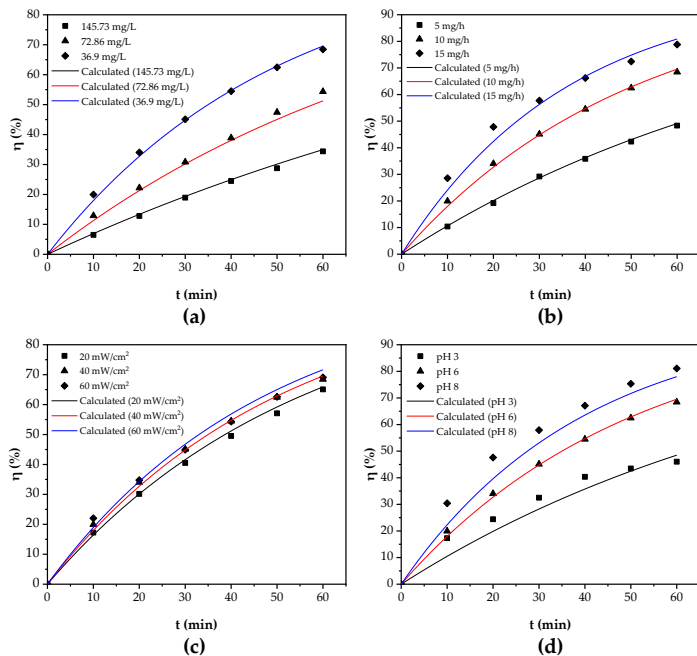
$$\ln k_t = -5.1661 - 0.7401 \ln C_0 + 0.8154 \ln C_{O_2} + 0.1441 \ln I_{UV} + 0.8407 \ln pH \quad (28)$$

$$k_t = (5.7068 \times 10^{-3}) C_0^{-0.7401} C_{O_2}^{0.8154} I_{UV}^{0.1441} pH^{0.8407} \quad (29)$$

$$\eta_{cal} (\%) = 100 - 100 \exp\left(- (5.7068 \times 10^{-3}) C_0^{-0.7401} C_{O_2}^{0.8154} I_{UV}^{0.1441} pH^{0.8407} t\right). \quad (30)$$



**Figure 9.** Comparison of observed and calculated value of  $k_t$ .



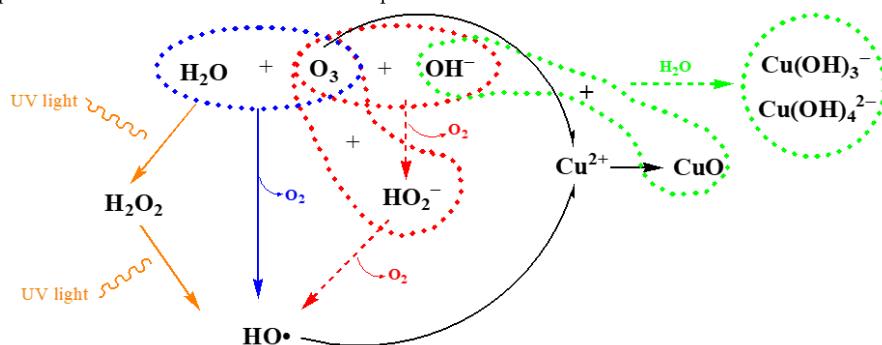
**Figure 230.** Comparison of data and calculated Cu removal efficiency at (a) varied  $C_0$ , (b) varied  $C_{O_3}$ , (c) varied  $I_{UV}$ , and (d) varied pH.

As can be seen in Table 2 and Equation (29), the exponent characteristic value of  $C_0$  is in a negative value. It indicates that the value of the initial Cu concentration is inversely proportional to the  $k_1$  value. This finding is in accordance with the finding of Ren et al. [24]. They reported that the initial concentration of polyacrylamide in the UV-Ozone process of polyacrylamide oxidation is inversely proportional to the kinetic rate constant value. Concerning the effect of UV and ozone treatment in this oxidation process, the value of the exponent characteristic of  $C_{O_3}$  and  $I_{UV}$  can be used to study this matter [49]. As can be seen, the exponent characteristic value of  $C_{O_3}$  is higher than  $I_{UV}$ . It is suggested that the ozone dosage is more significant in this oxidation process than UV irradiation intensity. This finding is in accordance with the previous study of the UV-Ozone process. The UV-Ozone process was conducted for  $\kappa$ -Carrageenan treatment, and the result showed that the ozone dosage was more significant than UV irradiation intensity [49]. Furthermore, the value of the exponent characteristic of  $I_{UV}$  is low enough, and it is close to zero. It indicates that the UV irradiation intensity is not significant enough for the Cu removal process from wastewater. In the case of the effect of pH on  $k_1$  value, it is clear that the pH has a significant effect on  $k_1$  value as the value of the exponent characteristic of pH is high. It is true because the metal oxidation process in an aqueous solution is affected by the presence of  $OH^-$  ions, which can promote the formation of  $HO\bullet$  radicals. On the other hand, the solubility of metal in aqueous solution is also affected by the pH value [44].

### 3.5. Proposed Mechanism

Based on the explanation in previous sections, the mechanism of Cu removal from electroplating wastewater through the UV-Ozone process is developed. Figure 11 shows the proposed mechanism in this study. As reported in several studies, the oxidation through AOPs is initiated by the formation of  $HO\bullet$  radical because the main oxidizing agent is  $HO\bullet$  radical [50,51]. Based on several findings

obtained in this study (reported in the previous sections), the HO• radical formation takes place through three different steps. In Figure 11, these steps are represented in orange, blue, and red arrows. The orange arrows represent the HO• radical formation through the UV-Ozone process. The blue arrow represents the direct ozonation of water producing HO• radicals releasing O<sub>2</sub> molecules. Furthermore, the red arrows represent the ozone degradation producing HO• radicals in alkaline condition releasing O<sub>2</sub> molecules. The red arrow is depicted in dash-line arrow type, this indicates that this process occurs in alkaline condition only due to the presence of OH<sup>-</sup> ions. At acidic condition, this process does not occur as OH<sup>-</sup> ions are not present.



**Figure 11.** Proposed mechanism of Cu removal from electroplating wastewater through UV-Ozone process.

After the formation of HO• radicals occurred, the next step is the oxidation process. This process, depicted in black arrows, includes direct and indirect oxidation since the oxidating agents in this UV-Ozone process are HO• radicals and ozone molecules. Both HO• radicals and O<sub>3</sub> react with Cu<sup>2+</sup> to form solid CuO. The oxidation process of Cu<sup>2+</sup> to CuO by HO• radicals is called indirect oxidation, whereas the oxidation process of Cu<sup>2+</sup> by O<sub>3</sub> molecules is called direct oxidation. Based on Figure 11, as the HO• radicals and O<sub>3</sub> molecules increase in the system, the CuO product produced increases. It means that the Cu removal from the electroplating wastewater increases. However, this CuO product can dissolve in an alkaline condition. As can be seen in Figure 11, if the OH<sup>-</sup> ions are excessively present in the system, the CuO product will dissolve. This process is depicted as a dash-arrow in green indicating that this process occurs in alkaline condition only due to the presence of excessive OH<sup>-</sup> ions. The dissolution of CuO to the aqueous phase in the alkaline condition is due to the formation of soluble hydroxy and hydroxide complexes [44].

Based on this proposed mechanism (Figure 11), it can be observed that the presence of the ozone molecule is important in this oxidation process. The ozone molecules have roles both to generate the HO• radicals and to oxidize the Cu directly. This is in accordance with the finding reported in Section 3.4 that the ozone dosage significantly affected the kinetic rate. On the other hand, the presence of UV irradiation assists the ozone photolysis process to produce HO• radicals through the formation of an intermediate oxidating agent, H<sub>2</sub>O<sub>2</sub>. Furthermore, the pH is also important in this mechanism. As can be seen in Figure 11, suitable alkaline condition accelerates the formation of HO• radicals. However, the high alkaline condition has a negative effect on the Cu removal process due to the CuO dissolution process in high alkaline condition. The excessive OH<sup>-</sup> ions catch the solid CuO to form soluble hydroxy and hydroxide complexes decreasing the Cu removal efficiency.

#### 4. Conclusions

The photochemical oxidation process of Cu from electroplating wastewater has been investigated. It is shown that the UV-Ozone process has high performance on Cu removal compared to UV and Ozone processes due to the high production rate of HO• radicals as the oxidant and due to the direct

oxidation by ozone. Furthermore, this process produced a CuO monoclinic crystal phase as a solid product. The initial Cu concentration, ozone dosage, and pH value have a significant effect on Cu removal efficiency. The initial Cu concentration significantly reduces Cu removal efficiency. As expected, the ozone dosage increases the Cu removal efficiency since it is responsible for HO• radical formation and direct oxidation. Furthermore, the Cu removal efficiency increases with the increase in pH value from 3 to 8. However, a further increase in pH value reduces the Cu removal efficiency due to the formation of soluble hydroxy and hydroxide complexes of Cu at the alkaline conditions. Interestingly, it is found that the UV irradiation intensity is not significant in the photochemical oxidation process on Cu from electroplating wastewater. However, it is responsible to promote the ozone photolysis producing HO• radicals through H<sub>2</sub>O<sub>2</sub> formation. It is found that the kinetic behavior of the photochemical oxidation of Cu follows the first-order kinetic model. Furthermore, the relation between the operating parameters and kinetic rate constant is also established. In addition, the mechanism of Cu removal through the UV-Ozone process was also proposed concerning the findings obtained in this study.

**Author Contributions:** Conceptualization, A.P., M.D., and T.R.; methodology, A.P.; software, T.R.; validation, A.P., T.R., M.D., and W.W.; formal analysis, A.P.; investigation, A.P. and M.D.; resources, T.R.; data curation, W.W.; writing—original draft preparation, A.P. and T.R.; writing—review and editing, W.W.; visualization, A.P.; supervision, A.P.; project administration, A.P. All authors have read and agreed to the published version of the manuscript.

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# Photochemical Oxidation Process of Copper from Electroplating Wastewater: Process Performance and Kinetic Study

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**Abstract:** An investigation of the process of ozone combined with ultraviolet radiation has been carried out in order to establish the kinetics for photochemical oxidation of copper (Cu) from electroplating wastewater. The effects of operating parameters, including initial Cu concentration, ozone dosage, UV irradiation intensity, and pH value on the photochemical oxidation of Cu have been studied comprehensively. The Cu concentration during the reaction was identified using atomic absorption spectroscopy (AAS) method. The solid product was analyzed using X-ray diffraction (XRD) and scanning electron microscope–energy-dispersive X-ray (SEM–EDX) methods. It was found that the UV–Ozone process has high performance on Cu removal compared to UV and Ozone processes due to the high production rate of HO• radicals. It was also found that the solid product from the UV–Ozone process was CuO monoclinic crystal phase. The initial Cu concentration, ozone dosage, and pH value were significantly affected the Cu removal efficiency. On the other hand, the UV irradiation intensity was not significant; however, it has responsibility in promoting the ozone photolysis. The kinetics model for the photochemical oxidation of Cu was established following the first-order kinetic model. Furthermore, the reaction mechanism was also developed.

**Keywords:** photochemical oxidation; Cu; kinetics; ozone; ultraviolet irradiation; advanced oxidation process

## 1. Introduction

Heavy metals have become a global issue of environmental and public health concern because of their toxicity and bioaccumulation in the human body and food chain [1]. The effects of urbanization and industrialization cause an increase in heavy metal pollution to the environment [2]. High toxicity and nonbiodegradability of heavy metals caused a number of environmental problems [3]. The accumulation of heavy metals in the atmosphere is responsible for both natural and anthropogenic activities [4]. Copper (Cu), as an essential trace element, is required by biological systems for the activation of some enzymes during photosynthesis. However, at higher concentrations, it shows harmful effects on the human body. Continuous exposure may lead to kidney damage and even death. Cu is also toxic to a variety of aquatic organisms even at very low concentrations. Mining, metallurgy, and industrial applications are the major sources of Cu exposure in the environment [5].

There were several techniques for the treatment of industrial wastewater containing heavy metals, including chemical precipitation, ion exchange, coagulation–flocculation, flotation, membrane filtration, electrochemical treatment, magnetic separation and purification, biosorption, and nanotechnology [6]. Advanced oxidation processes (AOPs) are promising, efficient, and environmentally friendly methods for the removal of wastewater contaminants [7]. The AOPs can be

photochemical AOP, sonochemical AOP, and electrochemical AOP [7]. The basic principles of AOPs are the in situ generations of hydroxyl radicals ( $\text{HO}\bullet$ ) during the oxidation process. The hydroxyl radicals can be produced from hydrogen peroxide ( $\text{H}_2\text{O}_2$ ), ozone, photocatalysis, or oxidants in combination with ultraviolet (UV) radiation [8].

Ozone is an active oxidant, which is commercially available and widely used in municipal water treatment and wastewater treatment. Moreover, wastewater treatment with ozone is an environment-friendly method. The pollutants such as color, odor, and microorganisms are oxidized directly without generating harmful chlorinated by-products or substantial residues [9]. In order to increase the effectivity of the ozonation process, it is necessary to combine the ozone process with another process that can increase the reaction efficiency between ozone and pollutant. The promising process is the combination of ozone and UV irradiation that could enhance the production of hydroxyl radicals ( $\text{HO}\bullet$ ) as the main oxidant compounds in AOP [10]. The combination of UV-Ozone process has been reported as a promising process for  $\text{HO}\bullet$  radical formation [11–13]. Therefore, the oxidation process could be accelerated. Based on this characteristic, the combination of UV-Ozone process has a potential option for wastewater treatment [14].

Since the UV-Ozone process has high beneficial result in wastewater treatment, it is important to investigate this process comprehensively. However, the utilization of the UV-Ozone process for Cu removal from electroplating wastewater is still limited. Therefore, the comparison of UV, Ozone, and UV-Ozone processes is investigated in this study. Furthermore, the effect of several operating parameters, including initial Cu concentration, ozone dosage, UV irradiation intensity, and pH value, on the Cu removal process from electroplating wastewater through photochemical (UV-Ozone) oxidation process is also comprehensively studied. In addition, the kinetic study of this process is important for scale-up processing. The study of the kinetics of wastewater treatment with a combination of UV-Ozone process for organic compound degradation has been investigated by several previous researchers [15,16]. However, to the best of our knowledge, there are no previous studies concerning the kinetic study in Cu removal from electroplating wastewater by UV-Ozone process. Some previous studies on Cu or other metals removal from wastewater are focused on investigating the process parameters affecting the process [17,18]. Based on these understandings, in this study, the kinetic models of the Cu removal process are investigated in order to determine the order of the kinetic rate. In addition, the relation of operating parameters with the kinetic parameter is also investigated comprehensively. Extendedly, the correlation between process parameters and kinetic parameter is developed. This correlation accommodates the prediction of the kinetic parameter on different process conditions. Therefore, the kinetic rate of Cu removal through photochemical oxidation can be easily predicted. The possible reaction mechanism of Cu removal using UV-Ozone process is also addressed in this study.

## 2. Materials and Method

### 2.1. Materials

This experiment was carried out using synthetic wastewater with an initial copper concentration of 145.73 mg/L. The initial concentration of samples was prepared based on the composition of copper from industrial electroplating wastewater from a plant located at Juwana, Pati, Central of Java Indonesia [which has copper concentration of 145.73 mg/L](#). Synthesized wastewater with varying copper concentrations (145.73, 72.86, and 36.9 mg/L) was prepared by dissolving the corresponding amount of  $\text{CuSO}_4\cdot 5\text{H}_2\text{O}$  (>98%, Merck) in deionized (DI) water. The initial pH value of the solution was adjusted using HCl (37%, Merck) and NaOH (>98%, Merck).

## 2.2. Experimental System Setup

The experimental study on photochemical oxidation of copper by ozone combined with UV irradiation was conducted in a bubble column reactor made of borosilicate glass. The reactor was equipped with a low-pressure mercury UV light (Philips–TUV 8 Watt, [Koninklijke Philips N.V.](#)) with main emission line at 253.7 nm. Ozone gas generated from ozone generator type dielectric barrier discharge (Dipo Technology, Diponegoro University) connected to reactors UV-Ozone (Figure 1). The ozone dosage was varied at 5, 10, and 15 mg/h. The UV-Ozone photoreactor was performed under a semibatch condition reaction. The reactor was an open-top cylindrical tank with a fixed top suspension with a low-pressure mercury UV light. UV irradiation intensity was varied at 20, 40, and 60 mW/cm<sup>2</sup>. The UV irradiation intensity was adjusted by varying the number of UV light. The UV irradiation intensity was measured using a J-225 Black Ray intensity meter ([Analytik Jena US](#)). A fritted glass diffuser was placed at the bottom of the reactor to allow the continuous injection of ozonized gas. Ozone was produced from the air, which flows into the ozone generator. The reaction was adjusted for different time periods (i.e., 10, 20, 30, 40, 50, and 60 min) and initial pH (3, 6, 8, and 10) during UV-Ozone treatment. All oxidation reaction processes were conducted at room temperature and atmospheric pressure. The initial pH was adjusted using NaOH and HCl solutions.

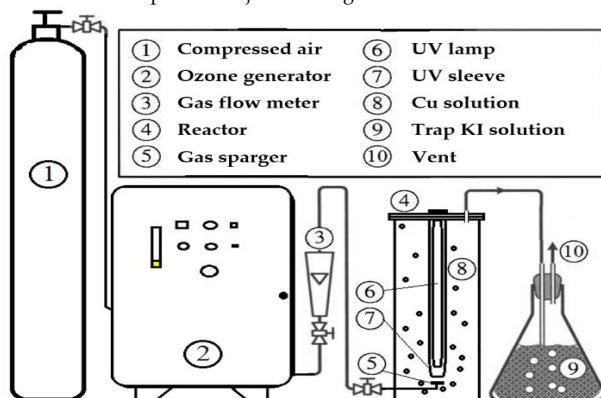


Figure 1. Schematic diagram of UV-Ozone treatment equipment.

## 2.3. Analytical Methods

A pH meter analyzer (EZDO PH-5011A) was used during the procedure for assessing the pH of the response solution. An atomic absorption spectroscopy (AAS) (Shimadzu AA 6300, [Japan](#)) was used to analyze Cu concentration in the solutions, the shift on maximum wavelength absorbance at different pH could affect the inaccuracy in the measurement [19–21] since we varied the pH as one of the process parameters investigated. The solid product was also analyzed using X-ray diffraction (XRD) (Shimadzu XRD-7000, [Japan](#)) method. The Cu K $\alpha$  radiation ( $\lambda = 1.54 \text{ \AA}$ ) was operated at 30 mA and 30 kV. The diffraction patterns were generated at  $2\theta$  angle ranges of  $20\text{--}70^\circ$  with a scanning speed of  $4^\circ \text{ min}^{-1}$ . The surface morphology and metal oxide composition of the solid product were analyzed using scanning electron microscope–energy dispersive X-ray (SEM–EDX) (SEM-EDX JEOL JSM-6510LA, [Japan](#)) method. The removal efficiency was calculated using Equation (1), when  $\eta$  is the Cu removal efficiency (%),  $C_0$  is the initial Cu concentration (mg/L), and  $C_t$  (mg/L) is the Cu concentration at time  $t$ .

$$\eta(\%) = \frac{C_0 - C_t}{C_0} \times 100. \quad (1)$$

## 3. Results and Discussions

### 3.1. Comparison of UV, Ozone, and Combination UV-Ozone

In order to study the different effects of UV, Ozone, and UV-Ozone combination processes on Cu removal from electroplating wastewater, these three processes are compared. The result is shown in Figure 2.

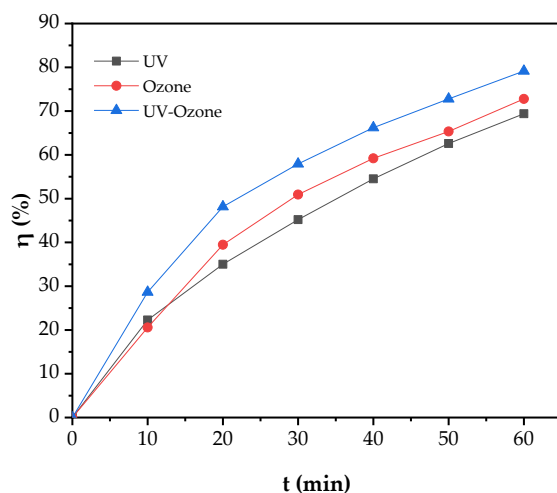
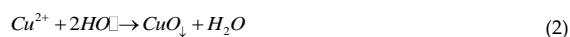


Figure 2. Comparison of UV, Ozone, and UV-Ozone combination processes.

Figure 2 depicted the comparison of UV, Ozone, and combined UV-Ozone treatment on Cu removal efficiency from electroplating wastewater. As can be seen, at 60 min of reaction, the Cu removal efficiency obtained from the UV irradiation process is 69.08%, whereas the Cu removal efficiency obtained from Ozone treatment is 72.64%. Interestingly, the Cu removal efficiency can be increased up to 78.8% when the UV and Ozone processes are combined. This high Cu removal efficiency can be obtained by the enhancement of hydroxyl radicals ( $\text{HO}\bullet$ ) during the combination of UV and Ozone processes. As reported by Hanela et al. [10], the combination of UV irradiation and ozone could enhance the production of hydroxyl radicals; therefore, the oxidation process could be accelerated. Furthermore, it is suggested that the combination of UV irradiation and Ozone treatment can increase the Cu removal efficiency in the Cu removal process from electroplating wastewater. It is true since the mechanism of Cu oxidation through AOP is initiated by the presence of  $\text{HO}\bullet$  radicals. Equations (2) and (3) represent the oxidation process of Cu through AOP. As can be seen in Equation (2), the  $\text{Cu}^{2+}$  ion is oxidized by  $\text{HO}\bullet$  radicals producing solid  $\text{CuO}$  and water molecules.



Based on Equation (2), the important thing in Cu removal through AOP is the presence of  $\text{HO}\bullet$  radicals. Therefore, it is suggested that the process of producing more  $\text{HO}\bullet$  radicals is the preferred process. As can be seen in Figure 2, the Cu removal efficiency obtained by the UV irradiation process is the lowest compared to the other processes. It is true since the UV irradiation process without the presence of ozone in the system only produces  $\text{HO}\bullet$  radicals through the photolysis of the  $\text{H}_2\text{O}$  molecule [12,22]. The photolysis of the  $\text{H}_2\text{O}$  molecule by UV irradiation is shown in Equation (4) [12]. The other possible mechanisms in  $\text{HO}\bullet$  production through the UV irradiation process are shown in Equations (5) and (6) [23].

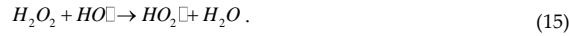
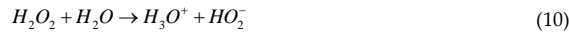




For the Ozone treatment, as depicted in Figure 2, the Cu removal efficiency is higher than the Cu removal efficiency obtained by the UV irradiation process. This is due to the fact that the Cu oxidation through Ozone treatment can be initiated by HO• radicals and directly oxidized by the ozone molecule (Equation (3)). These two reactions occurred in Ozone treatment, therefore; the Cu removal efficiency obtained by Ozone treatment is higher than obtained by UV treatment. The chemical reaction of HO• radicals formation through Ozone treatment is shown in Equation (7) [12].



As mentioned before, the highest Cu removal efficiency is obtained by the UV-Ozone process due to the high HO• radical formation during the combination of the UV irradiation process and the Ozone process. Besides, the presence of ozone can also increase the oxidation process due to the direct oxidation process. The formation of HO• radicals in the UV-Ozone process has been widely reported. Some proposed HO• radical formation during the UV-Ozone process follow the reaction mechanism as described in Equations (8)–(10) [12,24]:

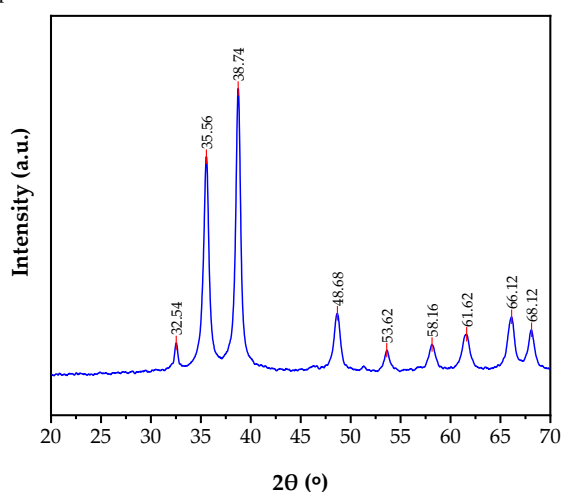


As can be seen, in the UV-Ozone process, an additional oxidant, H<sub>2</sub>O<sub>2</sub>, is generated through O<sub>3</sub> photolysis (Equation (8)) [12]. O<sub>3</sub> reacts with H<sub>2</sub>O to form H<sub>2</sub>O<sub>2</sub> under UV irradiation. This oxidant can produce more HO• radicals. H<sub>2</sub>O<sub>2</sub> absorbs UV light to generate HO• radicals. It should be noted that this process can occur only at the presence in light sources with wavelength below 300 nm [17]. Therefore, UV light is preferred rather than visible light in this study. By this fact, the Cu removal efficiency can be increased following the reaction shown in Equation (2) in the combination of UV and Ozone process. This finding is in accordance with several previous studies. In dyehouse wastewater subjected to the combination of UV-Ozone treatment, a significant color reduction, up to 98.3%, was obtained [13]. For another reason, Bes-Piá et al. [11] studied the UV-Ozone process for textile wastewater treatment. They reported that the combination of UV irradiation with ozone could significantly reduce the operating time to reach the same COD removal efficiency.

### 3.2. Characterization of the Solid Product

As reported in Section 3.1, the UV-Ozone process has the highest Cu removal efficiency compared to the other processes. The Cu removal through this process produces a solid product that is proposed as CuO, as shown in Equations (2) and (3). In order to prove that the solid product is CuO, the solid product was analyzed. Figure 3 shows the XRD pattern of the solid product obtained from the UV-Ozone process. Based on Figure 3, the characteristic peaks appear at 2θ of 32.54°, 35.56°, 38.74°, 48.68°,

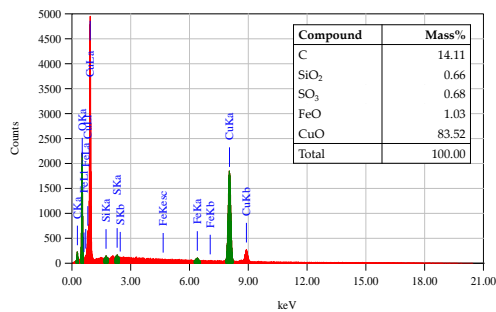
53.62°, 58.16°, 61.62°, 66.12°, and 68.12°. These peaks correspond to the CuO (tenorite phase) according to the JCPDS card number 96-900-8962. These also indicate that the formation of monoclinic crystal structure [25]. On the other hand, several studies reported that two peaks at  $2\theta = 35.6^\circ$  (002) and  $2\theta = 38.8^\circ$  (111) observed in the diffraction patterns are ascribed to the formation of the CuO (space group C2/c) monoclinic crystal phase [26,27]. In this study, these peaks appear at  $2\theta = 35.56^\circ$  and  $2\theta = 38.74^\circ$ . Therefore, it is confirmed that the solid product produced from the UV-Ozone process is CuO in the monoclinic crystal phase.



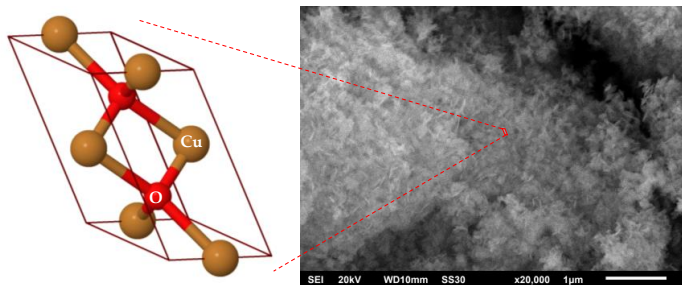
**Figure 3.** XRD pattern of the solid product obtained from UV-Ozone process.

The morphology and the metal oxide composition of the solid product from the UV-Ozone process are identified using SEM analysis. Based on the result of SEM-EDX analysis (Figure 4a), it is confirmed that the most metal oxide present in the solid product is CuO. The CuO content detected by SEM-EDX analysis in the solid product is 83.52%. The other components detected may be produced from the impurities in the wastewater. However, it is confirmed that the solid product is CuO. Figure 4b shows the appearance of the solid product surface (right) and the model of the CuO monoclinic crystal structure (left). As can be seen, the surface morphology of the CuO is agglomerated nanorods. Manyasree et al. [28] reported that the surface morphology of the CuO nanoparticle, which was synthesized from copper sulfate and sodium hydroxide through the coprecipitation process, is a flower-shaped structure.





(a)



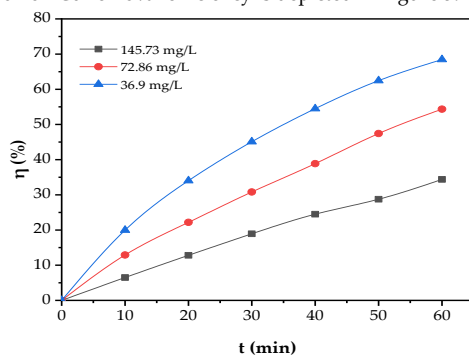
(b)

**Figure 4.** Composition of metal oxide in the solid product (a) and surface morphology (right) and crystal structure model (left) of the solid product (b).

### 3.3. The Effect of Operating Parameters

#### 3.3.1. Effect of Initial Concentration

In order to study the effect of the initial Cu concentration, the photochemical oxidation process was conducted with the variation of the initial Cu concentration. The initial Cu concentration was varied at 145.73, 72.86, and 36.9 mg/L. The monitored parameter is the Cu removal efficiency. The effect of initial Cu concentration on Cu removal efficiency is depicted in Figure 5.



**Figure 5.** Effect of initial Cu concentration on Cu removal efficiency through photochemical process.

As can be seen in Figure 5, the Cu removal efficiency is significantly affected by the initial Cu concentration. During the oxidation process for 60 min, the Cu removal efficiency obtained at the initial Cu concentration of 145.73 mg/L is 34.39%, the Cu removal efficiency obtained at the initial Cu concentration of 72.86 mg/L is 54.36%, while the Cu removal efficiency obtained at the initial Cu concentration of 36.9 mg/L is 68.46%. Based on these results, it is suggested that the initial Cu concentration has a significant effect on the Cu removal efficiency in the Cu removal process from electroplating wastewater. Furthermore, the Cu removal efficiency decreases significantly with the increase in the initial Cu concentration from 36.9 to 145.73 mg/L. The decrease in Cu removal efficiency at high initial Cu concentration is due to the presence of a high amount of hydroxyl radical scavengers. When the initial Cu concentration is high, the photochemical oxidation process is overloaded. As a result, the Cu in the solution competes with each other during the oxidation reaction process [29]. On the other hand, in the UV irradiation process, the permeation of photons is reduced at high solution concentration; therefore, the concentration of hydroxyl radical produced is low [29]. Therefore, the oxidation of Cu decreases at high initial Cu concentration. This finding is in accordance with several previous studies in AOP. Hassan et al. [30] reported that the decolorization of Direct Yellow 50 dye in seawater through the UV-Ozone process was highly affected by the initial dye concentration, i.e., the decolorization rate decreased by increasing the dye concentration. Dai et al. [31] also reported a similar finding in the degradation of carbamazepine in water through AOP. They reported that the degradation percentage of carbamazepine decreased from 34% to 13% with an increase in the initial carbamazepine concentration from 4.2 to 42.3  $\mu\text{M}$ . Jing et al. [32] also reported that the initial aniline concentration affected the aniline degradation process through ozonation. They reported that aniline degradation decreased with the increase in the initial aniline concentration due to the overload of the ozonation process.

### 3.3.2. Effect of Ozone Dosage

In this study, the effect of ozone dosage on the Cu removal process through the photochemical oxidation process is studied by varying the ozone dosage. The ozone dosage was varied at 5, 10, and 15 mg/h. Cu removal efficiency was monitored to study this matter. The effect of ozone dosage on Cu removal efficiency is depicted in Figure 6.

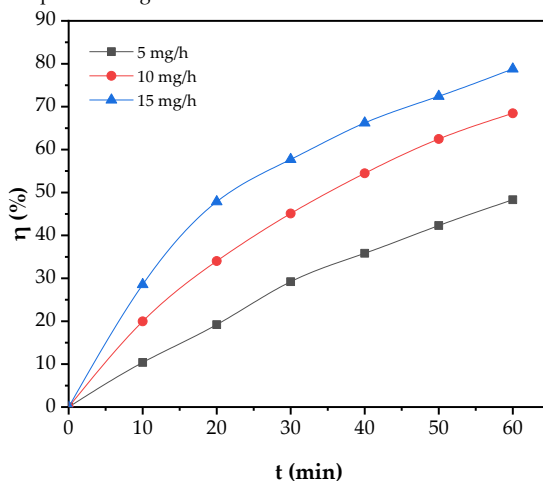


Figure 6. Effect of ozone dosage on Cu removal efficiency through a photochemical process.

As can be seen in Figure 6, the Cu removal efficiency increases significantly with increasing the ozone dosage. At 60 min reaction, the Cu removal efficiency obtained at ozone dosage of 5 mg/h is

48.31%, the Cu removal efficiency obtained at ozone dosage of 10 mg/h is 68.46%, while the Cu removal efficiency obtained at ozone dosage of 15 mg/h is 78.80%. Based on these results, it is suggested that the Cu removal efficiency in Cu removal from electroplating wastewater through the photochemical oxidation process is highly affected by the ozone dosage. As the ozone dosage increases, the Cu removal efficiency increases. It is true since in the ozonation process, the oxidation of Cu can occur through two different mechanisms, i.e., oxidation by HO• radicals (Equation (2)) and direct oxidation by ozone (Equation (3)). As reported by Wang et al. [33], in the ozone-based oxidation process, there are two methods, namely, indirect reaction of free radicals and direct reaction.

Pertaining to the effect of ozone dosage on HO• radical formation, when ozone dosage increases, more HO• radicals are formed. Under UV irradiation, H<sub>2</sub>O<sub>2</sub> can be formed through the reaction of ozone with H<sub>2</sub>O (Equation (8)). Furthermore, this H<sub>2</sub>O<sub>2</sub> molecule absorbs the UV light to generate the HO• radicals (Equation (9)) [24]. Ozone molecules also can react with H<sub>2</sub>O<sub>2</sub> molecules to produce HO• radicals. Besides, the ozone also can directly react with H<sub>2</sub>O to generate HO• radicals (Equation (7)). Then, Cu is oxidized by HO• radicals. Therefore, the photochemical oxidation rate of Cu increases with the increase in ozone dosage. As a comparison, Wang et al. [33] reported that the decomplexation of electroplating wastewater by the ozone-based oxidation process increased with the increase in ozone dosage. Ren et al. [24] reported that the removal efficiency of polyacrylamide through the photochemical oxidation process increased with the increase in ozone dosage. Guo et al. [34] also reported the same result in the degradation process of sulfadiazine in water by the UV-Ozone process.

### 3.3.3. Effect of UV Irradiation Intensity

In order to study the effect of UV irradiation intensity on Cu removal from electroplating wastewater, the photochemical process was conducted by varying the UV irradiation intensity. The UV irradiation intensity was varied at 20, 40, and 60 mW/cm<sup>2</sup>. Figure 7 shows the result of the effect of UV irradiation intensity on Cu removal efficiency.

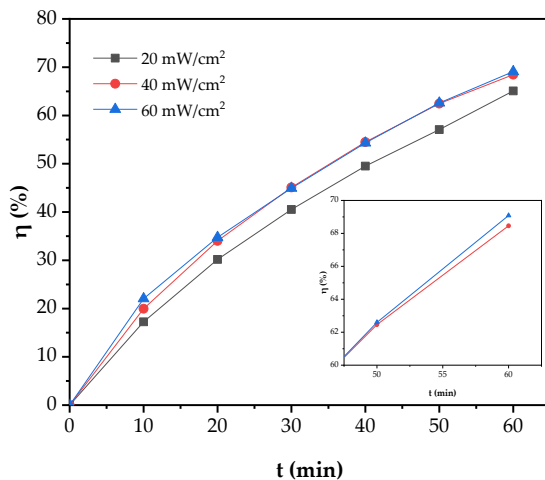


Figure 7. Effect of UV irradiation intensity on Cu removal efficiency through photochemical process.

As shown in Figure 7, at 60 min reaction, the Cu removal efficiency obtained at a UV irradiation intensity of 20 mW/cm<sup>2</sup> is 65.09%, the Cu removal efficiency obtained at UV irradiation intensity of 40 mW/cm<sup>2</sup> is 68.46%, while the Cu removal efficiency obtained at UV irradiation intensity of 60 mW/cm<sup>2</sup> is 69.08%. It can be concluded that the Cu photochemical oxidation rate slightly increases with the increase in UV radiation intensity. The Cu removal efficiency slightly increases for UV irradiation of

20–40 mW/cm<sup>2</sup>. Furthermore, the Cu removal efficiency remains unchanged for UV irradiation intensity of 40–60 mW/cm<sup>2</sup>.

The increase in Cu removal efficiency with the increase in UV irradiation intensity is due to the high possibility to produce HO• radicals at high UV irradiation intensity. The possible process of HO• radical formation during UV irradiation is the photolytic dissociation of water by UV irradiation at a wavelength of 254 nm [35]. However, this process is still unclear since some studies reported that the photolytic dissociation of water to HO• radicals only can be conducted at a wavelength of less than 242 nm. Deng and Zhao [12] claimed that this process occurs at a wavelength of less than 242 nm. Furthermore, Jin et al. [22] reported that the HO• radicals could be formed through irradiation on liquid water by UV light in the range of 150–200 nm. As the UV irradiation wavelength used in this study is around 253.7 nm, the increase in Cu removal efficiency with the increase in UV irradiation intensity from 20 to 40 mW/cm<sup>2</sup> is attributed to the formation of HO• radicals through ozone photolysis producing H<sub>2</sub>O<sub>2</sub> (Equation (8)). However, high UV irradiation intensity in the ozonation process is not good. It is true since, at high UV irradiation intensity, the ozone molecule could be degraded to oxygen [36]. Therefore, the formation of HO• radicals is low at high UV irradiation intensity. Furthermore, it is suggested that the unchanged Cu removal efficiency at a UV irradiation intensity of 60 mW/cm<sup>2</sup> is due to the degradation of the ozone molecule resulting in the low formation of HO• radicals.

### 3.3.4. Effect of pH

The efficiency of AOP can be influenced by various factors, such as the pH of the solution [37–39]. In order to study the effect of pH on the Cu removal process from electroplating wastewater through the photochemical oxidation process, the pH of solution was varied at 3, 6, 8, and 10. The result is depicted in Figure 8.

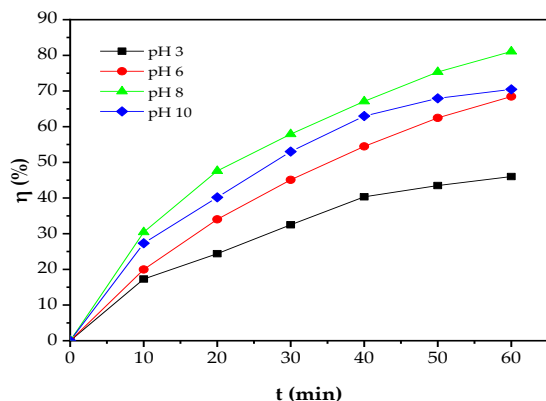


Figure 8. Effect of pH on Cu removal efficiency through photochemical process.

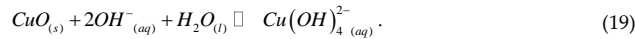
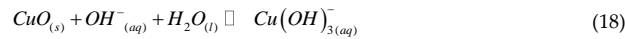
As can be seen in Figure 8, at 60 min reaction, the Cu removal efficiency obtained at pH of 3 is 46.02%, the Cu removal efficiency obtained at pH of 6 is 68.46%, the Cu removal efficiency obtained at pH of 8 is 80.09%, while the Cu removal efficiency obtained at pH of 10 is 70.46%. It can be seen that the highest Cu removal efficiency is obtained at a pH of 8. Hence, it can be concluded that the photochemical oxidation of Cu from electroplating wastewater increases with the increase in pH from 3 to 8, then it decreases with a further increase in pH to 10.

The increase in Cu removal efficiency with the increase in pH value is attributed to the high rate of HO• radical formation at high pH conditions. As reported by Muniyasamy et al. [39], in the oxidation process, pH influences the process by altering the chemical nature of ozone. At low pH conditions (acidic conditions), the decomposition of the ozone molecule to produce HO• radicals is relatively slow [40]. It was reported that the decomposition rate of ozone was sluggish below the pH of 4 [41].

Furthermore, ozone tends to remain in the molecular state at acidic conditions; however, ozone can react directly as ozone radical with the contaminants at alkaline conditions [38,42]. Therefore, the Cu removal efficiency is low at a low pH value. Furthermore, the higher the pH value, the higher the Cu removal efficiency. This tendency is attributed to the high formation of HO• radicals at the alkaline conditions. It was reported that the decomposition rate of ozone in water is better at higher pH values [43]. At alkaline conditions, ozone is unstable and rapidly decomposes into HO• radical [39,40]. The HO• radical formation through ozone decomposition occurs as follows:



As can be seen in Equations (16) and (17), the HO• radical, which is the primary oxidant in indirect oxidation [39], is produced at high pH level represented as OH<sup>-</sup>. Therefore, the Cu removal efficiency increases with the increase in pH value since the HO• radical formation is favored at a high pH level. However, the Cu removal efficiency decrease at a pH of 10. At higher pH value, CuO can dissolve to the aqueous phase due to the formation of soluble hydroxy and hydroxide complexes [44]. Therefore, Cu removal efficiency decreases. The possible dissolution mechanism of CuO at high pH value was proposed by Khan et al. [44] as follows:



### 3.4. Kinetic Study

#### 3.4.1. Determination of the Kinetic Rate Order

Three classical kinetic models are proposed to describe the Cu removal process and to determine the order or kinetic rate. These kinetic models include first-order model, second-order model, and pseudo-first-order model. The compatibility of these models is evaluated by the R<sup>2</sup> value as reported elsewhere [45]. In this work, the kinetic study of Cu removal from electroplating wastewater is considered for various initial Cu concentration ( $C_0$ ), ozone dosage ( $C_{os}$ ), UV irradiation intensity ( $I_{uv}$ ), and initial pH condition.

In this advanced oxidation process for Cu removal from electroplating wastewater, the mass conservation of Cu in the process can be generally expressed as:

$$-\frac{dC_t}{dt} = (-r), \quad (20)$$

where  $C_t$  (mg/L) is the concentration of Cu at time  $t$  (min) and  $(-r)$  (mg/L.min) is the rate of Cu removal. For first order model ( $-r = k_1 C_t$ ), integration of Equation (20) at the initial concentration of  $C_0$ , gives:

$$-\ln\left(\frac{C_t}{C_0}\right) = k_1 t, \quad (21)$$

where  $k_1$  (1/min) is the kinetic rate constant for first order. Further simplification of Equation (21) will give the time-dependent concentration of Cu (Equation (22)).

$$C_t = C_0 e^{-k_1 t}. \quad (22)$$

For second-order model ( $-r = k_2 C_t^2$ ), the integration of Equation (20) will give:

$$\frac{1}{C_t} = k_2 t + \frac{1}{C_0}, \quad (23)$$

where  $k_2$  (L/mg.min) is the kinetic rate constant of the second-order model. For the pseudo-first-order model ( $-r = k_p(C_t - C_e)$ ), the time-dependent concentration of Cu through the integration of Equation (20) is obtained as:

$$C_t = C_e + (C_0 - C_e)e^{-k_p t}, \quad (24)$$

where  $C_e$  (mg/L) is the concentration of Cu at equilibrium condition and  $k_p$  (1/min) is the kinetic rate constant of pseudo-first-order model.

The kinetic parameters were determined using the least-square method. As can be seen, the obtained equation for first-order and second-order kinetic models (Equations (21) and (23)) are linear equations. Therefore, the kinetic parameters ( $k_1$  and  $k_2$ ) can be obtained from the linear plot relating to these equations using the linear regression method. However, the equation derived from the pseudo-first-order kinetic model is not linear. Therefore, the kinetic parameters of the pseudo-first-order kinetic model ( $C_e$  and  $k_p$ ) are calculated using a nonlinear regression method. On the other hand, to measure the goodness of the kinetic models proposed, the squared-correlation coefficient,  $R^2$ , was used as the parameter [40,41]. The obtained kinetic parameters and  $R^2$  values for first-order, second-order, and pseudo-first-order kinetic models are shown in Table 1.

As can be seen in Table 1, all proposed models fit the data as the  $R^2$  values are close to unity. However, compared to the other proposed models, the  $R^2$  value of the second-order model is far enough from unity. Besides, the values of  $R^2$  obtained are not uniform for all data. Therefore, it is suggested that the second-order model is excluded as the proposed model to describe the kinetic rate of Cu removal. Hence, the first order and pseudo-first-order models are then considered as the most suitable proposed models to describe the kinetics of Cu removal. Considering the  $R^2$  values of the first order and pseudo-first-order models, both these two models have high goodness in describing the kinetic rate of Cu removal. However, at the initial Cu concentration,  $C_0$ , of 145.73 and 72.86 mg/L, the value of the equilibrium concentrations,  $C_e$ , obtained are zero. It indicates that at a high initial concentration of Cu in the wastewater, the kinetic rate will be increased. Furthermore, some of the  $C_e$  values are relatively low. In some cases, the theoretical value of  $C_e$  might be negative when the pseudo-first-order kinetic model is forcibly used [46]. In those cases, the pseudo-first-order model cannot be used to describe the kinetic rate. Obviously, if the value of the equilibrium concentration is zero or low enough, the pseudo-first-order model gets back to the first-order model [45,46]. Therefore, it is suggested that the most suitable model to describe the kinetic rate of Cu removal from electroplating wastewater through the photochemical oxidation process, combined UV-Ozone process, is the first-order model.

**Table 8.** Kinetic parameters of the first order, second-order, and pseudo-first-order models.

$C_0$ (mg/L)	$C_{O_3}$ (mg/h)	$I_{UV}$ (mW/cm <sup>2</sup> )	pH	Kinetic Parameters						
				First-Order		Second-Order		Pseudo-First-Order		
				$k_1$ (1/min)	$R^2$	$k_2$ (L/mg.min)	$R^2$	$k_p$ (1/min)	$C_e$ (mg/L)	$R^2$
145.73	10	40	6	0.0069	0.9997	$5.673 \times 10^{-5}$	0.9921	0.0069	0.000	0.9994
72.86	10	40	6	0.0128	0.9993	$2.451 \times 10^{-4}$	0.9678	0.0127	0.000	0.9983
36.9	10	40	6	0.0196	0.9995	$8.898 \times 10^{-4}$	0.9707	0.0237	3.769	0.9995
36.9	5	40	6	0.0111	0.9998	$3.972 \times 10^{-4}$	0.9875	0.0116	1.223	0.9993
36.9	15	40	6	0.0267	0.9959	$1.480 \times 10^{-3}$	0.9624	0.0395	5.528	0.9979
36.9	10	20	6	0.0173	0.9996	$7.407 \times 10^{-4}$	0.9609	0.0188	1.850	0.9990
36.9	10	60	6	0.0198	0.9989	$9.031 \times 10^{-4}$	0.9654	0.0252	4.663	0.9969
36.9	10	40	3	0.0116	0.9847	$4.160 \times 10^{-4}$	0.9790	0.0330	12.126	0.9940
36.9	10	40	8	0.0282	0.9980	$1.650 \times 10^{-3}$	0.9359	0.0376	4.170	0.9962
36.9	10	40	10	0.0226	0.9904	$1.100 \times 10^{-3}$	0.9909	0.0381	7.725	0.9970

The kinetic study of Cu removal using an advanced oxidation process has been widely reported. However, the kinetic study of Cu removal using the photochemical oxidation process, UV-Ozone process, is still limited. The most-reported process is the electrochemical/electrocoagulation process. Al-Shannag et al. [45] reported that the electrocoagulation of heavy metals from wastewater, including Cu, followed a pseudo-first-order model. Using the same method, Vasudevan and Lakshmi [47] reported that the electrocoagulation of Cu from water follows the second-order model. Furthermore, Khattab et al. [48] reported that Cu removal through the electrochemical process follows the first-order kinetic model.

### 3.4.2. The Effect of Operating Parameters on Kinetic Rate Constant

The kinetic rate behavior of Cu removal using the photochemical oxidation process, combined UV-Ozone process, follows the first-order kinetic model as reported in Section 3.3.1. The value of the kinetic rate constant of the first-order model,  $k_1$ , is presented in Table 1. As can be observed, the value of  $k_1$  is varied as the variation of operating parameters, including  $C_0$ ,  $C_{O_3}$ ,  $I_{UV}$ , and pH. The value of  $k_1$  increases with a decrease in  $C_0$ . Furthermore, the value of  $k_1$  increases with the increase in  $C_{O_3}$ ,  $I_{UV}$ , and pH. However, at a pH of 10, the value of  $k_1$  decreases. These phenomena indicate that the value of the observed  $k_1$  is affected by the operating parameters. This is in accordance with some previous studies that the kinetic rate constant of the advanced oxidation process, especially the UV-Ozone process, is affected by the operating parameters [24,49]. The operating parameters-dependent of the kinetic rate constant can be mathematically written as Equations (25) and (26) where  $\varepsilon$  is the pre-exponent constant, whereas  $a$ ,  $b$ ,  $c$ , and  $d$  are the exponent constant characteristic of  $C_0$ ,  $C_{O_3}$ ,  $I_{UV}$ , and pH, respectively. The linear form of Equation (26) is shown as Equation (27).

$$k_1 = f(C_0, C_{O_3}, I_{UV}, pH) \quad (25)$$

$$k_1 = \varepsilon C_0^a C_{O_3}^b I_{UV}^c pH^d \quad (26)$$

$$\ln k_1 = \ln \varepsilon + a \ln C_0 + b \ln C_{O_3} + c \ln I_{UV} + d \ln pH \quad (27)$$

Based on Equation (27), the value of  $\varepsilon$ ,  $a$ ,  $b$ ,  $c$ , and  $d$  can be obtained using multiple regression analysis which also has been used elsewhere [49]. However, the value of  $k_1$  at a pH of 10 is not included in this calculation because it does not follow the tendency. Table 2 shows the result of the multiple regression analysis. As can be seen, the  $p$ -value of the coefficients obtained for each parameter is lower than 0.05. This indicates that the coefficients obtained are significant. However, the  $p$ -value of  $\ln I_{UV}$  coefficient is higher than 0.05, which indicates that this coefficient is not significant. Table 3 shows the result of the analysis of variance (ANOVA) of the multiple regression analysis. As can be observed, the value of multiple R,  $R^2$ , and adjusted  $R^2$  is close to unity. These indicate that the obtained regression equation fits the data. Furthermore, the obtained  $F$ -value (113.4928) is higher than the  $F$ -table or theoretical  $F$ -value. The theoretical  $F$ -value ( $F_{0.05(4,7)}$ ) is 6.09.

Table 2. Multiple regression analysis result.

Parameters	Coefficients	Standard Error	$p$ -value
Intercept	-5.1661	0.3951	$3.5663 \times 10^{-6}$
$\ln C_0$	-0.7401	0.0441	$6.4919 \times 10^{-7}$
$\ln C_{O_3}$	0.8154	0.0778	$1.5626 \times 10^{-5}$
$\ln I_{UV}$	0.1441	0.0778	0.1064
$\ln pH$	0.8407	0.0839	$2.1105 \times 10^{-5}$

**Table 3.** Summary of the analysis of variance (ANOVA).

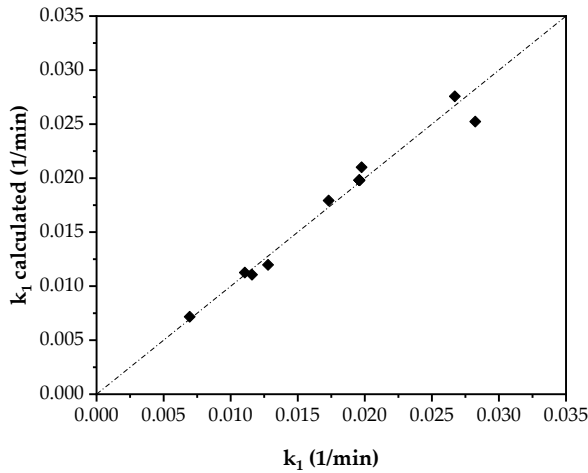
	<i>df</i>	<i>SS</i>	<i>MS</i>	<i>F</i>	<i>Significance F</i>
Regression	4	1.7467	0.4367	113.4928	$1.9188 \times 10^{-6}$
Residual	7	0.0269	0.0038		
Total	11	1.7736			
Multiple R	0.9924				
R <sup>2</sup>	0.9848				
Adjusted R <sup>2</sup>	0.9761				
Standard error	0.0620				

Based on the result of the multiple regression analysis (Table 2), Equation (27) can be rewritten as Equation (28). Furthermore, Equation (26) can be rewritten as Equation (29) with the value of  $\varepsilon$  constant calculated from the natural exponential of the intercept of Equation (28). The obtained value of  $k_t$  was then compared to the calculated value of  $k_t$  using Equation (29). The comparison of the observed  $k_t$  and calculated  $k_t$  is depicted in Figure 9. It is clear that the observed and calculated values of  $k_t$  are in good fit as the R<sup>2</sup> is close to unity (0.9848). By combining the Equations (1), (22), and (29), the calculated Cu removal efficiency can be rewritten as Equation (30). Furthermore, the comparison of the Cu removal efficiency between the observed value and the calculated value is also depicted in Figure 10.

$$\ln k_t = -5.1661 - 0.7401 \ln C_0 + 0.8154 \ln C_{O_2} + 0.1441 \ln I_{UV} + 0.8407 \ln pH \quad (28)$$

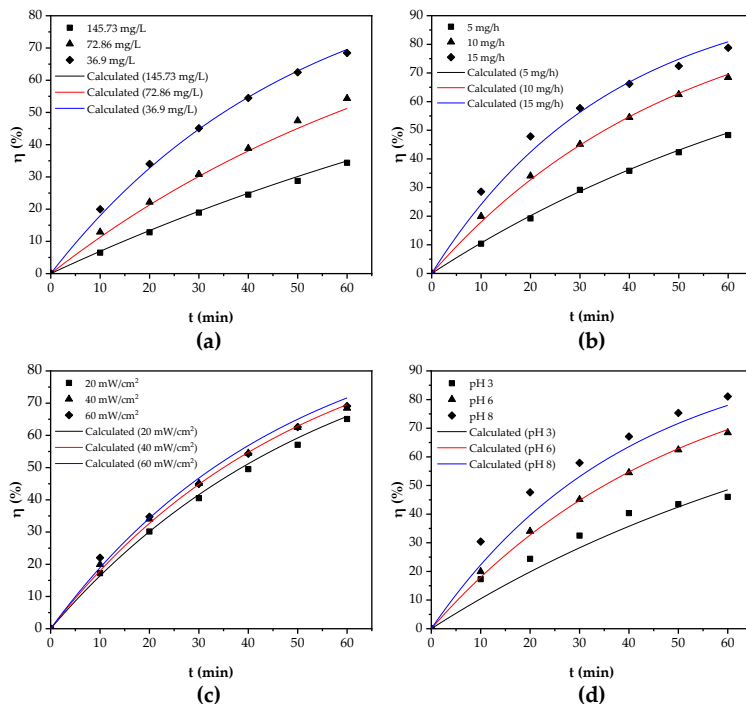
$$k_t = (5.7068 \times 10^{-3}) C_0^{-0.7401} C_{O_2}^{0.8154} I_{UV}^{0.1441} pH^{0.8407} \quad (29)$$

$$\eta_{cal} (\%) = 100 - 100 \exp\left(-\left(5.7068 \times 10^{-3}\right) C_0^{-0.7401} C_{O_2}^{0.8154} I_{UV}^{0.1441} pH^{0.8407} t\right). \quad (30)$$



**Figure 9.** Comparison of observed and calculated value of  $k_t$ .





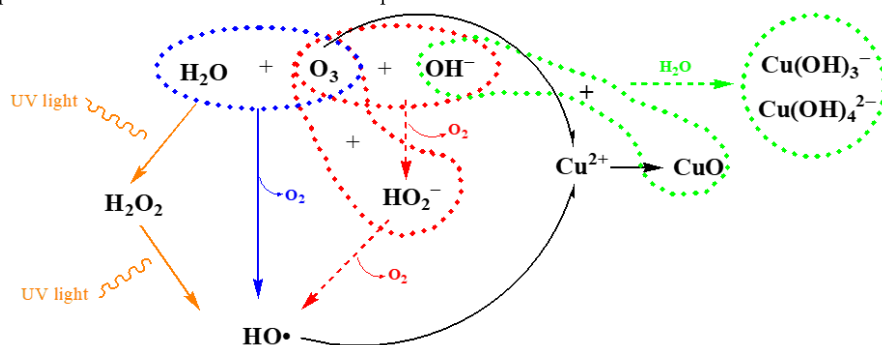
**Figure 240.** Comparison of data and calculated Cu removal efficiency at (a) varied  $C_0$ , (b) varied  $C_{O_3}$ , (c) varied  $I_{UV}$ , and (d) varied pH.

As can be seen in Table 2 and Equation (29), the exponent characteristic value of  $C_0$  is in a negative value. It indicates that the value of the initial Cu concentration is inversely proportional to the  $k_1$  value. This finding is in accordance with the finding of Ren et al. [24]. They reported that the initial concentration of polyacrylamide in the UV-Ozone process of polyacrylamide oxidation is inversely proportional to the kinetic rate constant value. Concerning the effect of UV and ozone treatment in this oxidation process, the value of the exponent characteristic of  $C_{O_3}$  and  $I_{UV}$  can be used to study this matter [49]. As can be seen, the exponent characteristic value of  $C_{O_3}$  is higher than  $I_{UV}$ . It is suggested that the ozone dosage is more significant in this oxidation process than UV irradiation intensity. This finding is in accordance with the previous study of the UV-Ozone process. The UV-Ozone process was conducted for  $\kappa$ -Carrageenan treatment, and the result showed that the ozone dosage was more significant than UV irradiation intensity [49]. Furthermore, the value of the exponent characteristic of  $I_{UV}$  is low enough, and it is close to zero. It indicates that the UV irradiation intensity is not significant enough for the Cu removal process from wastewater. In the case of the effect of pH on  $k_1$  value, it is clear that the pH has a significant effect on  $k_1$  value as the value of the exponent characteristic of pH is high. It is true because the metal oxidation process in an aqueous solution is affected by the presence of  $OH^-$  ions, which can promote the formation of  $HO^\bullet$  radicals. On the other hand, the solubility of metal in aqueous solution is also affected by the pH value [44].

### 3.5. Proposed Mechanism

Based on the explanation in previous sections, the mechanism of Cu removal from electroplating wastewater through the UV-Ozone process is developed. Figure 11 shows the proposed mechanism in

this study. As reported in several studies, the oxidation through AOPs is initiated by the formation of HO• radical because the main oxidating agent is HO• radical [50,51]. Based on several findings obtained in this study (reported in the previous sections), the HO• radical formation takes place through three different steps. In Figure 11, these steps are represented in orange, blue, and red arrows. The orange arrows represent the HO• radical formation through the UV-Ozone process. The blue arrow represents the direct ozonation of water producing HO• radicals releasing O<sub>2</sub> molecules. Furthermore, the red arrows represent the ozone degradation producing HO• radicals in alkaline condition releasing O<sub>2</sub> molecules. The red arrow is depicted in dash-line arrow type, this indicates that this process occurs in alkaline condition only due to the presence of OH<sup>-</sup> ions. At acidic condition, this process does not occur as OH<sup>-</sup> ions are not present.



**Figure 11.** Proposed mechanism of Cu removal from electroplating wastewater through UV-Ozone process.

After the formation of HO• radicals occurred, the next step is the oxidation process. This process, depicted in black arrows, includes direct and indirect oxidation since the oxidating agents in this UV-Ozone process are HO• radicals and ozone molecules. Both HO• radicals and O<sub>3</sub> react with Cu<sup>2+</sup> to form solid CuO. The oxidation process of Cu<sup>2+</sup> to CuO by HO• radicals is called indirect oxidation, whereas the oxidation process of Cu<sup>2+</sup> by O<sub>3</sub> molecules is called direct oxidation. Based on Figure 11, as the HO• radicals and O<sub>3</sub> molecules increase in the system, the CuO product produced increases. It means that the Cu removal from the electroplating wastewater increases. However, this CuO product can dissolve in an alkaline condition. As can be seen in Figure 11, if the OH<sup>-</sup> ions are excessively present in the system, the CuO product will dissolve. This process is depicted as a dash-arrow in green indicating that this process occurs in alkaline condition only due to the presence of excessive OH<sup>-</sup> ions. The dissolution of CuO to the aqueous phase in the alkaline condition is due to the formation of soluble hydroxy and hydroxide complexes [44].

Based on this proposed mechanism (Figure 11), it can be observed that the presence of the ozone molecule is important in this oxidation process. The ozone molecules have roles both to generate the HO• radicals and to oxidize the Cu directly. This is in accordance with the finding reported in Section 3.4 that the ozone dosage significantly affected the kinetic rate. On the other hand, the presence of UV irradiation assists the ozone photolysis process to produce HO• radicals through the formation of an intermediate oxidating agent, H<sub>2</sub>O<sub>2</sub>. Furthermore, the pH is also important in this mechanism. As can be seen in Figure 11, suitable alkaline condition accelerates the formation of HO• radicals. However, the high alkaline condition has a negative effect on the Cu removal process due to the CuO dissolution process in high alkaline condition. The excessive OH<sup>-</sup> ions catch the solid CuO to form soluble hydroxy and hydroxide complexes decreasing the Cu removal efficiency.

#### 4. Conclusions

The photochemical oxidation process of Cu from electroplating wastewater has been investigated. It is shown that the UV-Ozone process has high performance on Cu removal compared to UV and Ozone processes due to the high production rate of HO• radicals as the oxidant and due to the direct oxidation by ozone. Furthermore, this process produced a CuO monoclinic crystal phase as a solid product. The initial Cu concentration, ozone dosage, and pH value have a significant effect on Cu removal efficiency. The initial Cu concentration significantly reduces Cu removal efficiency. As expected, the ozone dosage increases the Cu removal efficiency since it is responsible for HO• radical formation and direct oxidation. Furthermore, the Cu removal efficiency increases with the increase in pH value from 3 to 8. However, a further increase in pH value reduces the Cu removal efficiency due to the formation of soluble hydroxy and hydroxide complexes of Cu at the alkaline conditions. Interestingly, it is found that the UV irradiation intensity is not significant in the photochemical oxidation process on Cu from electroplating wastewater. However, it is responsible to promote the ozone photolysis producing HO• radicals through H<sub>2</sub>O<sub>2</sub> formation. It is found that the kinetic behavior of the photochemical oxidation of Cu follows the first-order kinetic model. Furthermore, the relation between the operating parameters and kinetic rate constant is also established. In addition, the mechanism of Cu removal through the UV-Ozone process was also proposed concerning the findings obtained in this study.

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